

SEARCH REQUEST FORM**Scientific and Technical Information Center**

Requester's Full Name: BETELHEM SHEWAREGE D Examiner #: 75633 Date: 04/07/2005
 Art Unit: 1774 Phone Number 302-1529 Serial Number: 101613,497
 Mail Box and Bldg/Room Location: REM 9D21 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Ink jet recording materials containing siloxane copolymer surfactant.
 Inventors (please provide full names): Tienteh Chen SCIENTIFIC REFERENCE BP
 Sci & Tech Inf. Ctr

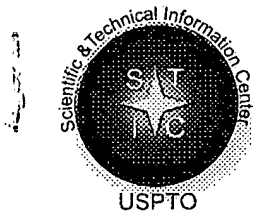
Earliest Priority Filing Date: 07/02/2003 APR 8 RECD

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number. Pat. & T.M. Office

1. Ink jet recording medium containing a nonionic siloxane copolymer surfactant having a structural formula recited in claim 2.
2. Ink jet recording medium containing a nonionic siloxane copolymer surfactant having a structural formula recited in claim 3.

STAFF USE ONLY**Type of Search****Vendors and cost where applicable**

Searcher: <u>Whe</u>	NA Sequence (#) _____	STN <u>8/523.04</u>
Searcher Phone #: _____	AA Sequence (#) _____	Dialog _____
Searcher Location: _____	Structure (#) <u>3</u>	Questel/Orbit _____
Date Searcher Picked Up: <u>4/20/05</u>	Bibliographic _____	Dr. Link _____
Date Completed: <u>4/21/05</u>	Litigation _____	Lexis/Nexis _____
Searcher Prep & Review Time: <u>120</u>	Fulltext _____	Sequence Systems _____
Clerical Prep Time: <u>30</u>	Patent Family _____	WWW/Internet _____
Online Time: <u>120</u>	Other _____	Other (specify) _____



STIC Search Report

EIC 1700

STIC Database Tracking Number: 150230

TO: Betelhem Shewareged

Location: REM 9D21

Art Unit : 1774 10/6/79 dcopy

April 21, 2005

Case Serial Number: 10/613497

From: Usha Shrestha

Location: EIC 1700

REMSEN 4B28

Phone: 571/272-3519

usha.shrestha@uspto.gov

Search Notes



STIC Search Results Feedback Form

EIC17000

Questions about the scope or the results of the search? Contact *the EIC searcher* or contact:

Kathleen Fuller, EIC 1700 Team Leader
571/272-2505 REMSEN 4B28

Voluntary Results Feedback Form

- I am an examiner in Workgroup: Example: 1713
- Relevant prior art **found**, search results used as follows:

- ☐ 102 rejection
- ☐ 103 rejection
- ☐ Cited as being of interest.
- ☐ Helped examiner better understand the invention.
- ☐ Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- ☐ Foreign Patent(s)
- ☐ Non-Patent Literature
(journal articles, conference proceedings, new product announcements etc.)

- Relevant prior art **not found**:

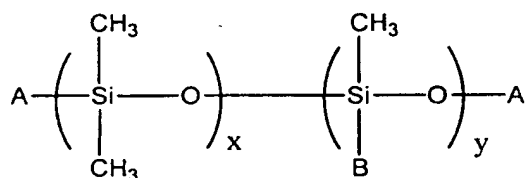
- ☐ Results verified the lack of relevant prior art (helped determine patentability).
- ☐ Results were not useful in determining patentability or understanding the invention.

Comments:

CLAIMS

- 5 1. A print medium comprising an ink-receiving layer and a coated paperbase, the ink-receiving layer comprising a nonionic siloxane copolymer surfactant.

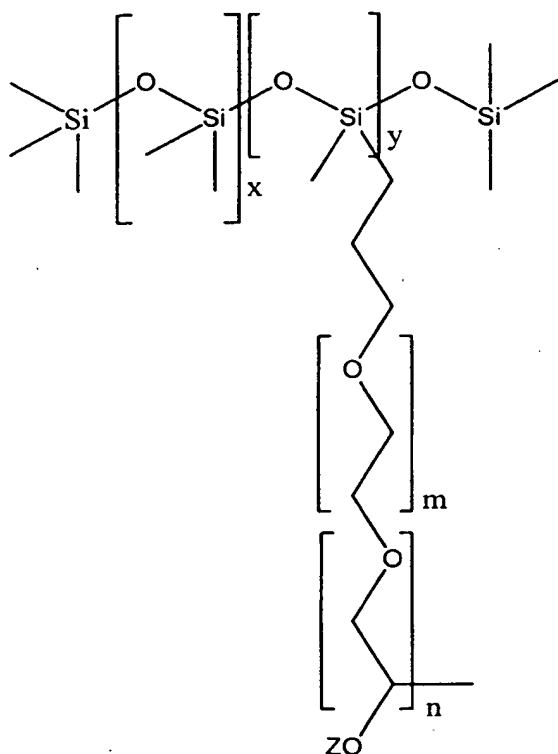
2. The print medium of claim 1, wherein the nonionic siloxane
10 copolymer surfactant comprises the following structure:



wherein A is $-\text{CH}_3$ or B, and B is a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and x and y are such as to provide a molecular weight greater than about 1000.

15

3. The print medium of claim 1, wherein the nonionic siloxane copolymer surfactant comprises the following structure:



wherein m, n, x, and y are such as to provide a molecular weight greater than about 1000, wherein Z is H, $-\text{CH}_3$, or a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and wherein the structure contains at least one polyethyleneoxide group.

4. The print medium of claim 1, wherein the surface tension of the nonionic siloxane copolymer surfactant is from about 20 dyne/cm to about 35 dyne/cm.

5. The print medium of claim 1, wherein the hydrophilic/hydrophobic balance value (HLB) of the nonionic siloxane copolymer surfactant is from about 10 to about 30.

6. The print medium of claim 1, wherein the weight percent (wt %) of the nonionic siloxane copolymer surfactant is from about 0.05 wt % to about 2 wt %.

7. The print medium of claim 1, wherein the nonionic siloxane copolymer surfactant has a molecular weight of greater than about 1000.

8. The print medium of claim 1, wherein the ink-receiving layer further comprises a nonionic or anionic surfactant, wherein the nonionic or anionic surfactant is present in a concentration that is less than the concentration of the nonionic siloxane copolymer surfactant present in the ink-receiving layer.

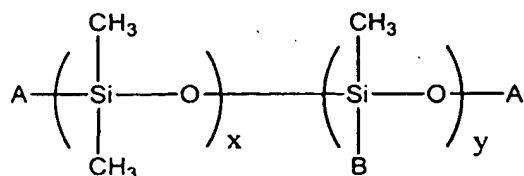
9. The print medium of claim 1, wherein the nonionic siloxane copolymer surfactant comprises at least one polysiloxane-polyethylene oxide compound or at least one polysiloxane-polyethylene oxide-polypropylene oxide compound.

10. The print medium of claim 1, wherein the coated paperbase comprises a coated paper, a cast-coated paper, or a commercial offset paper.

11. A method of forming a print medium having improved image quality and permanence, comprising:

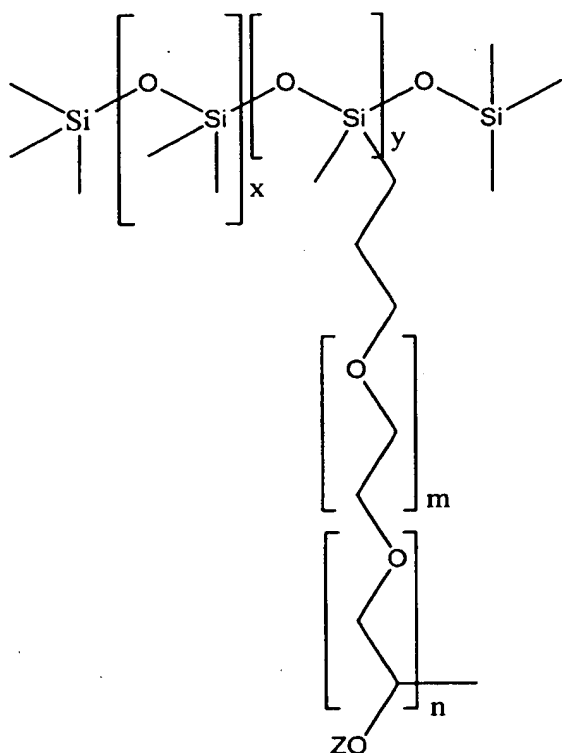
providing a coated paperbase; and
applying an ink-receiving layer to the coated paperbase, the ink-receiving layer comprising a nonionic siloxane copolymer surfactant.

12. The method of claim 11, wherein applying an ink-receiving layer to the coated paperbase comprises applying a surfactant having the following structure:



wherein A is $-\text{CH}_3$ or B, and B is a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and x and y are such as to provide a molecular weight greater than about 1000.

- 5 13. The method of claim 11, wherein applying an ink-receiving layer to the coated paperbase comprises applying a surfactant having the following structure:



- 10 wherein m, n, x, and y are such as to provide a molecular weight greater than about 1000, wherein Z is H, $-\text{CH}_3$, or a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and wherein the structure contains at least one polyethyleneoxide group.

- 15 14. The method of claim 11, wherein applying an ink-receiving layer to the coated paperbase comprises applying a nonionic siloxane copolymer surfactant having a molecular weight of greater than about 1000.

15. The method of claim 11, wherein applying an ink-receiving layer to the coated paperbase comprises applying a nonionic siloxane copolymer surfactant having at least one polysiloxane-polyethylene oxide compound or at least one polysiloxane-polyethylene oxide-polypropylene oxide compound.

5

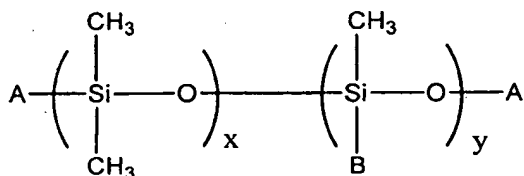
16. A method of printing an image having improved image quality and permanence, comprising:

providing a print medium comprising a coated paperbase and an ink-receiving layer present on the coated paperbase, the ink-receiving layer comprising a nonionic siloxane copolymer surfactant; and printing the image on the print medium.

10

17. The method of claim 16, wherein providing a print medium comprises providing an ink-receiving layer having a surfactant with the following structure:

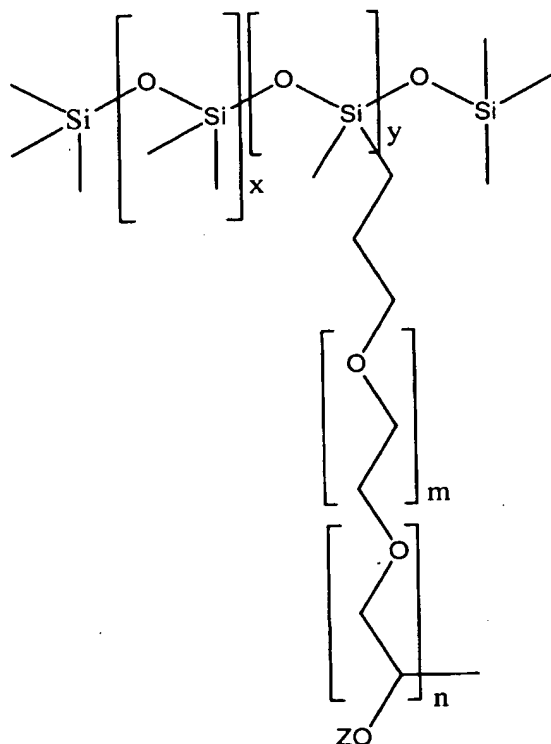
15



wherein A is $-\text{CH}_3$ or B, and B is a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and x and y are such as to provide a molecular weight greater than about 1000.

20

18. The method of claim 16, wherein providing a print medium comprises providing an ink-receiving layer having a surfactant with the following structure:



wherein m, n, x, and y are such as to provide a molecular weight greater than about 1000, wherein Z is H, -CH₃, or a C₁ to C₁₀ straight chain or branched primary or secondary hydroxy terminated alkylene group, and wherein the structure contains at least one polyethyleneoxide group.

19. The method of claim 16, wherein providing a print medium comprises providing an ink-receiving layer having a nonionic siloxane copolymer surfactant with a molecular weight of greater than about 1000.

20. The method of claim 16, wherein providing a print medium comprises providing an ink-receiving layer having at least one polysiloxane-polyethylene oxide compound or at least one polysiloxane-polyethylene oxide-polypropylene oxide compound.

=> fil reg

FILE 'REGISTRY' ENTERED AT 11:08:51 ON 21 APR 2005

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FILE 'HCAPLUS' ENTERED AT 09:24:24 ON 21 APR 2005

L1 1 SEA ABB=ON PLU=ON US20050003112/PN
SEL RN

FILE 'REGISTRY' ENTERED AT 09:24:53 ON 21 APR 2005

L2 10 SEA ABB=ON PLU=ON (107397-59-1/BI OR 110617-70-4/BI
OR 441052-10-4/BI OR 51569-39-2/BI OR 587848-36-0/BI
OR 691397-13-4/BI OR 9002-93-1/BI OR 9005-64-5/BI OR
9005-66-7/BI OR 9014-85-1/BI)

D L2

D L2 1-10 RN STR

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D SCAN

L4 1 SEA ABB=ON PLU=ON 9005-66-7/RN
D SCAN

L5 2 SEA ABB=ON PLU=ON L2 AND SILWET
D L5 1-2 RN STR

L6 1 SEA ABB=ON PLU=ON 587848-36-0/RN
D SCAN

L7 STR

L8 STR

L9 STR

L10 SCR 2043

L11 50 SEA SSS SAM L7 AND L8 AND L9 AND L10
D QUE STAT L11

L12 1429 SEA SSS FUL L7 AND L8 AND L9 AND L10
SAV L12 SHE497/A

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L13 1218 SEA ABB=ON PLU=ON L12

L14 625 SEA ABB=ON PLU=ON L13 (L) TEM?/RL

L15 190 SEA ABB=ON PLU=ON L13 AND PHOTO?/SC, SX
D FHITSTR

L16 7 SEA ABB=ON PLU=ON L15 AND INK? (A) JET?

L17 12 SEA ABB=ON PLU=ON L15 AND INK?
D FHITSTR

L18 12 SEA ABB=ON PLU=ON L16 OR L17

L19 120594 SEA ABB=ON PLU=ON (POLYSILOXANE? OR SILWET? OR

SILOXANE?)/IT

L20 398 SEA ABB=ON PLU=ON L19 AND (DI-ME OR DIMETHYL?) AND
POLYETHYLENE (A) POLYPROPYLENE (A) GLYCOL?

L21 197 SEA ABB=ON PLU=ON L20 AND POLYOXYALKYLEN?

L22 9 SEA ABB=ON PLU=ON L21 AND PHOTO?/SC

L23 9 SEA ABB=ON PLU=ON L21 AND PHOTO?/SC, SX

L24 14 SEA ABB=ON PLU=ON L21 AND INK?

D SCAN TI

L25 5 SEA ABB=ON PLU=ON L21 AND RECORD?

L26 22 SEA ABB=ON PLU=ON L23 OR L24 OR L25

L27 21 SEA ABB=ON PLU=ON L15 AND RECORD?

L28 26 SEA ABB=ON PLU=ON L18 OR L27

L29 48 SEA ABB=ON PLU=ON L26 OR L28

L30 120466 SEA ABB=ON PLU=ON (POLYSILOXANE? OR SILOXANE?)/IT

L31 398 SEA ABB=ON PLU=ON L30 AND (DI-ME OR DIMETHYL? OR
DI (A) METHYL) AND
POLYETHYLENE (A) POLYPROPYLENE (A) GLYCOL?

L32 197 SEA ABB=ON PLU=ON L31 AND POLYOXYALKYLEN?

L33 9 SEA ABB=ON PLU=ON L32 AND PHOTO?/SC, SX

L34 5 SEA ABB=ON PLU=ON L32 AND RECORD?

L35 12 SEA ABB=ON PLU=ON L33 OR L34

L36 1 SEA ABB=ON PLU=ON L35 AND L1

L37 38 SEA ABB=ON PLU=ON L28 OR L35

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FILE HCAPLUS

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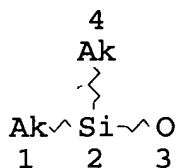
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L7 STR



NODE ATTRIBUTES:

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DEFAULT ECLEVEL IS LIMITED

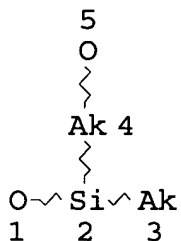
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NUMBER OF NODES IS 4

STEREO ATTRIBUTES: NONE

L8 STR



NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

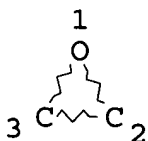
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NUMBER OF NODES IS 5

STEREO ATTRIBUTES: NONE

L9 STR



NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 3

STEREO ATTRIBUTES: NONE

L10 SCR 2043

L12 1429 SEA FILE=REGISTRY SSS FUL L7 AND L8 AND L9 AND L10

L13 1218 SEA FILE=HCAPLUS ABB=ON PLU=ON L12

=> fil hcap

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=> d l37 1-38 ibib abs hitstr hitind

L37 ANSWER 1 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2005:259285 HCAPLUS

DOCUMENT NUMBER: 142:325989

TITLE: **Ink-jet recording
head and ink-jet
recording device**

INVENTOR(S): Kato, Eiichi; Ishizuka, Takahiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: U.S. Pat. Appl. Publ., 50 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
-----	-----	----	-----	-----
-----	-----	----	-----	-----
	US 2005062801	A1	20050324	US 2004-946296
2004				
0922				
	JP 2005096214	A2	20050414	JP 2003-332240

2003

0924

PRIORITY APPLN. INFO.:

JP 2003-332240

A

2003

0924

AB To provide an **ink jet recording** head in which a high **ink** repelling property is kept even against the repeated use and which is excellent in film strength and abrasion resistance and is excellent with respect to printing quality of the resulting image, the **ink-jet recording** head comprises a nozzle having: a hole for discharging a **recording** liquid including an **ink**; and a portion capable of repelling the **ink** at the periphery of the hole, wherein the portion comprises a cured film formed from a composition comprising a block copolymer, and the block

copolymer comprises: a block polymer comprising a fluorine-containing polymer; and a block polymer comprising a repeating unit having a siloxane structure.

IT **848229-99-2DP**, trimethylsilyl ether **848366-82-5P**
(assumed monomers; **ink-jet** printer head
with good abrasion resistance and **ink** repelling)

RN 848229-99-2 HCAPLUS

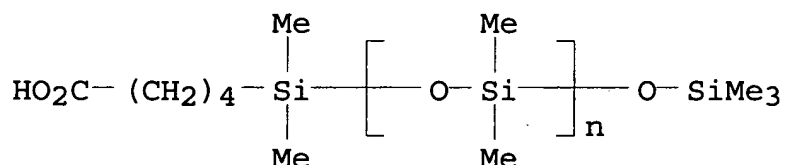
CN INDEX NAME NOT YET ASSIGNED

CM 1

CRN 847200-62-8

CMF (C2 H6 O Si)_n C10 H24 O3 Si2

CCI PMS



CM 2

CM 3

$$\text{CH}_2\text{--O--CH}_2\text{--CH}_2\text{--C}\begin{matrix} \text{CF}_2 \\ || \\ \text{F} \end{matrix}$$

CM 4

$$\begin{array}{c} \text{CF}_2 \\ || \\ \text{F}-\text{C}-\text{CF}_2-\text{CF}_2-\text{O}-\text{C}-\text{F} \\ || \\ \text{CF}_2 \end{array}$$

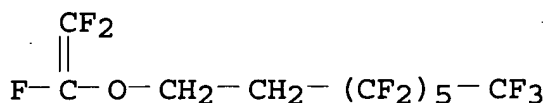
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RN      848366-82-5   HCAPLUS
CN      2-Propenoic acid, 2-methyl-, 3-(nonamethyltetrasiloxanyl)propyl
        ester, polymer with 1,1,2,3,3,4,4,4-octafluoro-1-butene,
        oxiranylmethyl 2-methyl-2-propenoate and
1,1,1,2,2,3,3,4,4,5,5,6,6-
        tridecafluoro-8-[(trifluoroethenyl)oxy]octane, graft (9CI)  (CA
        INDEX NAME)

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CM 1

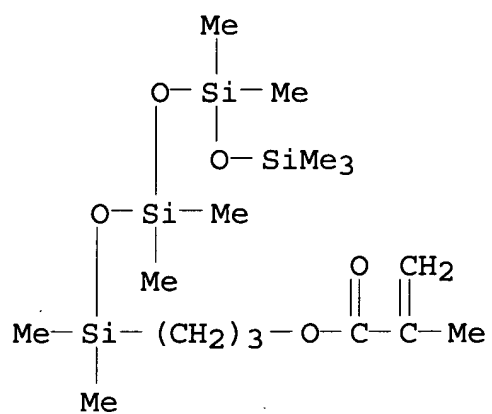
CRN 667457-03-6
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CM 2

CRN 77865-90-8

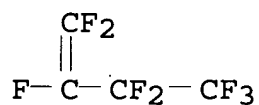
CMF C16 H38 O5 Si4



CM 3

CRN 357-26-6

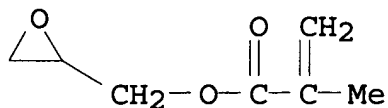
CMF C4 F8



CM 4

CRN 106-91-2

CMF C7 H10 O3

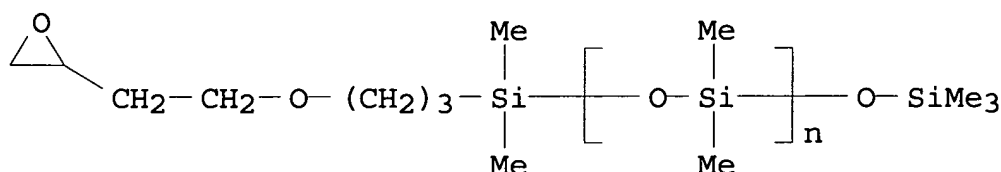


IT 847200-61-7DP, reaction products with graft fluoropolymer
(ink-jet printer head with good abrasion)

resistance and **ink** repelling)

RN 847200-61-7 HCAPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(2-oxiranylethoxy)propyl]silyl]- ω -[(trimethylsilyl)oxy]- (9CI)
(CA INDEX NAME)



IT 658079-18-6P

(repellent liner; **ink-jet** printer head with good abrasion resistance and **ink** repelling)

RN 658079-18-6 HCAPLUS

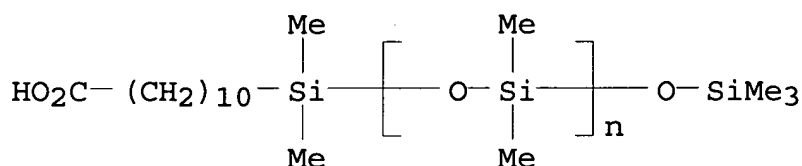
CN Oxirane, [[(2,3,3-trifluoro-2-propenyl)oxy]methyl]-, polymer with 1,1,2,3,3,4,4,4-octafluoro-1-butene, ester α -[(10-carboxydecyl)dimethylsilyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], graft (9CI) (CA INDEX NAME)

CM 1

CRN 188921-66-6

CMF (C2 H6 O Si)n C16 H36 O3 Si2

CCI PMS



CM 2

CRN 658079-17-5

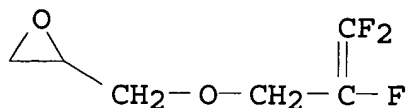
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CCI PMS

CM 3

CRN 658074-78-3

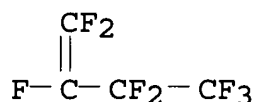
CMF C6 H7 F3 O2



CM 4

CRN 357-26-6

CMF C4 F8



IC ICM B41J002-015
 NCL 347045000
 CC 74-6 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)
 Section cross-reference(s): 38, 42
 ST fluoropolymer siloxane block copolymer **ink** repelling head printer; jet printer head **ink** repelling coating
 IT Polysiloxanes, preparation
 (fluorine-containing, graft block; **ink-jet** printer head with good abrasion resistance and **ink** repelling)
 IT **Ink-jet** printers
 (**ink-jet** printer head with good abrasion resistance and **ink** repelling)
 IT Coating materials
 (linings; **ink-jet** printer head with good abrasion resistance and **ink** repelling)
 IT Fluoropolymers, preparation
 (polysiloxane-, graft block; **ink-jet** printer head with good abrasion resistance and **ink** repelling)
 IT 848229-93-6DP, reaction products with glycidyl-containing polysiloxanes 848229-97-0DP, trimethylsilyl ether **848229-99-2DP**, trimethylsilyl ether 848230-00-2DP, trimethylsilyl ether 848230-13-7P 848230-15-9P 848230-16-0P 848230-18-2P 848230-19-3P 848366-81-4P **848366-82-5P**
 (assumed monomers; **ink-jet** printer head)

with good abrasion resistance and **ink** repelling)
IT 29570-58-9DP, Dipentaerythritol hexaacrylate, crosslinked products
with block graft fluoropolymer-polysiloxanes 60506-81-2DP, Dipentaerythritol pentaacrylate, crosslinked products with block graft fluoropolymer-polysiloxanes 848366-83-6P
(**ink-jet** printer head with good abrasion resistance and **ink** repelling)
IT 106-91-2DP, Glycidyl methacrylate, reaction products with carboxyphenylmethyl-terminated fluoropolymer, graft copolymer with functional siloxane 868-77-9DP, 2-Hydroxyethyl methacrylate, graft copolymer with fluoro macromer and functional siloxane 30674-80-7DP, 2-(Methacryloyloxy)ethyl isocyanate, reaction products with carboxy-terminated fluoropolymer, block graft copolymer with functional siloxanes 111481-56-2DP, graft copolymer with fluoropolymer and methacrylate ester 667457-02-5DP, carboxy-terminated, reaction products with 2-(methacryloyloxy)ethyl isocyanate, graft copolymer with functional siloxanes 667457-04-7DP, carboxyphenylmethyl-terminated, reaction products with glycidyl methacrylate, graft copolymer with functional siloxane and methacrylate 847200-61-7DP, reaction products with graft fluoropolymer 848229-95-8DP, graft copolymers with block fluoropolymers 848230-04-6DP, graft copolymer with fluoro macromer and functional siloxane 848230-08-0DP, graft copolymer with fluoro macromer and methacrylate ester
(**ink-jet** printer head with good abrasion resistance and **ink** repelling)
IT 658079-18-6P
(repellent liner; **ink-jet** printer head with good abrasion resistance and **ink** repelling)

L37 ANSWER 2 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2005:238651 HCAPLUS
DOCUMENT NUMBER: 142:325972
TITLE: Thermal donor for high-speed printing
INVENTOR(S): Foster, David G.; Gray, Maurice L.; Kung, Teh-Ming; York, William M.; Pope, Brian T.
PATENT ASSIGNEE(S): Eastman Kodak Company, USA
SOURCE: U.S. Pat. Appl. Publ., 11 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
US 2005059550	A1	20050317	US 2003-667065
WO 2005032839	A1	20050414	WO 2004-US28455

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW

RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

PRIORITY APPLN. INFO.: US 2003-667065 A

2003

0917

AB A dye-donor element including a dye-donor layer is described, wherein the dye-donor element includes a stick preventative agent (e.g., polysiloxane). The dye-donor element is capable of printing an image on a receiver element at a line speed of 2 ms/line or less while maintaining a print d. of at least two, and a print to fail value of at least four. A print assembly including the dye-donor element and a receiver element is also described, as well as a method of printing using the dye-donor element.

IC ICM B41M005-38

NCL 503227000

CC 74-6 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

- IT **Polysiloxanes**, uses
(3-aminopropyl Me, di-Me, release agent; GP 4, GP 6; release agents for use in thermal donor for high-speed printing with reduced sticking complication)
- IT **Polysiloxanes**, uses
(Dow Corning 18, release agent; Dow Corning 11, GP 5, GP 70S, GP 7200, GP 71S; release agents for use in thermal donor for high-speed printing with reduced sticking complication)
- IT **Polysiloxanes**, uses
(Me stearyl, release agent; PS 130; release agents for use in thermal donor for high-speed printing with reduced sticking complication)
- IT **Polysiloxanes**, uses
(amino, GP-RA 156, release agent; GP 4E, GP 50A, GP-RA 157; release agents for use in thermal donor for high-speed printing with reduced sticking complication)
- IT **Polysiloxanes**, uses
(aminoalkyl, release agent; GP 7100; release agents for use in thermal donor for high-speed printing with reduced sticking complication)
- IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethers with polyethylene-polypropylene glycol mono-Me ether, release agent; Silwet L 7001; release agents for use in thermal donor for high-speed printing with reduced sticking complication)
- IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethoxylated propoxylated, release agent; release agents for use in thermal donor for high-speed printing with reduced sticking complication)
- IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethoxylated, release agent; DBE 224; release agents for use in thermal donor for high-speed printing with reduced sticking complication)
- IT **Polyoxyalkylenes**, uses
(di-Me, Me hydrogen polysiloxane -, release agent; Dow 190; release agents for use in thermal donor for high-speed printing with reduced sticking complication)
- IT **Polysiloxanes**, uses
(di-Me, Me hydrogen, polyoxyalkylene-, release agent; Dow 190; release agents for use in thermal donor for high-speed printing with

- reduced sticking complication)
- IT **Polysiloxanes**, uses
(di-Me, Me trifluoropropyl,
hydroxy-terminated, release agent, PS 187; release agents for
use in thermal donor for high-speed printing with reduced
sticking complication)
- IT **Polysiloxanes**, uses
(epoxy, release agent; GP 32, GP 502; release agents for use
in
thermal donor for high-speed printing with reduced sticking
complication)
- IT **Polysiloxanes**, uses
(fluorine-containing, release agents; release agents for use
in
thermal donor for high-speed printing with reduced sticking
complication)
- IT **Polysiloxanes**, uses
(polyester-, release agent; Byk 371; release agents for use in
thermal donor for high-speed printing with reduced sticking
complication)
- IT **Polyesters**, uses
(**polysiloxane**-, release agent; Byk 371; release
agents for use in thermal donor for high-speed printing with
reduced sticking complication)
- IT **Epoxy resins**, uses
(**polysiloxane**-, release agent; GP 32, GP 502; release
agents for use in thermal donor for high-speed printing with
reduced sticking complication)
- IT **Fluoropolymers**, uses
(**polysiloxane**-, release agents; release agents for
use in thermal donor for high-speed printing with reduced
sticking complication)
- IT 156395-52-7, **Dimethylsilanediol**-methyl-3,3,3-
trifluoropropylsilanediol copolymer
(assumed monomers; release agent; PS 187; release agents for
use in thermal donor for high-speed printing with reduced
sticking complication)
- IT 9002-88-4, Vybar 103 31900-57-9D, **Dimethylsilanediol**
polymer, aminopropyldimethylsilyl-terminated 97917-34-5, PS 513
158421-85-3, GP 501 159791-74-9, GP-134 195889-49-7, S 379N
219997-22-5, Dow Corning 57 568593-97-5, Zonyl FSG
848044-83-7, Dow Corning 163 848045-64-7, Zonyl 9233B
(release agent; release agents for use in thermal donor for
high-speed printing with reduced sticking complication)

L37 ANSWER 3 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2005:33909 HCAPLUS

DOCUMENT NUMBER: 142:123246
TITLE: Holographic **recording** material, its
manufacture, and **recording** method
INVENTOR(S): Sasa, Nobumasa
PATENT ASSIGNEE(S): Konica Minolta Medical & Graphic, Inc., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 24 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
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JP 2005010187	A2	20050113	JP 2003-170646

2003

0616

PRIORITY APPLN. INFO.:

JP 2003-170646

2003

0616

OTHER SOURCE(S): MARPAT 142:123246

AB The material contains (A) photo-image forming composition
containing acationic polymerizable compound and S-containing photo-acid
generatorand (B) an inorg. or organic matrix precursor. The material is
manufactured by mixing A and B, coating the mixture on a
support, andcuring the matrix-forming compds. The material is imagewise
irradiated with actinic ray for holog. image formation. The
material shows high sensitivity, dimensional stability, and high
refractivity contrast.

IT 820232-92-6P

(holog. **recording** material comprising cationic
polymerizable composition and matrix precursor)

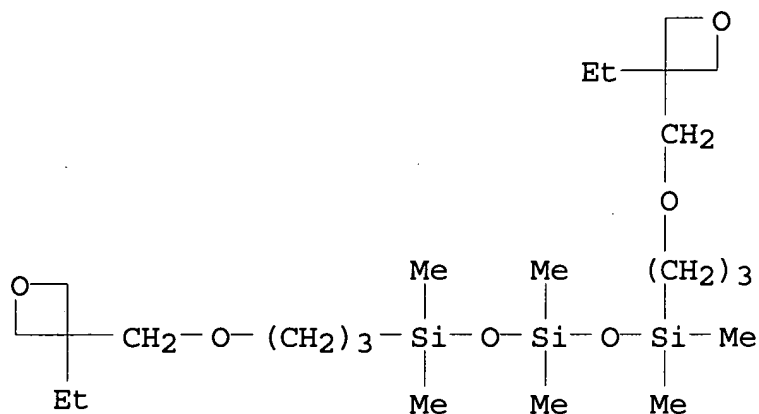
RN 820232-92-6 HCAPLUS

CN 7-Oxabicyclo[4.1.0]heptane-3-carboxylic acid, 7-
oxabicyclo[4.1.0]hept-3-ylmethyl ester, polymer with
1,5-bis[3-[(3-ethyl-3-oxetanyl)methoxy]propyl]-1,1,3,3,5,5-
hexamethyltrisiloxane (9CI) (CA INDEX NAME)

CM 1

CRN 144993-30-6

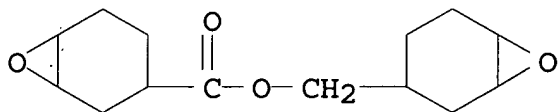
CMF C24 H52 O6 Si3



CM 2

CRN 2386-87-0

CMF C14 H20 O4



IC ICM G03H001-02

ICS G03F007-004; G03F007-032

CC 74-8 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)ST holog **recording** material matrix precursor; cationic polymerizable compn sulfur photoacid generator

IT Polysiloxanes, uses

(Me Ph; holog. **recording** material comprising cationic polymerizable image forming composition and matrix precursor)

IT Polyoxyalkylenes, preparation

(holog. **recording** material comprising cationic polymerizable composition and matrix precursor)IT Holographic **recording** materials

(holog. **recording** material comprising cationic polymerizable image forming composition and matrix precursor)

IT Polyurethanes, preparation
(polyoxyalkylene-, matrix; holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 5551-72-4, NAI 101 823819-47-2, PI 105
(holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 29616-43-1P, Celloxide 3000 120309-91-3P 820232-90-4P
820232-92-6P 820232-93-7P
(holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 9005-12-3, Poly[oxy(methylphenylsilylene)] 31230-04-3,
Poly(Methylphenylsiloxane)
(holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 25322-69-4DP, Polypropylene glycol, copolymers with diisocyanate-terminated polypropylene glycol 25322-69-4DP,
Polypropylene glycol, diisocyanate-terminated, copolymers with polypropylene glycol
(matrix; holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 104558-95-4, Cyracure UVI 6990 205944-57-6, SP 152
(photoacid generator; holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 820232-94-8
(sensitizer; holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

L37 ANSWER 4 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2005:9264 HCAPLUS

DOCUMENT NUMBER: 142:103198

TITLE: Inkjet **recording** materials
containing siloxane copolymer surfactants

INVENTOR(S): Chen, Tienteh

PATENT ASSIGNEE(S): Hewlett-Packard Development Company, L.P.,
USA

SOURCE: Eur. Pat. Appl., 11 pp.
CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			

EP 1493591

A2

20050105

EP 2004-1605

2004

0126

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE,
MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ,
EE, HU, SK

US 2005003112

A1

20050106

US 2003-613497

2003

0702

JP 2005022415

A2

20050127

JP 2004-196255

2004

0702

PRIORITY APPLN. INFO.:

US 2003-613497

A

2003

0702

AB A print medium having improved image quality and permanence. The print medium comprises a coated paper base and an ink-receiving layer. The ink-receiving layer comprises a nonionic siloxane copolymer surfactant. A method of forming the print medium is also disclosed. In addition, a method of printing an image having

improved image quality and permanence is disclosed.

IC ICM B41M005-00

CC 74-6 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)ST ink jet **recording** material siloxane copolymer surfactant

IT Alcohols, uses

(C11-15-secondary, ethoxylated; ink jet **recording** materials containing **siloxane** copolymer surfactants)

IT Polyethers, uses

(**di-Me siloxane**-; ink jet **recording** materials containing **siloxane** copolymer surfactants)

IT **Polysiloxanes**, uses

(**di-Me**, 3-hydroxypropyl Me, ethers with polyethylene glycol mono-Me ether; ink jet **recording**

- materials containing **siloxane** copolymer surfactants)
- IT **Polysiloxanes**, uses
(**di-Me**, 3-hydroxypropyl Me, ethers with
polyethylene-polypropylene glycol
mono-Me ether; ink jet **recording** materials containing
siloxane copolymer surfactants)
- IT **Polysiloxanes**, uses
(**di-Me**, 3-hydroxypropyl Me, ethoxylated
propoxylated; ink jet **recording** materials containing
siloxane copolymer surfactants)
- IT **Polyoxyalkylenes**, uses
(**di-Me**, Me hydrogen **polysiloxane**
-; ink jet **recording** materials containing
siloxane copolymer surfactants)
- IT **Polysiloxanes**, uses
(**di-Me**, Me hydrogen,
polyoxyalkylene-; ink jet **recording** materials
containing **siloxane** copolymer surfactants)
- IT **Polysiloxanes**, uses
(**di-Me**, hydroxy-terminated, ethoxylated
propoxylated; ink jet **recording** materials containing
siloxane copolymer surfactants)
- IT **Polysiloxanes**, uses
(**di-Me**, polyether-; ink jet
recording materials containing **siloxane** copolymer
surfactants)
- IT Ink-jet printing
Surfactants
(ink jet **recording** materials containing **siloxane**
copolymer surfactants)
- IT 9002-93-1, Triton X-405 9005-64-5, Tween 20 9005-66-7, Tween
40 9014-85-1, Surfynol 420 51569-39-2, Olin 10G
107397-59-1,
Tetronic 90R4 110617-70-4, Tetronic 704 441052-10-4, Silwet L
7220 587848-36-0, Silwet L 7650 691397-13-4, Pluronic L44
(ink jet **recording** materials containing **siloxane**
copolymer surfactants)

L37 ANSWER 5 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2004:878586 HCAPLUS

DOCUMENT NUMBER: 141:372733

TITLE: Method for use of polymer coated paper or
board as reusable printing substrate and
printed product

INVENTOR(S): Haakana, Sami Pekka Juhani; Vesanto, Risto

PATENT ASSIGNEE(S): Finnish Chemicals Oy, Finland; Stora Enso Oyj

SOURCE: PCT Int. Appl., 16 pp.

DOCUMENT TYPE: CODEN: PIXXD2
 LANGUAGE: Patent
 FAMILY ACC. NUM. COUNT: English
 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
WO 2004090642	A1	20041021	WO 2004-FI212

2004

0407

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ,
 CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG,
 ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP,
 KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD,
 MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL,
 PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR,
 TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
 RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW,
 AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY,
 CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC,
 NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM,
 GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

FI 2003000541 A 20041011 FI 2003-541

2003

0410

PRIORITY APPLN. INFO.:

FI 2003-541

A

2003

0410

AB The invention relates to a method for using a polymer-coated paper

or board as a printing substrate, to the printed product thus obtained and to the use of the coating. The invention relates to repeated use of the printing substrate, so that the printing ink is removed with a solvent from the surface that has been printed once, and the printing substrate thus cleaned is

used

for reprint. In accordance with the invention, the printing

surface is formed of polysiloxane, to which polyester or styrene acrylate-based toners attach so as to be irremovable by mech. means, yet removable by washing with a suitable solvent, such as acetone, for instance. A polysiloxane-coated paper or board is suitable especially for electro-photog. print with a dry toner, which

can be fixed to the printing surface by fusion.

IT 778624-42-3P

(use of polymer coated paper or board as reusable printing substrate)

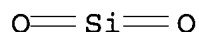
RN 778624-42-3 HCAPLUS

CN Phenol, 4,4'-(1-methylethylidene)bis-, polymer with diethoxymethyl[3-(oxiranylmethoxy)propyl]silane and silica (9CI)
(CA INDEX NAME)

CM 1

CRN 7631-86-9

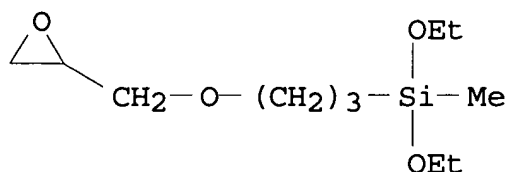
CMF 02 Si



CM 2

CRN 2897-60-1

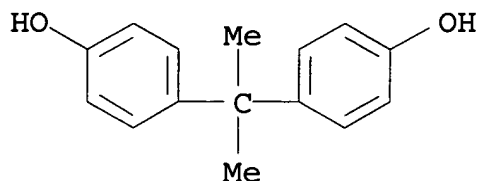
CMF C11 H24 O4 Si



CM 3

CRN 80-05-7

CMF C15 H16 O2



IC ICM G03G005-00
 ICS G03G007-00; B41M005-00; B41M007-00; D21H019-32
 CC 74-3 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38
 IT 778624-40-1P 778624-41-2P **778624-42-3P**
 (use of polymer coated paper or board as reusable printing
 substrate)
 REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE
 FOR THIS RECORD. ALL CITATIONS
 AVAILABLE
 IN THE RE FORMAT

L37 ANSWER 6 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2004:857021 HCAPLUS
 DOCUMENT NUMBER: 141:358156
 TITLE: Holographic **recording** medium and
recording method
 INVENTOR(S): Takeyama, Toshihisa
 PATENT ASSIGNEE(S): Japan
 SOURCE: U.S. Pat. Appl. Publ., 23 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
US 2004202942	A1	20041014	US 2004-815490

2004

0331

PRIORITY APPLN. INFO.:

JP 2003-105006

A

2003

0409

JP 2003-194816 A

2003

0710

OTHER SOURCE(S): MARPAT 141:358156

AB A holog. **recording** contains a first substrate and a second substrate having a holog. **recording** layer between the first substrate and the second substrate, the holog. **recording** layer containing: (A) a binder compound having a reactive group capable of cationic polymerization; (B) a polymerizable compound having an ethylenic double bond in the mol.; (C) a photoinitiator; and (D) a crosslinking agent which reacts with the reactive group in the binder compound, the crosslinking agent being a thermal cationic polymerization initiator. The feature of the present invention is to provide holog. **recording** media having a high sensitivity and a low volume decreasing property, and a holog.

recording method employing the media.

IT 774592-40-4P

(holog. **recording** medium and **recording** method)

RN 774592-40-4 HCAPLUS

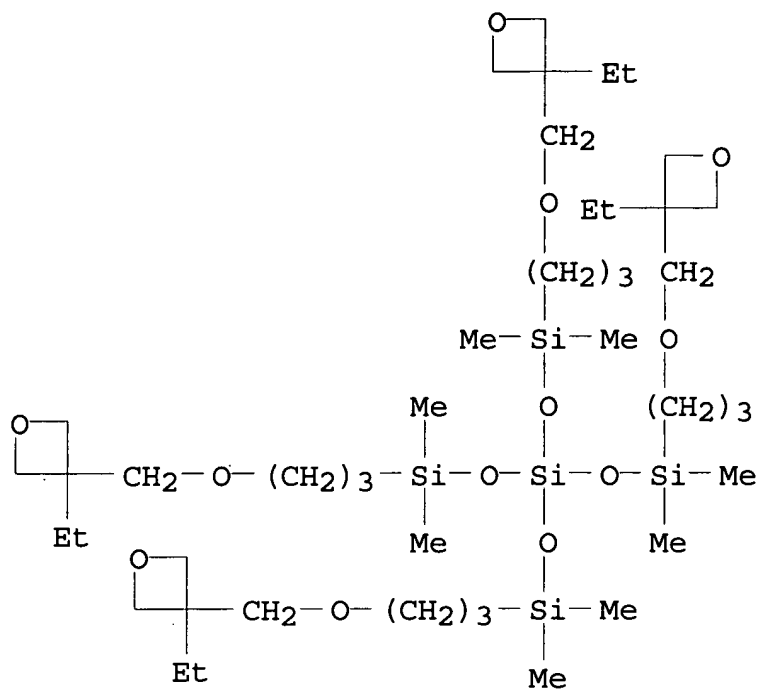
CN Trisiloxane, 1,5-bis[3-[(3-ethyl-3-oxetanyl)methoxy]propyl]-3,3-bis[[[3-[(3-ethyl-3-oxetanyl)methoxy]propyl]dimethylsilyl]oxy]-1,1,5,5-tetramethyl-, polymer with 2,2'-[[2-ethyl-2-

[(oxiranylmethoxy)methyl]-1,3-propanediyl]bis(oxymethylene)]bis[oxirane] and 2,2'-[(1-methylethylidene)bis(4,1-phenyleneoxymethylene)]bis[oxirane] (9CI) (CA INDEX NAME)

CM 1

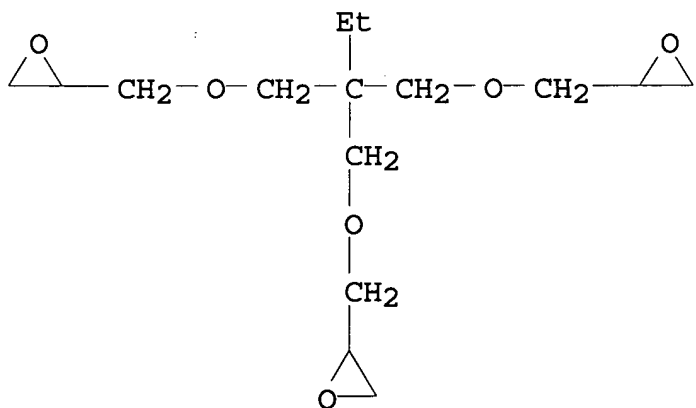
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CMF C44 H92 O12 Si5



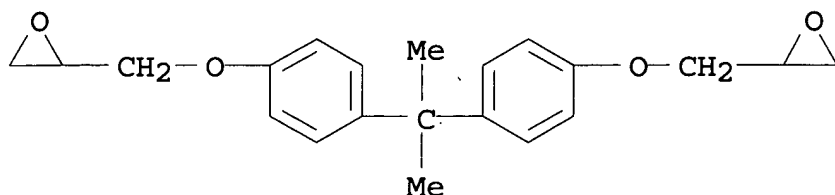
CM 2

CRN 3454-29-3
CMF C15 H26 O6



CM 3

CRN 1675-54-3
CMF C21 H24 O4



IC ICM G03H001-00
NCL 430001000
CC 74-8 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 38
ST holog **recording** medium card
IT Holographic **recording** materials
(holog. **recording** medium and **recording** method)
IT Polyethers, preparation
(holog. **recording** medium and **recording** method)
IT 26142-30-3, Polypropylene glycol diglycidyl ether (Epilight 200P; holog. **recording** medium and **recording** method)
IT 774592-43-7, NK Ester A-CMP 1E
(NK Ester A-CMP 1E; holog. **recording** medium and **recording** method)
IT 64022-15-7, NK Ester A-NP 1E
(NK Ester A-NP 1E; holog. **recording** medium and **recording** method)
IT 7347-19-5, New Frontier BR-31
(New Frontier BR-31; holog. **recording** medium and **recording** method)
IT 67006-39-7, New Frontier BR-42M
(New Frontier BR-42M; holog. **recording** medium and **recording** method)
IT 774592-34-6P 774592-35-7P 774592-36-8P 774592-37-9P
774592-38-0P 774592-39-1P **774592-40-4P** 774592-41-5P,
4-Bromostyrene-4-chlorophenyl acrylate copolymer 774592-42-6P,
4-Bromostyrene-New Frontier BR-31 copolymer 774592-44-8P
774592-45-9P 774592-46-0P 774592-47-1P 774592-48-2P
(holog. **recording** medium and **recording** method)
IT 2039-82-9, 4-Bromostyrene 3047-32-3, 3-Ethyl-3-

hydroxymethyloxetane 3454-29-3, Trimethylolpropane triglycidyl
 ether 3897-65-2, 3-Ethyl-3-(phenoxyethyl)oxetane 13633-87-9,
 4-Chlorophenyl acrylate 24293-30-9 25085-99-8, Epo Tohto YD
 127 32760-80-8 51156-89-9, Tribromophenyl methacrylate
 52794-68-0, Tribromophenyl acrylate 125051-32-3 125662-54-6
 133152-67-7 134507-97-4 134508-03-5 134508-05-7
 135842-78-3 144993-31-7 180423-87-4 186419-14-7
 220666-63-7 300822-65-5 331623-03-1 773058-26-7
 773058-27-8 774592-32-4 774592-33-5 774594-70-6
 (holog. **recording** medium and **recording**
 method)

L37 ANSWER 7 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2004:824978 HCAPLUS
 DOCUMENT NUMBER: 141:340478
 TITLE: Holographic **recording** medium and
recording method
 INVENTOR(S): Takeyama, Toshihisa
 PATENT ASSIGNEE(S): Konica Minolta Holdings, Inc., Japan
 SOURCE: U.S. Pat. Appl. Publ., 21 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
-----	-----	----	-----	-----
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2004	US 2004197670	A1	20041007	US 2004-802143
0316	JP 2004287138	A2	20041014	JP 2003-79523
2003				
0324	WO 2004086151	A1	20041007	WO 2004-JP3684
2004				
0318				

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ,
 CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG,

ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE,
 KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG,
 MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT,
 RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT,
 TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW
 RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW,
 AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY,
 CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC,
 NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM,
 GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

PRIORITY APPLN. INFO.:

JP 2003-79523

A

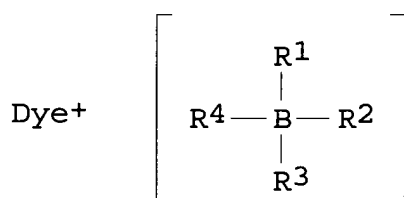
2003

0324

OTHER SOURCE(S):

MARPAT 141:340478

GI



I

AB A holog. **recording** medium having high sensitivity
 comprises a first substrate and a second substrate having a
 holog.

recording layer between the first substrate and the second
 substrate, the holog. **recording** layer containing: (A) a
 binder compound having a reactive group; (B) a polymerizable
 compound
 having an ethylenic double bond; (C) a photoinitiator; and (D) a
 crosslinking agent which reacts with the reactive group in the
 binder compound, wherein the photoinitiator contains a compound
 represented by formula I (Dye+ = cationic dye; R1-R4 = alkyl,
 aryl, aralkyl, alkenyl, alkynyl, heterocyclic, cyano; provided
 that two or more of R1-R4 can form a ring).

IT 771534-35-1P 773091-90-0P 773091-91-1P
 773091-92-2P 773091-93-3P 773091-94-4P
 773091-95-5P 773091-96-6P 773091-97-7P

773091-98-8P 773092-00-5P 773092-01-6P

773092-02-7P 773092-03-8P

(holog. **recording** medium and **recording** method)

RN 771534-35-1 HCAPLUS

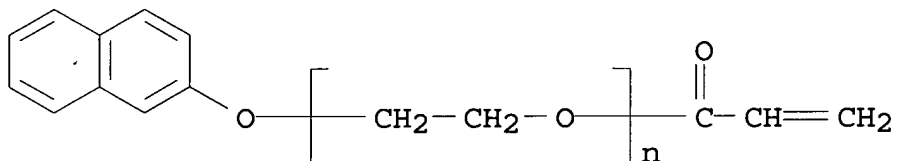
CN Poly[oxy(dimethylsilylene)], α -[[3-(2-hydroxyethoxy)propyl]dimethylsilyl]- ω -[[[3-(2-hydroxyethoxy)propyl]dimethylsilyl]oxy]-, polymer with α, α' -[(1-methylethylidene)di-4,1-phenylene]bis[ω -(oxiranylmethoxy)poly[oxy(methyl-1,2-ethanediyl)]] and α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

CM 1

CRN 286833-74-7

CMF (C2 H4 O)_n C13 H10 O2

CCI PMS

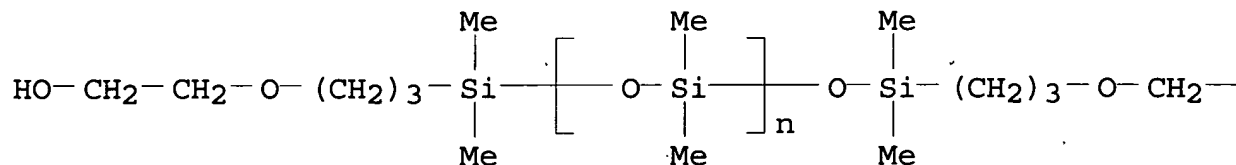


CM 2

CRN 156327-07-0

CMF (C2 H6 O Si)_n C14 H34 O5 Si2

CCI PMS



PAGE 1-A

PAGE 1-B

—CH₂—OH

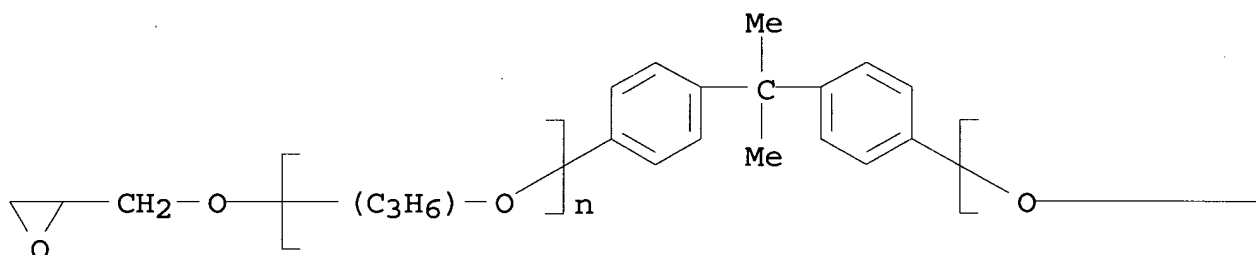
CM 3

CRN 55236-42-5

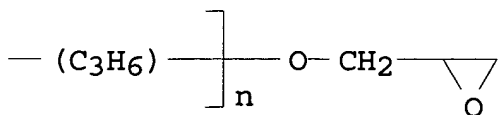
CMF (C₃ H₆ O)_n (C₃ H₆ O)_n C₂₁ H₂₄ O₄

CCI IDS, PMS

PAGE 1-A



PAGE 1-B



RN 773091-90-0 HCAPLUS

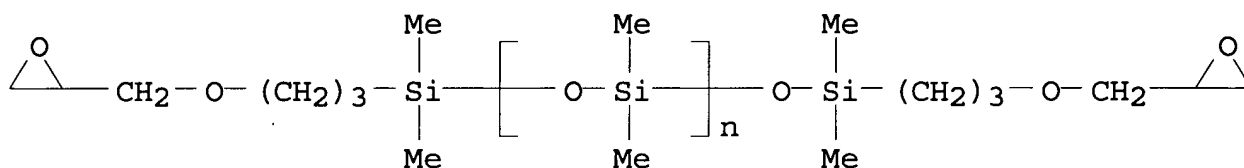
CN 2-Propenoic acid, 4-chlorophenyl ester, polymer with
 2,2-bis[(3-mercapto-1-oxopropoxy)methyl]-1,3-propanediyl
 bis(3-mercaptopropanoate) and α-[dimethyl[3-(oxiranylmethoxy)propyl]silyl]-ω-[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)]
 (9CI) (CA INDEX NAME)

CM 1

CRN 130167-23-6

CMF (C2 H6 O Si)_n C16 H34 O5 Si2

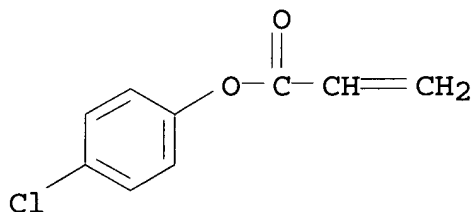
CCI PMS



CM 2

CRN 13633-87-9

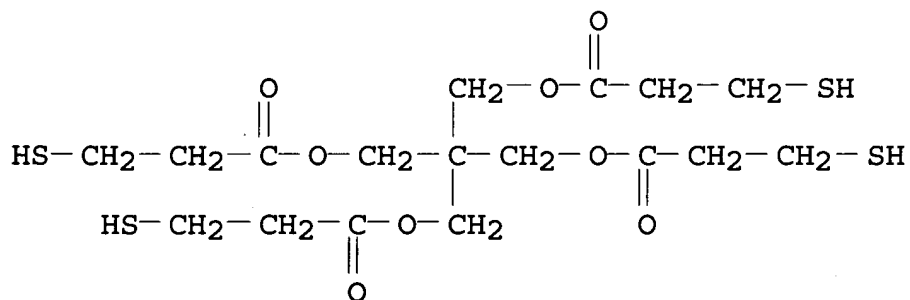
CMF C9 H7 Cl O2



CM 3

CRN 7575-23-7

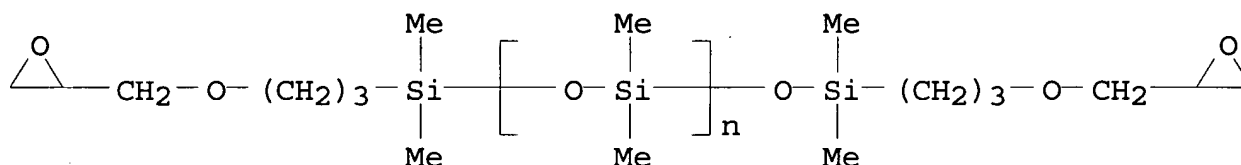
CMF C17 H28 O8 S4



RN 773091-91-1 HCAPLUS
 CN 2-Propenoic acid, 4-chlorophenyl ester, polymer with
 2,2-bis[(3-mercapto-1-oxopropoxy)methyl]-1,3-propanediyl
 bis(3-mercaptopropanoate), α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] and
 α,α' -[(1-methylethylidene)di-4,1-phenylene]bis[ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

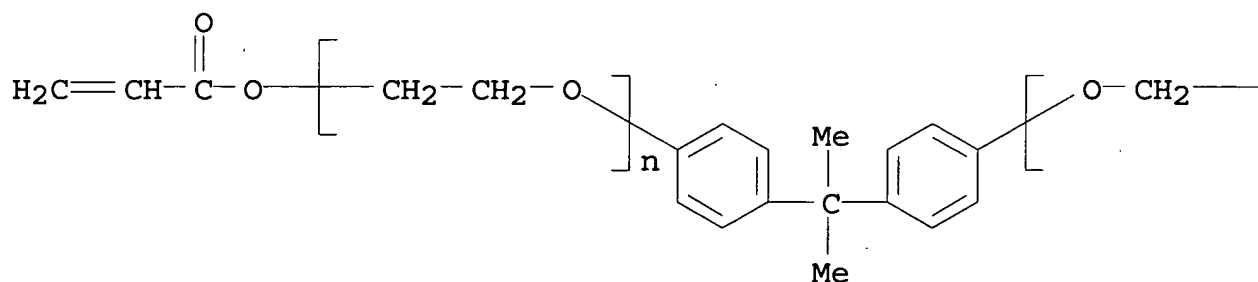
CM 1

CRN 130167-23-6
 CMF (C2 H6 O Si)_n C16 H34 O5 Si2
 CCI PMS



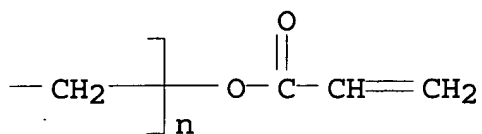
CM 2

CRN 64401-02-1
 CMF (C2 H4 O)_n (C2 H4 O)_n C21 H20 O4
 CCI PMS



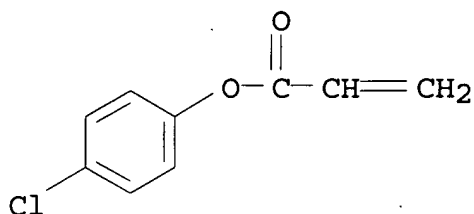
PAGE 1-A

PAGE 1-B



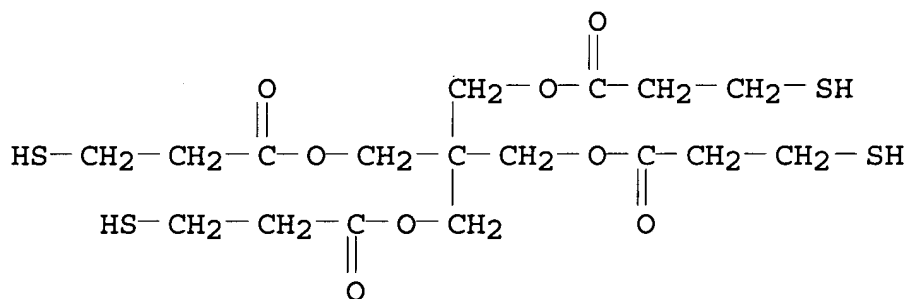
CM 3

CRN 13633-87-9
CMF C9 H7 Cl O2



CM 4

CRN 7575-23-7
CMF C17 H28 O8 S4



RN 773091-92-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[4-(1-methyl-1-phenylethyl)phenoxy]ethyl ester, polymer with 2,2-bis[(3-mercapto-1-oxopropoxy)methyl]-1,3-propanediyl bis(3-mercaptopropanoate) and

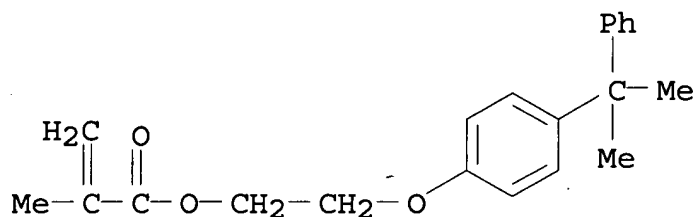
α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -

[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] (9CI) (CA INDEX NAME)

CM 1

CRN 191853-23-3

CMF C21 H24 O3

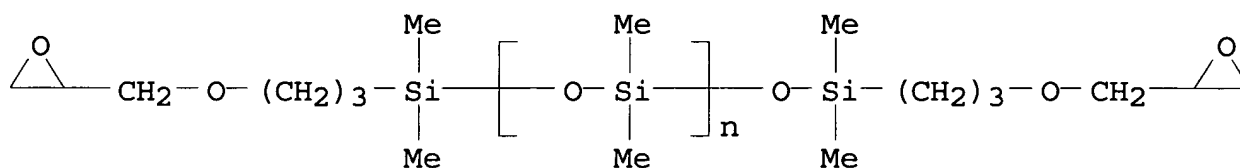


CM 2

CRN 130167-23-6

CMF (C2 H6 O Si)_n C16 H34 O5 Si2

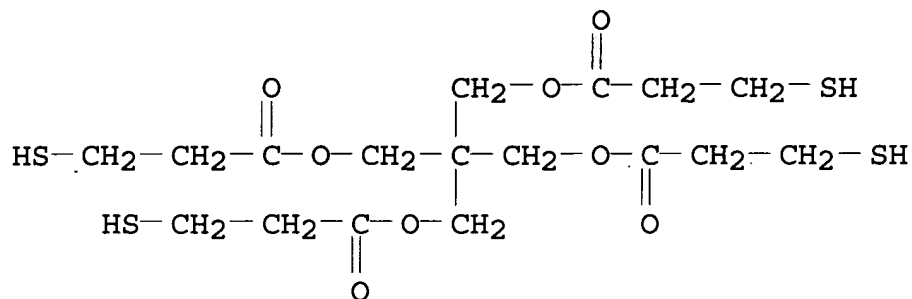
CCI PMS



CM 3

CRN 7575-23-7

CMF C17 H28 O8 S4



RN 773091-93-3 HCAPLUS

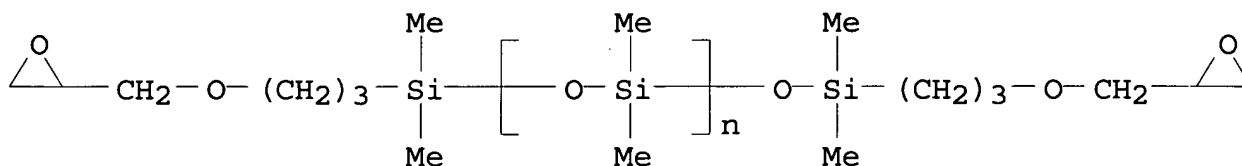
CN 2-Propenoic acid, 2-[4-(1-methyl-1-phenylethyl)phenoxy]ethyl ester, polymer with 2,2-bis[(3-mercapto-1-oxopropoxy)methyl]-1,3-propanediyl bis(3-mercaptopropanoate) and α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] (9CI) (CA INDEX NAME)

CM 1

CRN 130167-23-6

CMF (C2 H6 O Si)_n C16 H34 O5 Si2

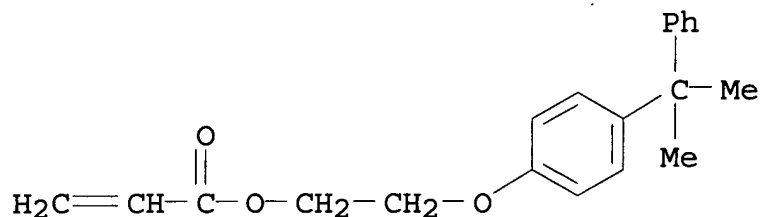
CCI PMS



CM 2

CRN 86148-08-5

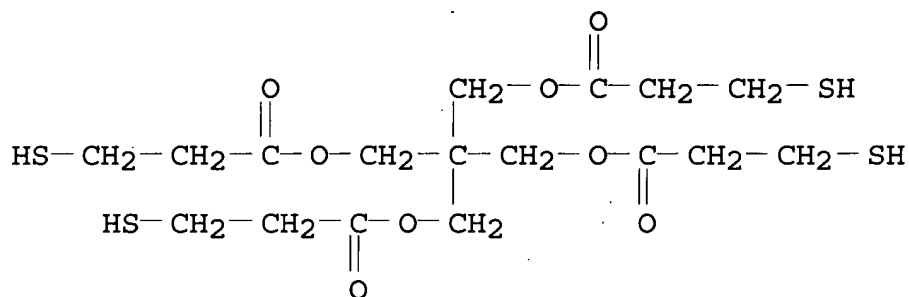
CMF C20 H22 O3



CM 3

CRN 7575-23-7

CMF C17 H28 O8 S4



RN 773091-94-4 HCAPLUS.

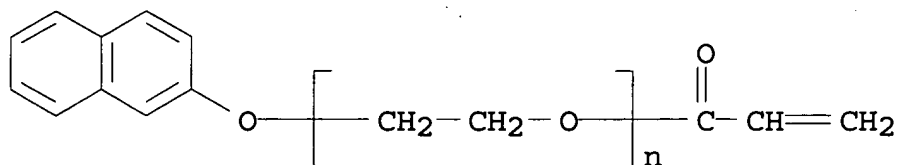
CN 2-Propenoic acid, 2-[4-(1-methyl-1-phenylethyl)phenoxy]ethyl ester, polymer with 2,2-bis[(3-mercaptopropoxy)methyl]-1,3-propanediyl bis(3-mercaptopropanoate), α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] and α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

CM 1

CRN 286833-74-7

CMF (C2 H4 O)_n C13 H10 O2

CCI PMS

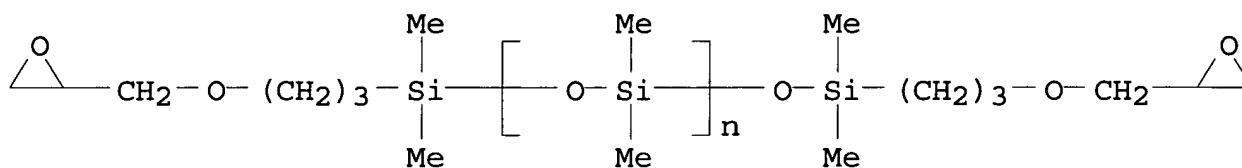


CM 2

CRN 130167-23-6

CMF (C2 H6 O Si)_n C16 H34 O5 Si2

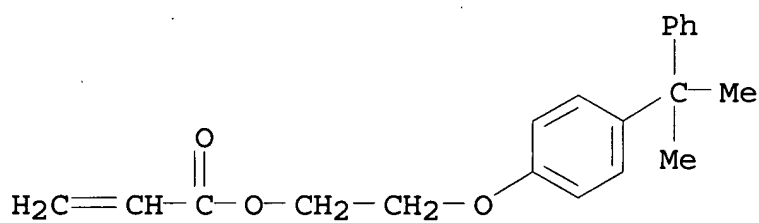
CCI PMS



CM 3

CRN 86148-08-5

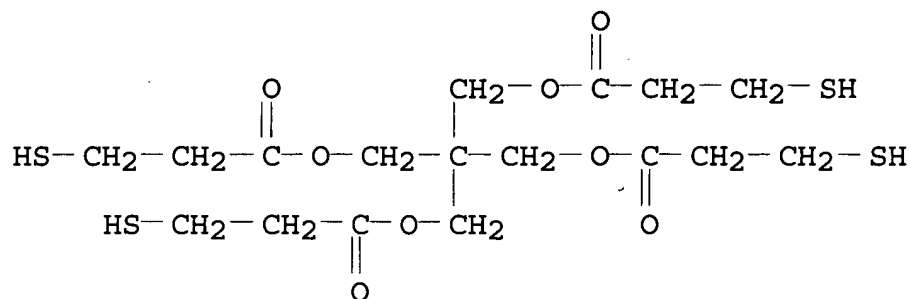
CMF C20 H22 O3



CM 4

CRN 7575-23-7

CMF C17 H28 O8 S4



RN 773091-95-5 HCAPLUS

CN Propanoic acid, 3-mercapto-, 2,2-bis[(3-mercapto-1-oxopropoxy)methyl]-1,3-propanediyl ester, polymer with α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -

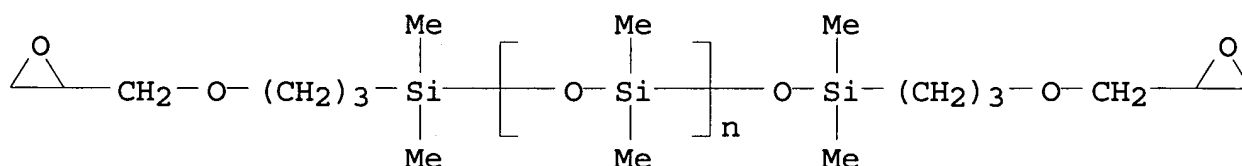
[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] and α -(1-oxo-2-propenyl)- ω -([1,1'-biphenyl]-2-yloxy)poly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

CM 1

CRN 130167-23-6

CMF (C2 H6 O Si)_n C16 H34 O5 Si2

CCI PMS

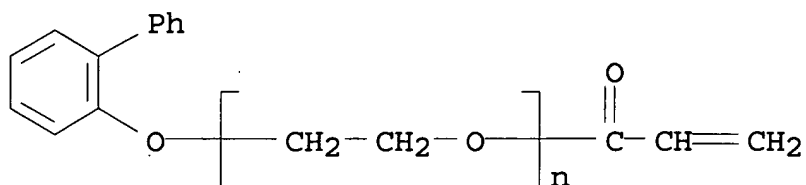


CM 2

CRN 72009-86-0

CMF (C2 H4 O)_n C15 H12 O2

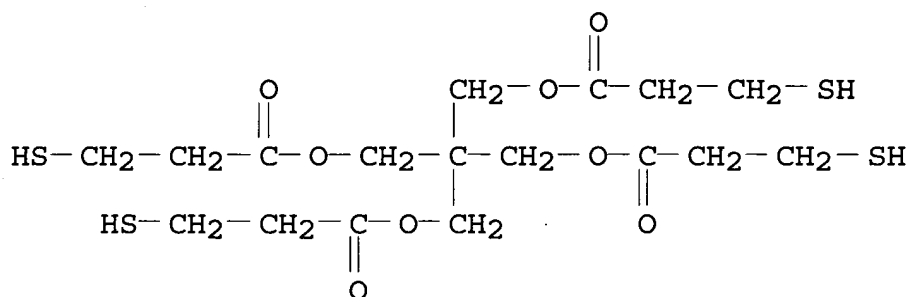
CCI PMS



CM 3

CRN 7575-23-7

CMF C17 H28 O8 S4



RN 773091-96-6 HCAPLUS

CN Propanoic acid, 3-mercapto-, 2,2-bis[(3-mercapto-1-oxopropoxy)methyl]-1,3-propanediyl ester, polymer with α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -

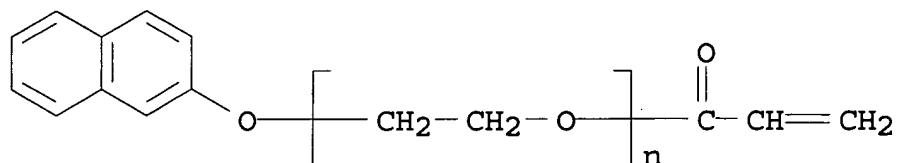
[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] and α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

CM 1

CRN 286833-74-7

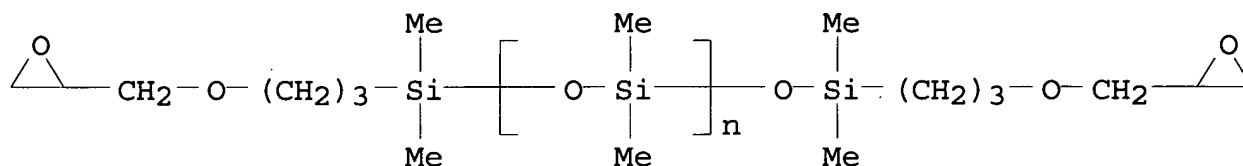
$$\text{CMF} \quad (\text{C}_2 \text{ H}_4 \text{ O})_n \text{ C}_{13} \text{ H}_{10} \text{ O}_2$$

CCI PMS



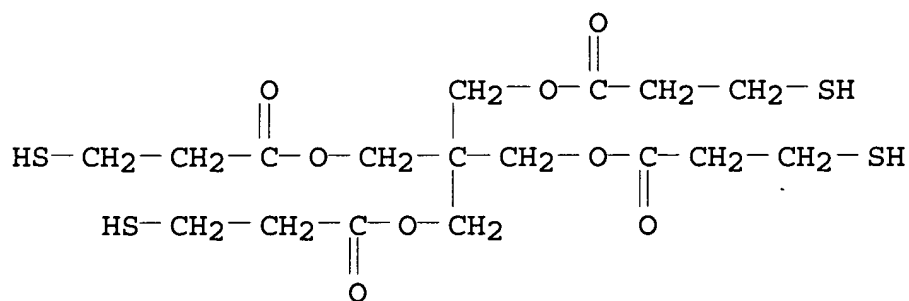
CM 2

CRN 130167-23-6
CMF (C2 H6 O Si)n C16 H34 O5 Si2
CCI PMS



CM 3

CRN 7575-23-7
CMF C17 H28 O8 S4



RN 773091-97-7 HCAPLUS

CN 2-Propenoic acid, 4-chlorophenyl ester, polymer with
2,2-bis[(3-mercapto-1-oxopropoxy)methyl]-1,3-propanediyl
bis(3-mercaptopropanoate), α -[dimethyl[3-(
(oxiranylmethoxy)propyl)silyl]- ω -[[dimethyl[3-(
(oxiranylmethoxy)propyl)silyl]oxy]poly[oxy(dimethylsilylene)] and

α, α' -[9H-fluoren-9-ylidenebis([1,1'-biphenyl]-5,2-diyl)]bis[ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl)]
(9CI) (CA INDEX NAME)

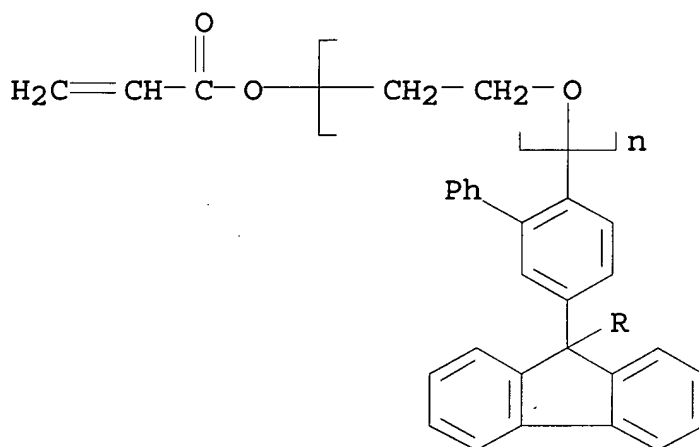
CM 1

CRN 337966-87-7

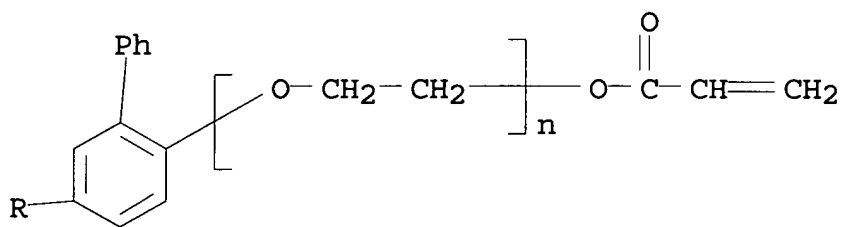
CMF (C2 H4 O)_n (C2 H4 O)_n C43 H30 O4

CCI PMS

PAGE 1-A



PAGE 2-A

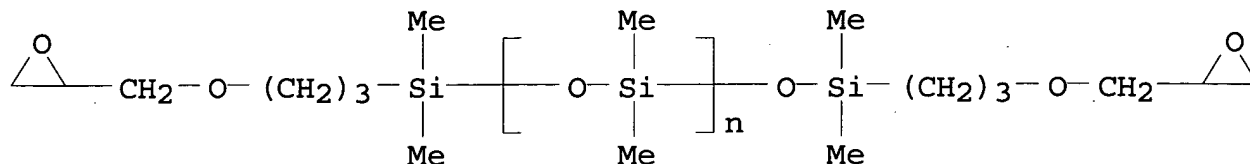


CM 2

CRN 130167-23-6

CMF (C2 H6 O Si)_n C16 H34 O5 Si2

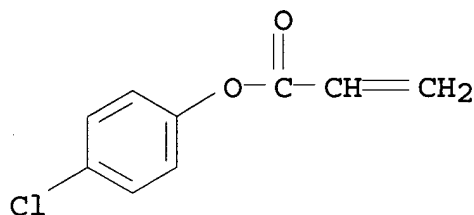
CCI PMS



CM 3

CRN 13633-87-9

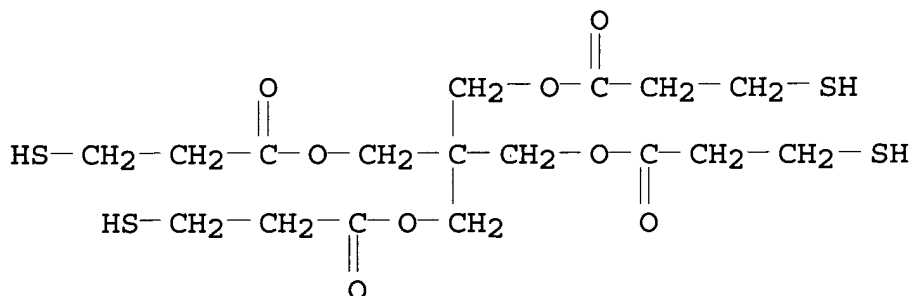
CMF C9 H7 Cl O2



CM 4

CRN 7575-23-7

CMF C17 H28 O8 S4



RN 773091-98-8 HCAPLUS

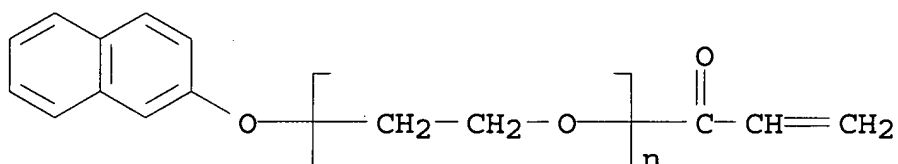
CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]-, polymer with α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) and Sanaid SI 60 (9CI) (CA INDEX NAME)

CM 1

CRN 286833-74-7

CMF (C2 H4 O)_n C13 H10 O2

CCI PMS



CM 2

CRN 192391-58-5

CMF Unspecified

CCI MAN

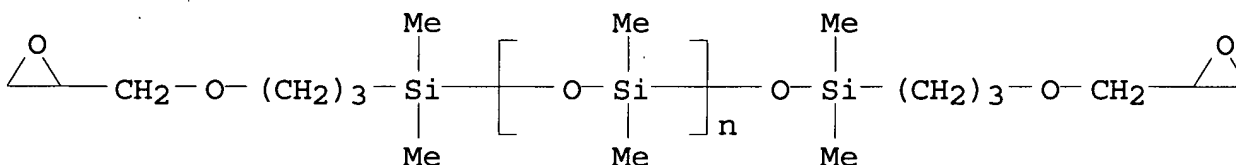
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 130167-23-6

CMF (C2 H6 O Si)_n C16 H34 O5 Si2

CCI PMS



RN 773092-00-5 HCAPLUS

CN Poly[oxy(dimethylsilylene)], α-[dimethyl[3-(oxiranylmethoxy)propyl]silyl]-ω-[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]-, polymer with 3-ethyl-3-(phenoxymethyl)oxetane, α-(1-oxo-2-propenyl)-ω-(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) and Sanaid SI 20 (9CI) (CA INDEX NAME)

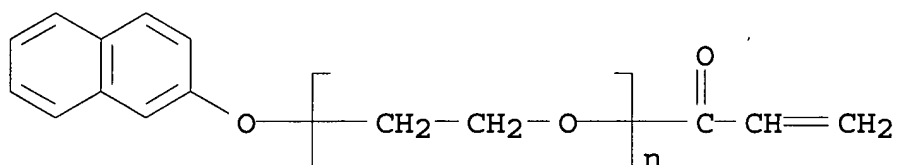
CM 1

CRN 773080-63-0
 CMF Unspecified
 CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

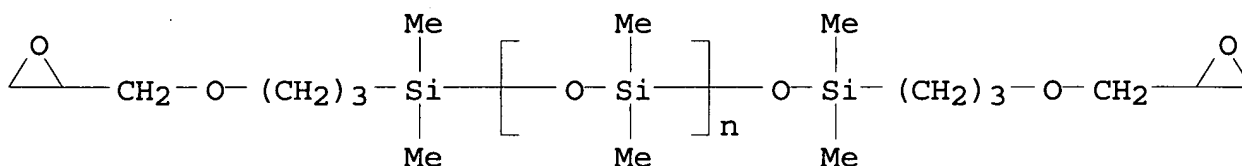
CM 2

CRN 286833-74-7
 CMF (C2 H4 O)_n C13 H10 O2
 CCI PMS



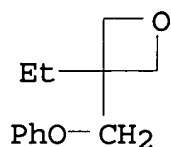
CM 3

CRN 130167-23-6
 CMF (C2 H6 O Si)_n C16 H34 O5 Si2
 CCI PMS



CM 4

CRN 3897-65-2
 CMF C12 H16 O2



RN 773092-01-6 HCAPLUS
 CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]-, polymer with α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl), 3,3'-[oxybis(methylene)]bis[3-ethyloxetane] and Sanaid SI 20 (9CI) (CA INDEX NAME)

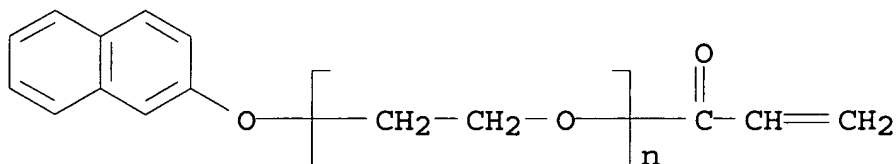
CM 1

CRN 773080-63-0
 CMF Unspecified
 CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

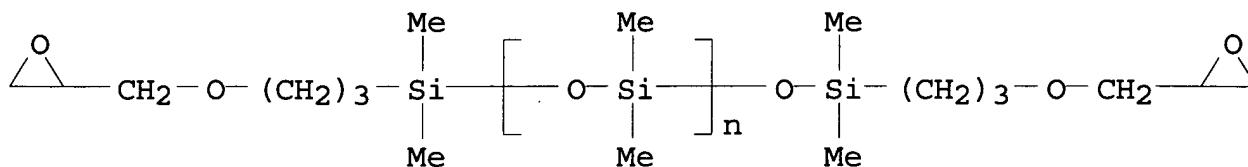
CM 2

CRN 286833-74-7
 CMF (C2 H4 O)_n C13 H10 O2
 CCI PMS



CM 3

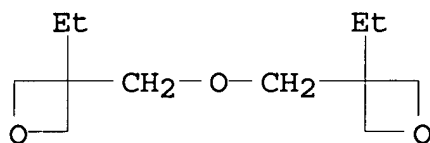
CRN 130167-23-6
 CMF (C2 H6 O Si)_n C16 H34 O5 Si2
 CCI PMS



CM 4

CRN 18934-00-4

CMF C12 H22 O3



RN 773092-02-7 HCAPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl)silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl)silyl]oxy]-, polymer with 3-ethyl-3-[[[(2-ethylhexyl)oxy)methyl]oxetane, α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) and Sanaid SI 20 (9CI) (CA INDEX NAME)

CM 1

CRN 773080-63-0

CMF Unspecified

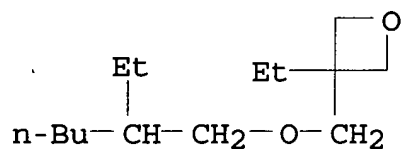
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

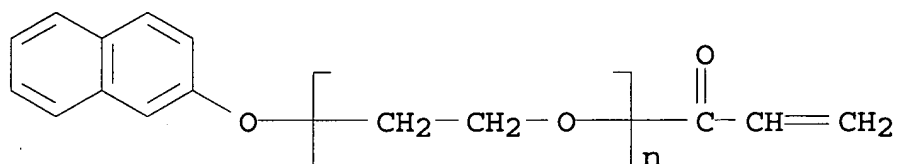
CM 2

CRN 298695-60-0

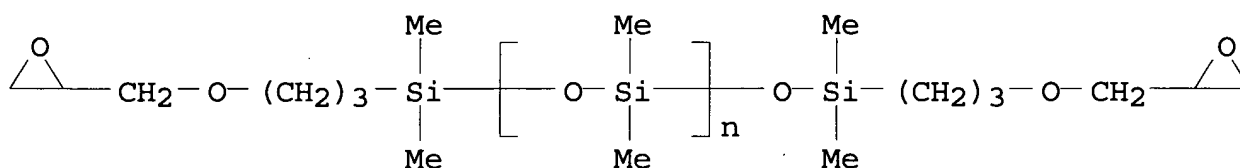
CMF C14 H28 O2



CRN 286833-74-7
CMF (C2 H4 O)n C13 H10 O2
CCI PMS



CRN 130167-23-6
CMF (C2 H6 O Si)n C16 H34 O5 Si2
CCI PMS



RN 773092-03-8 HCAPLUS
CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]-, polymer with α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl), 3,3'-[1,4-phenylenebis(methyleneoxymethylene)]bis[3-ethyloxetane] and Sanaid SI 20 (9CI) (CA INDEX NAME)

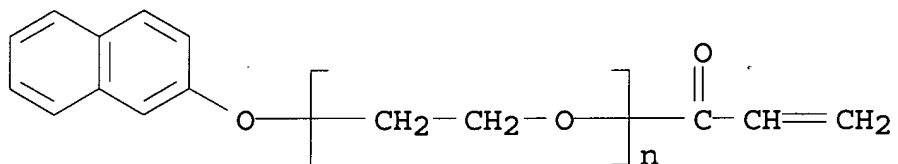
CM 1

CRN 773080-63-0
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

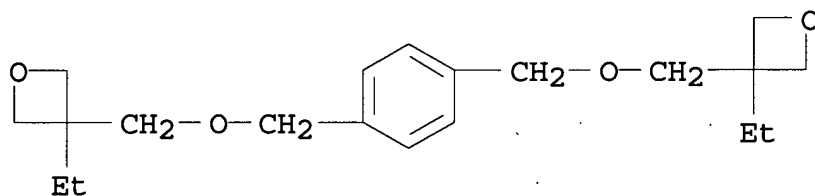
CM 2

CRN 286833-74-7
CMF (C2 H4 O)n C13 H10 O2
CCI PMS



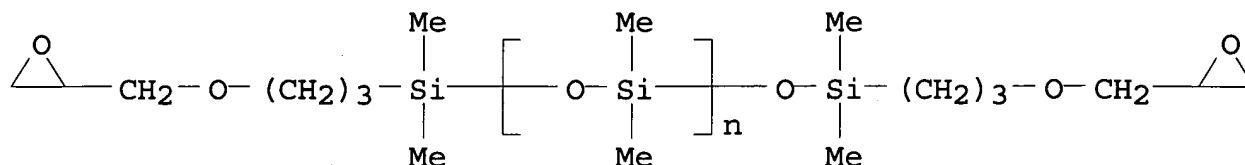
CM 3

CRN 142627-97-2
CMF C20 H30 O4



CM 4

CRN 130167-23-6
CMF (C2 H6 O Si)n C16 H34 O5 Si2
CCI PMS



- IC ICM G03H001-04
 NCL 430001000; 430002000; 359003000; 430281100
 CC 74-8 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)
 Section cross-reference(s): 38
 ST holog **recording** medium polymer photoinitiator
 IT Holographic **recording** materials
 (holog. **recording** medium and **recording** method)
 IT Polyoxyalkylenes, preparation
 (holog. **recording** medium and **recording** method)
 IT 13633-87-9DP, 4-Chlorophenyl acrylate, reaction products with diisocyanate-end polypropyleneglycol and α,ω -dihydroxy polypropyleneglycol 25322-69-4DP, Polypropyleneglycol, diisocyanate-end, reaction products with chlorophenyl acrylate and diisocyanate-end polypropyleneglycol 25322-69-4DP, Polypropyleneglycol, diisocyanate-end, reaction products with chlorophenyl acrylate and α,ω -dihydroxy polypropyleneglycol 771534-33-9P, Propylene glycol diglycidyl ether-pentaerythritol mercaptopropionate-4-bromostyrene copolymer 771534-34-0P, Propylene glycol diglycidyl ether-pentaerythritol mercaptopropionate-4-chlorophenyl acrylate copolymer 771534-35-1P 773081-54-2P 773091-90-0P 773091-91-1P 773091-92-2P 773091-93-3P 773091-94-4P 773091-95-5P 773091-96-6P 773091-97-7P 773091-98-8P 773091-99-9P 773092-00-5P 773092-01-6P 773092-02-7P 773092-03-8P (holog. **recording** medium and **recording** method)
 IT 303110-70-5 773058-26-7 773058-27-8 773058-28-9 773058-29-0 773058-30-3 773058-32-5 773058-34-7 773058-37-0 773058-38-1 773058-39-2 773058-41-6 (photopolymn. initiator; holog. **recording** medium and **recording** method)

L37 ANSWER 8 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2004:508030 HCAPLUS
 DOCUMENT NUMBER: 141:79425
 TITLE: Formation of pixel elements of color filters,
 ribbed substrates, and rib-forming
 compositions therefor
 INVENTOR(S): Uraki, Hisashi; Fukuchi, Yoshihisa
 PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 20 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
-----	----	-----	-----
JP 2004177948	A2	20040624	JP 2003-379531

2003

1110

PRIORITY APPLN. INFO.: JP 2002-326318 A

2002

1111

AB The compns. contain (0.01-10%) vinyl polymers containing
 ethylenically unsatd. double bonds and polyorganosiloxane chains and optionally
 photopolymn. initiators. The compns. form barrier ribs which
 suppress color mixing or blurring of pixel-forming **inks**
 on jet printing.

IT 709649-40-1P

(formation of pixel elements of color filters forming siloxane
polymer-containing rib patterns)

RN 709649-40-1 HCAPLUS

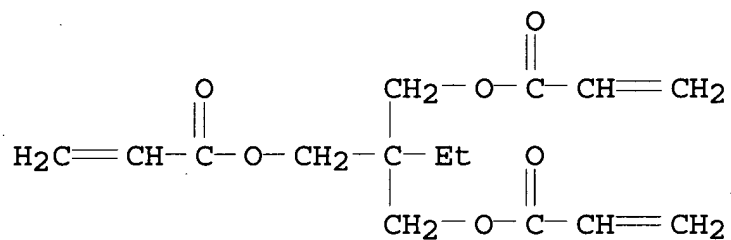
CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
 α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-
 ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)] and
 oxiranylmethyl 2-methyl-2-propenoate, 2-propenoate, graft,
 polymer

with 2-ethyl-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl
 di-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 15625-89-5

CMF C15 H20 O6



CM 2

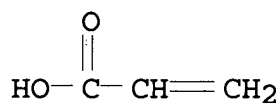
CRN 709649-39-8

CMF (C8 H14 O2 . C7 H10 O3 . (C2 H6 O Si)n C12 H26 O3 Si2)x . x
C3 H4 O2

CM 3

CRN 79-10-7

CMF C3 H4 O2



CM 4

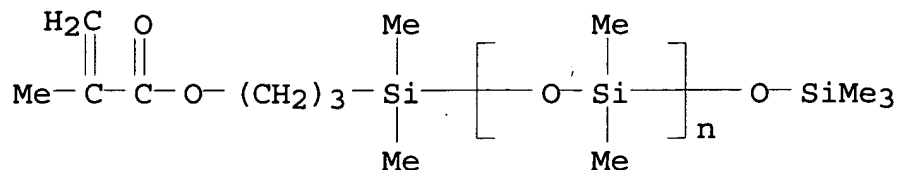
CRN 657393-71-0

CMF (C8 H14 O2 . C7 H10 O3 . (C2 H6 O Si)n C12 H26 O3 Si2)x
CCI PMS

CM 5

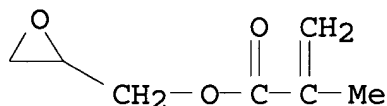
CRN 123109-42-2

CMF (C2 H6 O Si)n C12 H26 O3 Si2
CCI PMS



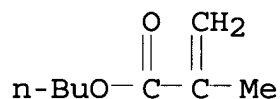
CM 6

CRN 106-91-2
CMF C7 H10 O3



CM 7

CRN 97-88-1
CMF C8 H14 O2



IC ICM G02B005-20

ICS C08F008-00; C08F290-06; B41J002-01

CC 74-13 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)

Section cross-reference(s): 38, 73

IT 868-77-9DP, 2-Hydroxyethyl methacrylate, reaction products with isocyanato-bearing graft copolymers, polymers with trimethylolpropane trimethacrylate 56793-67-0P, Butyl methacrylate-methacrylic acid-methyl methacrylate-styrene copolymer 657393-70-9DP, reaction products with hydroxyethyl methacrylate, polymer with trimethylolpropane trimethacrylate 709632-98-4DP, trimethylsilyl-terminated, reaction products with hydroxyethyl methacrylate, polymer with trimethylolpropane trimethacrylate 709649-27-4P, Butyl methacrylate-2-hydroxyethyl methacrylate-Silaplane FM 0721 graft copolymer ester with isophorone diisocyanate 2-hydroxyethyl acrylate adduct (1:1),

polymer wth NK Ester ATMP 709649-38-7DP, trimethylsilyl ether
709649-40-1P 709649-43-4DP, trimethylsilyl terminated
(formation of pixel elements of color filters forming siloxane
polymer-containing rib patterns)

L37 ANSWER 9 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2004:118493 HCAPLUS

DOCUMENT NUMBER: 140:190067

TITLE: Photosensitive composition for manufacturing
color filter barrier wall of display using
ink jet printing

INVENTOR(S): Uraki, Hisashi; Fukuchi, Yoshihisa

PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
-----	-----	----	-----	-----
-----	JP 2004045910	A2	20040212	JP 2002-205040

2002

0715

PRIORITY APPLN. INFO.: JP 2002-205040

2002

0715

AB The title photosensitive composition comprises (A) a vinyl
polymer
containing a crosslinking group and polyorganosiloxane chain,
and (B)
a vinyl polymer containing a crosslinking group. The
crosslinking
group is hydroxy, carboxyl, isocyno, and/or epoxy. The
composition
may further contain a photoinitiator.

IT 657393-71-0P, Butyl methacrylate-glycidyl
methacrylate-Silaplane FM 0721 graft copolymer
(photosensitive composition for manufacturing color filter
barrier wall of

display using **ink jet** printing)

RN 657393-71-0 HCAPLUS

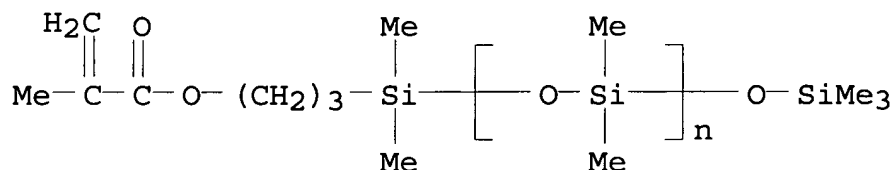
CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
 α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-
 ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)] and
 oxiranylmethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX
 NAME)

CM 1

CRN 123109-42-2

CMF (C2 H6 O Si)_n C12 H26 O3 Si2

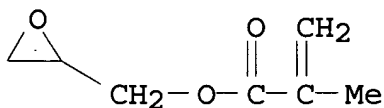
CCI PMS



CM 2

CRN 106-91-2

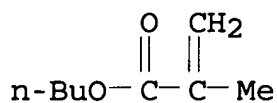
CMF C7 H10 O3



CM 3

CRN 97-88-1

CMF C8 H14 O2



IC ICM G02B005-20

ICS G02F001-1335
CC 74-13 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 42, 73
ST photosensitive compn color filter barrier wall **ink**
jet printing
IT **Inks**
(**jet**-printing; photosensitive composition for manufacturing
color filter barrier wall of display using **ink**
jet printing)
IT Polysiloxanes, preparation
(methacrylate-, graft; photosensitive composition for
manufacturing color
filter barrier wall of display using **ink jet**
printing)
IT **Ink-jet** printing
Optical filters
Optical imaging devices
Photoresists
(photosensitive composition for manufacturing color filter
barrier wall of
display using **ink jet** printing)
IT 56793-67-0P, Butyl methacrylate-methacrylic acid-methyl
methacrylate-styrene copolymer 657393-69-6P, Butyl
methacrylate-2-hydroxyethyl methacrylate-Silaplane FM 0721 graft
copolymer 657393-70-9P, Butyl methacrylate-2-
(methacryloyloxy)ethyl isocyanate-Silaplane FM 0721 graft
copolymer **657393-71-0P**, Butyl methacrylate-glycidyl
methacrylate-Silaplane FM 0721 graft copolymer
(photosensitive composition for manufacturing color filter
barrier wall of
display using **ink jet** printing)

L37 ANSWER 10 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:97722 HCAPLUS
DOCUMENT NUMBER: 140:129937
TITLE: Ink compositions for marking pens for
recording materials
INVENTOR(S): Fujiwara, Yoshito
PATENT ASSIGNEE(S): Mitsubishi Pencil Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
-----	-----	----	-----	-----
	JP 2004035823	A2	20040205	JP 2002-197415

2002

0705

PRIORITY APPLN. INFO.:

JP 2002-197415

2002

0705

AB The ink compns., having surface tension ≤ 22 mN/m at 25° and showing smooth writability on substrates (e.g., labels of CD-R disks), contain colorants, solvents containing C ≤ 4 aliphatic alcs. and C ≤ 6 glycol derivs., styrene-acrylic acid copolymer (I) and/or styrene- α -methylstyrene-acrylic acid copolymer, and **polyoxyalkylene**-modified polysiloxanes (HLB 1-14). Thus, an ink contained Valifast Black 3820 10.0, I (Joncryl 67) 3.0, propylene glycol monomethyl ether 53.9, EtOH 30.0, benzyl alc. 3.0, and **polyoxyalkylene**-modified polysiloxane (L 720, HLB 7) 0.1 part.

IC ICM C09D011-16

CC 42-12 (Coatings, Inks, and Related Products)

ST polyoxylalylene polysiloxane marking ink **recording** material; acrylic styrene copolymer marking ink; surface tension marking ink surfactant writability

IT **Polyoxyalkylenes**, uses
(di-Me polysiloxane-, Silwet FZ 2122; ink compns. for marking pens for **recording** materials)

IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethers with **polyethylene-polypropylene glycol** mono-Bu ether, Silwet L 720; ink compns. for marking pens for **recording** materials)

IT **Polysiloxanes**, uses
(di-Me, **polyoxyalkylene**-, Silwet FZ 2122; ink compns. for marking pens for **recording** materials)

IT Optical **recording** materials
(ink compns. for marking pens for **recording** materials)

IT Inks
 (marking; ink compns. for marking pens for **recording** materials)

IT Surfactants
 (**polyoxyalkylene-polysiloxanes**; ink compns. for marking pens for **recording** materials)

IT **Polysiloxanes**, uses
 (polyoxyethylene-, Silwet FZ 2104, Silwet FZ 2191; ink compns. for marking pens for **recording** materials)

IT 52831-04-6, Styrene- α -methylstyrene-acrylic acid copolymer
 (Joncryn 682; ink compns. for marking pens for **recording** materials)

IT 25085-34-1, Joncryn 67
 (Joncryn 690; ink compns. for marking pens for **recording** materials)

L37 ANSWER 11 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2003:568630 HCAPLUS

DOCUMENT NUMBER: 139:140985

TITLE: Curable epoxy resin composition, surface modification process, **ink-jet recording** head and **ink-jet recording** apparatus

INVENTOR(S): Shimomura, Akihiko; Noguchi, Hiromichi; Imamura, Isao

PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan

SOURCE: Eur. Pat. Appl., 24 pp.
 CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
-----	----	-----	-----
EP 1329472	A1	20030723	EP 2003-885

2003

0115

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE,
 MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ,
 EE, HU, SK

CN 1432600 A 20030730 CN 2003-100277

2003

0110

JP 2003277472 A2 20031002 JP 2003-3825

2003

0110

US 2003170401 A1 20030911 US 2003-341373

2003

0114

PRIORITY APPLN. INFO.: JP 2002-8441 A

2002

0117

AB The title composition comprises (i) a first epoxy resin having
 ≥ 1 water-repellency-imparting group and ≥ 2 cyclic
 aliphatic epoxy groups, and having Mn 8000-22,000 and
polydispersity
 3.5-5.0, (ii) a second epoxy resin having ≥ 1
 water-repellency-imparting group and ≥ 2 cyclic aliphatic epoxy
 groups, having Mn 2500-8000 and polydispersity 1.5-3.0, and (iii)
 a cationic polymerization catalyst. The composition is useful
for surface
 treatment to impart water repellency or **ink** repellency
 to an article surface, especially for forming coating in a
pattern by UV
 irradiation
IT **473272-74-1**

 (water-repellent; epoxy resin composition for surface
modification
 of **ink-jet recording** head and
 ink-jet recording apparatus)

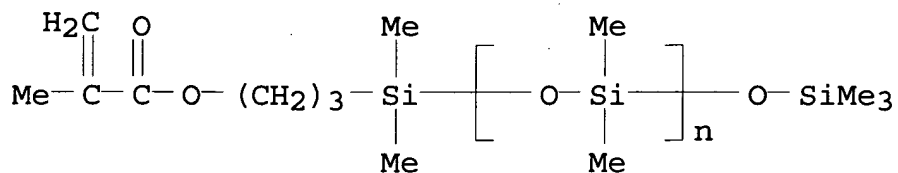
RN 473272-74-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 7-oxabicyclo[4.1.0]hept-3-ylmethyl
 ester, polymer with α -[dimethyl[3-[(2-methyl-1-oxo-2-
propenyl)oxy]propyl]silyl]- ω -[(trimethylsilyl)oxy]poly[oxy(d
imethylsilylene)], graft (9CI) (CA INDEX NAME)

CM 1

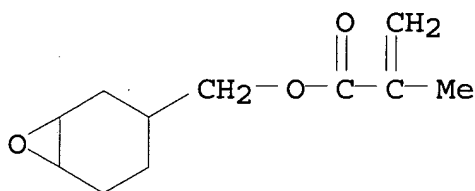
CRN 123109-42-2

CMF (C2 H6 O Si)_n C12 H26 O3 Si2
 CCI PMS



CM 2

CRN 82428-30-6
 CMF C11 H16 O3



IC ICM C08G059-30
 ICS C08G059-32; C08G059-38; C08L063-00; B41J002-16
 CC 74-6 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)
 ST epoxy resin compn water repellency **ink jet recording head**
 IT **Ink-jet printer heads**
 Ink-jet printers
 (epoxy resin composition for surface modification of **ink-jet recording head** and **ink-jet recording apparatus**)
 IT Epoxy resins, uses
 (water-repellent; epoxy resin composition for surface modification of **ink-jet recording head** and **ink-jet recording apparatus**)
 IT 68050-65-7, Bisphenol AF-epichlorohydrin copolymer 160099-23-0
 (compatibilizers; epoxy resin composition for surface modification of **ink-jet recording head** and **ink-jet recording apparatus**)

IT 473272-74-1 565232-42-0

(water-repellent; epoxy resin composition for surface
modification

of ink-jet recording head and

ink-jet recording apparatus)

REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS
AVAILABLE

IN THE RE FORMAT

L37 ANSWER 12 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2002:946891 HCAPLUS

DOCUMENT NUMBER: 138:31051

TITLE: Lithographic printing plate comprising
protective overlayerINVENTOR(S): Savariar-Hauck, Celin; Hauck, Gerhard; Frank,
Dietmar; Fiebag, Ulrich

PATENT ASSIGNEE(S): Germany

SOURCE: U.S. Pat. Appl. Publ., 13 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
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US 2002187425	A1	20021212	US 2001-805327
2001			
0313			
US 6613494	B2	20030902	
EP 1241003	A2	20020918	EP 2002-5304
2002			
0312			
EP 1241003	A3	20031029	
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE,			
MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR			
PRIORITY APPLN. INFO.:		US 2001-805327	A
2001			
0313			

AB Pos.-working imageable printing plate and methods for the plate preparation are disclosed. The printing plate comprises a hydrophilic substrate; a bottom layer, which contains a pos.-working photosensitive composition; and a protective overlayer, which has an overlayer material that reduces the solubility of the photosensitive composition in an aqueous alkaline developer. The overlayer may be conveniently applied by a dip and rinse procedure. The object of the invention is to provide a printing plate that has improved photospeed but in which the unexposed regions are resistant to alkaline developers and do not require a prolonged conditioning step as part of the manufacturing process.

IC ICM G03F007-11

NCL 430272100; 430273100

CC 74-6 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

IT **Polyoxyalkylenes**, uses
(Lubrimet P 900; pos.-working lithog. printing plate comprising protective overlayer)

IT Polyethers, uses
(**di-Me siloxane-**, Byk 307; pos.-working lithog. printing plate comprising protective overlayer)

IT **Polysiloxanes**, uses
(**di-Me**, 3-hydroxypropyl Me, ethers with **polyethylene-polypropylene glycol** acetate, DC 190; pos.-working lithog. printing plate comprising protective overlayer)

IT **Polysiloxanes**, uses
(**di-Me**, polyether-, Byk 307; pos.-working lithog. printing plate comprising protective overlayer)

IT **Polysiloxanes**, uses
(glycidyl group-containing, Edaplan LA 411; pos.-working lithog. printing plate comprising protective overlayer)

L37 ANSWER 13 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2002:658607 HCAPLUS
DOCUMENT NUMBER: 137:208403
TITLE: Method for producing ink jet

**recording head, and ink
jet recording head produced
by such method**
 INVENTOR(S): Suzuki, Toshio
 PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan
 SOURCE: U.S. Pat. Appl. Publ., 18 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
----- -----	----	-----	-----
US 2002119248	A1	20020829	US 2002-79898
2002			
0222			
US 6811715	B2	20041102	
PRIORITY APPLN. INFO.:		JP 2001-47082	A

2001

0222

AB A method for producing an **ink jet
recording head**, comprises steps of forming, on a
 substrate, a solid layer composed of soluble resin and having a
 pattern for constituting a liquid flow path; forming an inorg.
 film
 by low temperature film formation so as to cover the solid layer;
 forming a layer of a head forming material so as to cover the
 inorg. film; removing a part of the inorg. film for forming a
 discharge port; and removing the solid film thereby forming a
 liquid
 flow path communicating with the discharge port. An object of
 the
 present invention is to provide a method for producing an
ink jet recording head, capable of
 avoiding peeling of the flow path forming material from the
 substrate even in case of a long-sized head, and enabling
 satisfactory range of material selection and satisfactory
 productivity. Another object of the present invention is to
 provide a method for producing an **ink jet**

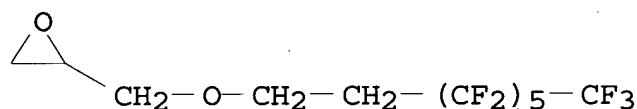
on the discharge port face.

(water-repellent resin for ink jet recording head)

CN Phenol, 4,4'-(1-methylethylidene)bis-, polymer with (chloromethyl)oxirane, 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]disiloxane and

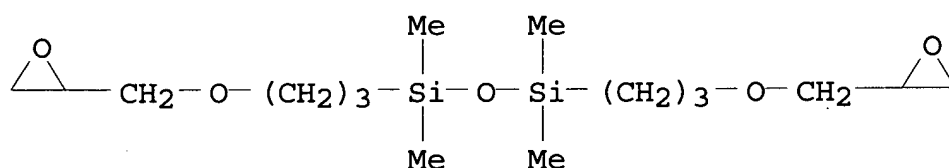
CM 1

CMF C11 H9 F13 O2



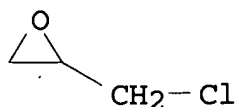
CM 2

CMF C16 H34 O5 Si2



CM 3

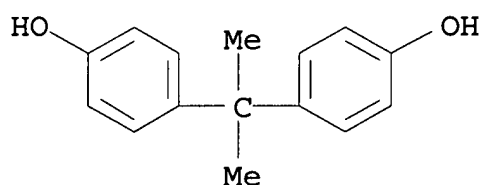
CMF C3 H5 Cl O



CM 4

CRN 80-05-7

CMF C15 H16 O2



IC ICM C23C016-00

ICS B05D003-00

NCL 427248100

CC 74-6 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)ST **ink jet recording** head printer manufIT Vapor deposition process
(chemical; method for producing **ink jet**
recording head)IT Sputtering
(etching, reactive; method for producing **ink**
jet recording head)IT **Ink-jet** printer heads

Photoresists

Sputtering

Vapor deposition process

(method for producing **ink jet**
recording head)IT Etching
(sputter, reactive; method for producing **ink**
jet recording head)IT 452296-36-5, Epikote 828-Fujicure 6010 copolymer
(coating for **ink jet recording**
head)IT 7631-86-9, Silicon oxide (SiO₂), processes
(hydrophilic film covering solid substrate of **ink**
jet recording head)

IT 132702-22-8, AZ-4903 452310-23-5, MF 58

(photoresist for ink jet recording head)

IT 7440-25-7, Tantalum, uses (substrate in ink jet recording head)

IT 7429-90-5, Aluminum, uses 7440-02-0, Nickel, uses 7440-21-3, Silicon, uses 7440-50-8, Copper, uses (substrate of ink jet recording head)

IT 186294-09-7 (water-repellent resin for ink jet recording head)

REFERENCE COUNT: 23 THERE ARE 23 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L37 ANSWER 14 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2002:503671 HCAPLUS

DOCUMENT NUMBER: 137:64382

TITLE: Elastic polyurethane foam parts and their use in image formation devices

INVENTOR(S): Sakata, Junji; Yamazaki, Hirotaka

PATENT ASSIGNEE(S): Bridgestone Corp., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp. CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
2000	JP 2002187929	A2	20020705	JP 2000-388889
1221	US 2002091170	A1	20020711	US 2001-985771
2001				
1106	US 6818674	B2	20041116	
PRIORITY APPLN. INFO.:				JP 2000-339883 A

2000

1108

JP 2000-388889 A

2000

1221

AB The parts with low surface friction resistance and fine cells for rollers in electrophotog. apparatus, electrostatic recording apparatus, etc., are obtained by (A) stirring urethane

prepolymers

prepared from modified silicone oils, polyols, and

polyisocyanates

with blowing agents and foam stabilizers or (B) stirring polyols, polyisocyanates, modified silicone oils, blowing agents, and foam stabilizers, wherein the modified silicone oils have polyisocyanate-reactive groups, and the foam stabilizers are silicones modified with polyethers having oxyethylene unit weight ratio 50-100%. Thus, a prepolymer prepared from ethylene oxide-propylene oxide copolymer glycerin ether, TDI, X 22-176B (alc.-modified silicone oil having 2 functional groups at one terminal) and a mixture containing conductive C, a catalyst in dipropylene glycol, and a polyether-modified silicone foam stabilizer (having polyoxyethylene content 70% in the polyether) were mixed, cast in a mold, and cured to give a conductive polyurethane foam (surface friction resistance 0.87 N), which was used to give a toner supplying roller in a dry electrophotog.

apparatus

showing good printability.

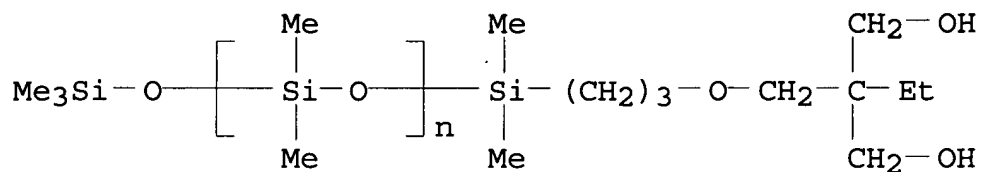
IT 439667-99-9P, Dipropylene glycol-ethylene oxide-propylene oxide copolymer glycerin ether-crude MDI-TDI-X 22-176B copolymer (elastic polyurethane foam parts and their use in image formation devices)

RN 439667-99-9 HCAPLUS

CN Isocyanic acid, polymethylenepolyphenylene ester, polymer with α -[[3-[2,2-bis(hydroxymethyl)butoxy]propyl]dimethylsilyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], 1,3-diisocyanatomethylbenzene, methyloxirane polymer with oxirane ether with 1,2,3-propanetriol (3:1), and oxybis[propanol] (9CI) (CA INDEX NAME)

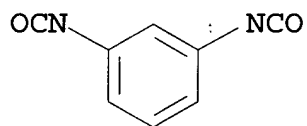
CM 1

CRN 128147-46-6
 CMF (C2 H6 O Si)_n C14 H34 O4 Si2
 CCI PMS



CM 2

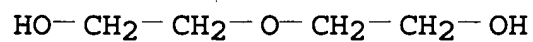
CRN 26471-62-5
 CMF C9 H6 N2 O2
 CCI IDS



D1-Me

CM 3

CRN 25265-71-8
 CMF C6 H14 O3
 CCI IDS



2 (D1-Me)

CM 4

CRN 9016-87-9
CMF Unspecified
CCI PMS, MAN

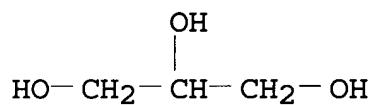
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 5

CRN 9082-00-2
CMF C3 H8 O3 . 3 (C3 H6 O . C2 H4 O)x

CM 6

CRN 56-81-5
CMF C3 H8 O3

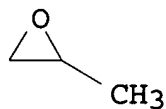


CM 7

CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 8

CRN 75-56-9
CMF C3 H6 O



CM 9

CRN 75-21-8
CMF C2 H4 O



IT 439667-98-8P, Dipropylene glycol-ethylene oxide-propylene oxide copolymer glycerin ether-TDI-X 22-176B copolymer
(rubber; elastic polyurethane foam parts and their use in image

formation devices)

RN 439667-98-8 HCAPLUS

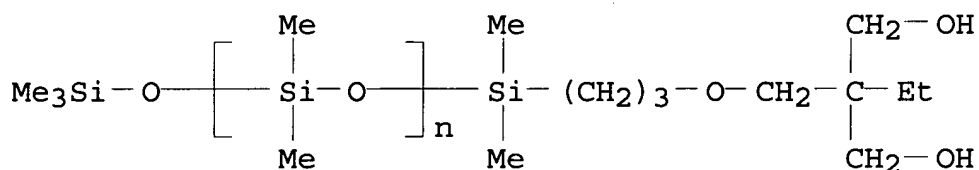
CN Propanol, oxybis-, polymer with α -[[3-[2,2-bis(hydroxymethyl)butoxy]propyl]dimethylsilyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], 1,3-diisocyanatomethylbenzene and methyloxirane polymer with oxirane ether with 1,2,3-propanetriol (3:1) (9CI) (CA INDEX NAME)

CM 1

CRN 128147-46-6

CMF (C2 H6 O Si)_n C14 H34 O4 Si2

CCI PMS

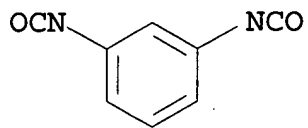


CM 2

CRN 26471-62-5

CMF C9 H6 N2 O2

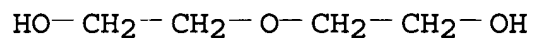
CCI IDS



D1-Me

CM 3

CRN 25265-71-8
 CMF C6 H14 O3
 CCI IDS



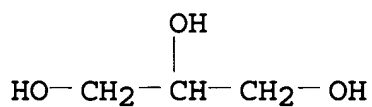
2 (D1-Me)

CM 4

CRN 9082-00-2
 CMF C3 H8 O3 . 3 (C3 H6 O . C2 H4 O) x

CM 5

CRN 56-81-5
 CMF C3 H8 O3



CM 6

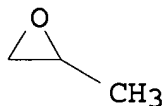
CRN 9003-11-6

CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 7

CRN 75-56-9

CMF C3 H6 O



CM 8

CRN 75-21-8

CMF C2 H4 O



IC ICM C08G018-61
ICS F16C013-00; G03G015-02; G03G015-08; G03G015-16; C08G018-61;
C08G101-00
CC 39-9 (Synthetic Elastomers and Natural Rubber)
Section cross-reference(s): 74
IT 439667-99-9P, Dipropylene glycol-ethylene oxide-propylene
oxide copolymer glycerin ether-crude MDI-TDI-X 22-176B copolymer
(elastic polyurethane foam parts and their use in image
formation devices)
IT 9082-00-2DP, Ethylene oxide-propylene oxide copolymer glycerin
ether, polymers with TDI and alc.-modified silicones
26471-62-5DP, TDI, polymers with polyether polyols and
alc.-modified silicones 439667-98-8P, Dipropylene
glycol-ethylene oxide-propylene oxide copolymer glycerin
ether-TDI-X 22-176B copolymer
(rubber; elastic polyurethane foam parts and their use in
image formation devices)

L37 ANSWER 15 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2002:10038 HCAPLUS
DOCUMENT NUMBER: 136:55389

TITLE: Ink, ink set, ink-jet **recording**
process, ink cartridge, **recording**
unit and ink-jet **recording** apparatus
INVENTOR(S): Osumi, Koichi; Mishina, Shinya; Teraoka,
Hisashi; Yakushigawa, Yuko
PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan
SOURCE: Eur. Pat. Appl., 36 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
EP 1167474	A1	20020102	EP 2001-115205
JP 2002080768	A2	20020319	JP 2001-191881
US 6474804	B2	20021105	US 2001-887259
JP 2000-190331	A		

AB An ink comprises a dye, a silicon-containing surfactant, an ethylene oxide adduct of acetylene glycol and a liquid medium, wherein a weight ratio of the silicon-containing surfactant to the ethylene oxide adduct of acetylene glycol is not lower than 1/5000, but lower than 1/20. An ink-jet **recording** process comprises the

step of ejecting the ink by an ink-jet system. An ink set comprises in combination a first dye having a certain color tone, and a second dye ink having a color tone different from that of the first dye ink, wherein at least one of the first and second dye inks is the above ink. An ink set comprises dye inks of yellow, magenta and cyan, wherein the dye inks comprise an ethylene oxide adduct of acetylene glycol resp., and the dye inks of magenta and cyan further comprise a silicon-containing

surfactant.

IC ICM C09D011-00

CC 42-12 (Coatings, Inks, and Related Products)

IT **Polysiloxanes**, uses

(FZ-2162; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT Polyurethanes, uses

(cartridge; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Polysiloxanes**, uses

(di-Me, 3-hydroxypropyl Me, ethers with **polyethylene-polypropylene glycol** mono-Bu ether, L-720; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT Dyes

Ink-jet printers

(ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT Inks

(jet-printing; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Polysiloxanes**, uses

(polyoxyalkylene-, FZ-2123; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Polyoxyalkylenes**, uses

(**polysiloxane**-, FZ-2123; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT Surfactants

(silicon-containing; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT 9003-07-0, Polypropylene 9003-20-7, Polyvinyl acetate

9004-34-6, Cellulose, uses
(cartridge; ink, ink set, ink-jet **recording** process,
ink cartridge, **recording** unit and ink-jet
recording apparatus)

IT 9014-85-1, Acetylenol EH 12222-04-7, C.I. Direct Blue 199
27306-78-1, Silwet L-77 50925-42-3, C.I. Direct Yellow 86
(ink, ink set, ink-jet **recording** process, ink
cartridge, **recording** unit and ink-jet
recording apparatus)

REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS

AVAILABLE

IN THE RE FORMAT

L37 ANSWER 16 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2001:565158 HCAPLUS
DOCUMENT NUMBER: 135:154154
TITLE: Lubricating acrylic polysiloxane coating
agents
INVENTOR(S): Kamiya, Daisuke; Maeda, Keiji; Okazaki,
Eiichi
PATENT ASSIGNEE(S): Toagosei Co., Ltd., Japan
SOURCE: PCT Int. Appl., 27 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
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WO 2001055272	A1	20010802	WO 2001-JP350

2001

0119

W: CN, KR, US
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU,
MC, NL, PT, SE, TR
JP 2001279165 A2 20011010 JP 2000-149335

2000

0522

PRIORITY APPLN. INFO.: JP 2000-15140 A

2000

0125

JP 2000-149335 A

2000

0522

AB Title agents, useful as antisticking backings of thermal-transfer **recording** films, are polymers consisting of silicone units 0.5-60, cyclic imido units 5-99, and other monomer-based units 0.5-94.5%. A MEK solution containing 30:40:30 Me methacrylate-tetrahydrophthalimidoethyl acrylate-X 22 174DX copolymer was spread on a polyester film and UV-cured to form a film showing dynamic friction 0.030 μ k and releasing ability 19 N/m and resulting good prints in thermal-transfer printing.

IT 352239-21-5P

(imido acrylate polysiloxane coatings as antisticking backings for thermal-transfer **recording** films)

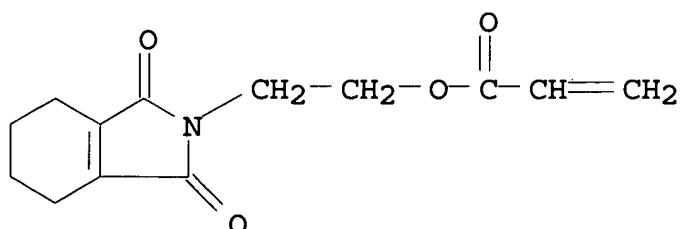
RN 352239-21-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], 2-(1,3,4,5,6,7-hexahydro-1,3-dioxo-2H-isoindol-2-yl)ethyl 2-propenoate, methyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

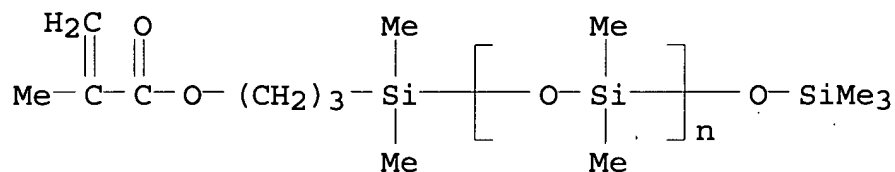
CRN 125350-99-4

CMF C13 H15 N O4



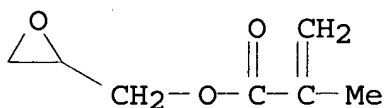
CM 2

CRN 123109-42-2
 CMF (C2 H6 O Si)_n C12 H26 O3 Si2
 CCI PMS



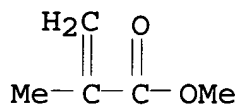
CM 3

CRN 106-91-2
 CMF C7 H10 O3



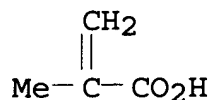
CM 4

CRN 80-62-6
 CMF C5 H8 O2



CM 5

CRN 79-41-4
 CMF C4 H6 O2



IC C09D183-04; C09D135-00; C09D133-06; C09D004-06; B41M005-40
CC 42-10 (Coatings, Inks, and Related Products)
Section cross-reference(s): 74
IT Polysiloxanes, uses
 (acrylic; imido acrylate polysiloxane coatings as antisticking
 backings for thermal-transfer **recording** films)
IT Coating materials
 (blocking-resistant; imido acrylate polysiloxane coatings as
 antisticking backings for thermal-transfer **recording**
 films)
IT Thermal-transfer printing materials
 (sheets; imido acrylate polysiloxane coatings as antisticking
 backings for thermal-transfer **recording** films)
IT 352239-18-0P 352239-19-1P 352239-20-4P **352239-21-5P**
352270-56-5P
 (imido acrylate polysiloxane coatings as antisticking backings
 for thermal-transfer **recording** films)
REFERENCE COUNT: 12 THERE ARE 12 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS
AVAILABLE

IN THE RE FORMAT

L37 ANSWER 17 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2001:189208 HCAPLUS
DOCUMENT NUMBER: 134:214917
TITLE: Removing agent composition for photoresist
INVENTOR(S): Paek, Chiheun; Oh, Changi; Lee, Sangdae; Jin,
Yuanlai; Liu, Zhongshun
PATENT ASSIGNEE(S): Tongjin Chemical Industry Co., Ltd., S. Korea
SOURCE: Faming Zhuanli Shenqing Gongkai Shuomingshu,
32 pp.
CODEN: CNXXEV
DOCUMENT TYPE: Patent
LANGUAGE: Chinese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
-----	-----	-----	-----	-----
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CN 1258730 A 20000705 CN 1999-118360
 1999
 0830
 CN 1118003 B 20030813
 KR 2000046480 A 20000725 KR 1998-63166
 1998
 1231
 TW 575782 B 20040211 TW 1999-88113365
 1999
 0805
 US 6140027 A 20001031 US 1999-435569
 1999
 1108
 PRIORITY APPLN. INFO.: KR 1998-63166 A
 1998
 1231
 AB This patent disclosed a photoresist removing agent composition
 comprising: (1) 10-40 weight% water-soluble amine compound, (2)
 20-50 weight%
 polar organic solvent selected from DMSO, N-methylpyrrolidone
 (NMP),
 di-Me acetamide (DMA), **DMF** and
 di-Me imidazolidinone (DMI), (3) 10-30 weight%
 water, (4) 0.1-10 weight% polyhydroxy phenol compound, (5)
 0.1-10%
 triazole compound, and (6) 0.01-1 weight% polysiloxane
 surfactant. The
 composition can easily remove photoresist layer with min.
 corrosion on
 metal substrate.
 IC ICM C11D001-82
 ICS C11D003-32; H05K003-26
 CC 74-5 (Radiation Chemistry, **Photochemistry**, and
 Photographic and Other Reprographic Processes)
 Section cross-reference(s): 76
 IT **Polysiloxanes**, uses

(di-Me, 3-hydroxypropyl Me, ethers with
polyethylene-polypropylene glycol
mono-Bu ether, L 720; surfactant in photoresist removing agent
composition)

IT **Polysiloxanes**, uses

(di-Me, 3-hydroxypropyl Me, ethoxylated
propoxylated, L 7230; surfactant in photoresist removing agent
composition)

IT **Polyoxyalkylenes**, uses

(di-Me, Me hydrogen **polysiloxane**
-, L 7600; surfactant in photoresist removing agent
composition)

IT **Polysiloxanes**, uses

(di-Me, Me hydrogen,
polyoxyalkylene-, L 7600; surfactant in photoresist
removing agent composition)

IT **Polysiloxanes**, uses

(di-Me, hydroxypropyl Me, ethers with
polyoxyalkylene glycol mono-C1-3-alkyl ether, L 7604;
surfactant in photoresist removing agent composition)

IT **Polysiloxanes**, uses

(ethoxylated, L 7614; surfactant in photoresist removing agent
composition)

IT 67-68-5, DMSO, uses 68-12-2, **DMF**, uses 80-73-9

872-50-4, NMP, uses

(polar solvent in photoresist removing agent composition).

L37 ANSWER 18 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2000:511793 HCAPLUS

DOCUMENT NUMBER: 133:142575

TITLE: Developer for electrophotographic development
and **ink-jet** printing and
recording material such as **ink**
therefor

INVENTOR(S): Tsubushi, Kazuo; Asami, Takeshi; Ishikawa,
Aiko

PATENT ASSIGNEE(S): Ricoh Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 14 pp.
CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	----	-----

— — — — —

JP 2000206738

A2

20000728

JP 1999-3488

1999

0108

US 2002081515

A1

20020627、

US 2001-943448

2001

0830

US 2003065064

A1

20030403

US 2002-170910

2002

0612

US 6620569

B2

20030916

US 2004010075

A1

20040115

US 2003-613544

2003

0702

PRIORITY APPLN. INFO.:

JP 1999-3488

A

1999

0108

US 1999-472575

B1

1999

1227

US 2001-943448

B1

2001

0830

US 2002-170910

A3

2002

0612

AB The invention relates to a developer used in electrophotog.

development or in **ink-jet** printing has a toner, which contains a colorant and a resin, or **ink** in an insulative carrier solution, wherein the developer contains a reactive silicone compound. The addition of the silicone compound enables

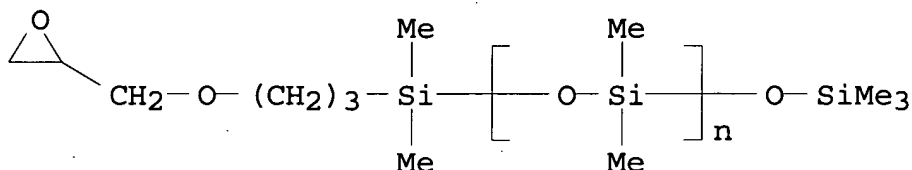
the developer suitable for use with a high-b.p. carrier solution

IT 157723-26-7, FM 0511

(FM 0511; developer for electrophotog. development and **ink-jet** printing and **recording** material such as **ink**)

RN 157723-26-7 HCAPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[(trimethylsilyl)oxy]-(9CI) (CA INDEX NAME)



IC ICM G03G009-12

ICS C09D011-00; G03G009-13

CC 74-3 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

ST developer electrophotog **ink jet** printing

IT Polysiloxanes, uses

(developer for electrophotog. development and **ink-jet** printing)

IT Electrophotographic developers

(developer for electrophotog. development and **ink-jet** printing and **recording** material such as **ink**)

IT Polysiloxanes, uses

(di-Me, di-Ph, [(ethenyldimethylsilyl)oxy]-terminated, FP

2231;

developer for electrophotog. development and **ink-jet** printing and **recording** material such as **ink**)

IT Polysiloxanes, uses

(methacrylate-, X 22-5502; developer for electrophotog. development and **ink-jet** printing and **recording** material such as **ink**)

IT 157723-26-7, FM 0511

(FM 0511; developer for electrophotog. development and

ink-jet printing and recording
material such as **ink**)

IT 115254-29-0, FM 1111
(FM 1111; developer for electrophotog. development and
ink-jet printing and recording
material such as **ink**)

IT 26403-67-8, KF 99 42557-10-8, KF 96-100 156048-34-9D,
ethenyldimethylsilyl terminated 156327-07-0, FM 4421
(developer for electrophotog. development and **ink-**
jet printing and recording material such as
ink)

L37 ANSWER 19 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2000:312492 HCAPLUS

DOCUMENT NUMBER: 133:51072

TITLE: Epoxy Resin-Photopolymer Composites for
Volume

AUTHOR(S): Holography
Trentler, Timothy J.; Boyd, Joel E.; Colvin,
Vicki L.

CORPORATE SOURCE: Department of Chemistry, Rice University,
Houston, TX, 77005, USA

SOURCE: Chemistry of Materials (2000), 12(5),
1431-1438

CODEN: CMATEX; ISSN: 0897-4756

PUBLISHER: American Chemical Society

DOCUMENT TYPE: Journal

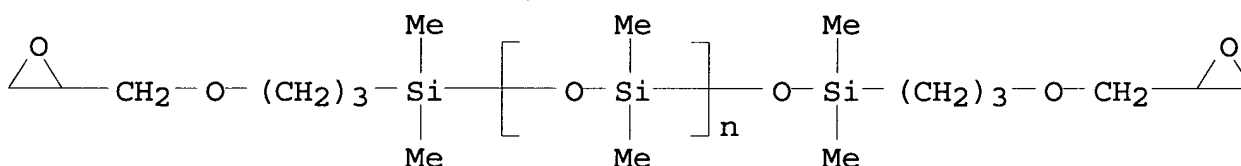
LANGUAGE: English

AB Efficient materials for **recording** volume holograms are
described that could potentially find application in archival
data
storage. These materials are prepared by mixing
photopolymerizable
vinyl monomers with a liquid epoxy resin and an amine hardener.

A
solid matrix is formed in situ as the epoxy cures at room
temperature
The unreacted vinyl monomers are subsequently photopolymerized during
hologram **recording**. A key feature of these materials is
the separation of the epoxy and vinyl polymers. This separation
allows for a
large index contrast to be developed in holograms when components
are optimized. The standard material described in this work
consists
of a low index matrix (n equivalent 1.46), comprised of
diethylenetriamine and 1,4-butanediol diglycidyl ether, and a
high

index photopolymer mixture (n equivalent 1.60) of N-vinylcarbazole and N-vinyl-2-pyrrolidinone. This material is functional in thick formats (several millimeters), which enables narrow angular bandwidth and high diffraction efficiency. A dynamic range (M/#) up to 13 has been measured in these materials. Holog. performance is highly dependent on the amount of amine hardener used, as well as on photopolymer shrinkage.

IT 130167-23-6 (holog. **recording** material mixture containing photopolymerizable vinyl monomers and epoxy resin matrix produced by curing composition containing)
 RN 130167-23-6 HCAPLUS
 CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]- (9CI) (CA INDEX NAME)



CC 74-8 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)
 ST holog **recording** material epoxy resin photopolymerizable monomer composite; vinyl photopolymerizable monomer epoxy resin matrix holog **recording**
 IT Polyamines
 Polyamines
 Polyamines
 (epoxy-polyether-; holog. **recording** material containing photopolymerizable vinyl monomers and epoxy resin matrix)
 IT Holographic **recording** materials
 (holog. **recording** material containing photopolymerizable vinyl monomers and epoxy resin matrix)
 IT Polymerization
 (photopolymn.; holog. **recording** material containing photopolymerizable vinyl monomers and epoxy resin matrix)
 IT Polyethers, uses
 Polyethers, uses
 Polyethers, uses
 (polyamine-epoxy-; holog. **recording** material containing

- photopolymerizable vinyl monomers and epoxy resin matrix)
- IT Epoxy resins, uses
Epoxy resins, uses
Epoxy resins, uses
(polyamine-polyether-; holog. **recording** material
containing photopolymerizable vinyl monomers and epoxy resin
matrix)
- IT 30112-03-9, N-Vinylcarbazole-N-Vinyl-2-pyrrolidinone copolymer
(holog. **recording** in material containing
photopolymerizable vinyl monomers and epoxy resin matrix)
- IT 75-91-2, Tert-Butylhydroperoxide
(holog. **recording** in material containing
photopolymerizable vinyl monomers and epoxy resin matrix)
- IT 88-12-0, N-Vinyl-2-pyrrolidinone, reactions 1484-13-5,
N-Vinylcarbazole
(holog. **recording** material containing photopolymerizable
vinyl monomers and epoxy resin matrix)
- IT 78811-10-6, 1,4-Butanediol diglycidyl ether-diethylenetriamine
copolymer 153972-09-9, Bis(4-glycidyloxyphenyl)methane-m-
xylenediamine copolymer 238752-94-8, 1,2,7,8-Diepoxyoctane-
diethylenetriamine copolymer
(holog. **recording** material containing photopolymerizable
vinyl monomers and epoxy resin matrix)
- IT 111-40-0, Diethylenetriamine 1477-55-0, m-Xylylenediamine
2095-03-6, Bis(4-glycidyloxyphenyl)methane 2425-79-8,
1,4-Butanediol diglycidyl ether 2426-07-5,
1,2,7,8-Diepoxyoctane
130167-23-6
(holog. **recording** material mixture containing
photopolymerizable vinyl monomers and epoxy resin matrix
produced by curing composition containing)
- IT 125051-32-3, Irgacure 784
(photoinitiator; holog. **recording** in material containing
photopolymerizable vinyl monomers and epoxy resin matrix)

REFERENCE COUNT: 47 THERE ARE 47 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS

AVAILABLE

IN THE RE FORMAT

L37 ANSWER 20 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1999:679933 HCAPLUS

DOCUMENT NUMBER: 131:315851

TITLE: **Recording** material for aqueous
ink and its manufacture

INVENTOR(S): Kuwahara, Shoji; Yoshikawa, Takeshi;
Nakagami,

Yoshiaki

PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
-----	----	-----	-----
JP 11291613	A2	19991026	JP 1998-100728

1998

0413

PRIORITY APPLN. INFO.: JP 1998-100728

1998

0413

AB The title **recording** material comprises an **ink**
 -receiving layer formed on at least one side of a support,
 wherein
 the **ink**-receiving layer has microvoids on the surface
 and contains a water-absorbing polyurethane-polyurea 60.0-99.9
 and
 dimethylpolysiloxane-modified acrylic resin 0.1-40.0%. The
 process comprises drying the **ink**-receiving layer at
 50-150° after applying a coating material to form the
ink-receiving layer on the support. The recording material
 evaluated by using **ink-jet** printing and
 gravure printing methods provided sharp images and waterfastness.

IT 247240-90-0

(**ink**-receiving layer of **recording** material
 for aqueous **ink**)

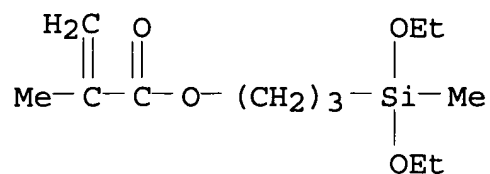
RN 247240-90-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 3-
 (diethoxymethylsilyl)propyl 2-methyl-2-propenoate,
 α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-
 ω -[[dimethyl[3-[(2-methyl-1-oxo-2-
 propenyl)oxy]propyl]silyl]oxy]poly[oxy(dimethylsilylene)], ethyl
 2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA
 INDEX NAME)

CM 1

CRN 65100-04-1

CMF C12 H24 O4 Si

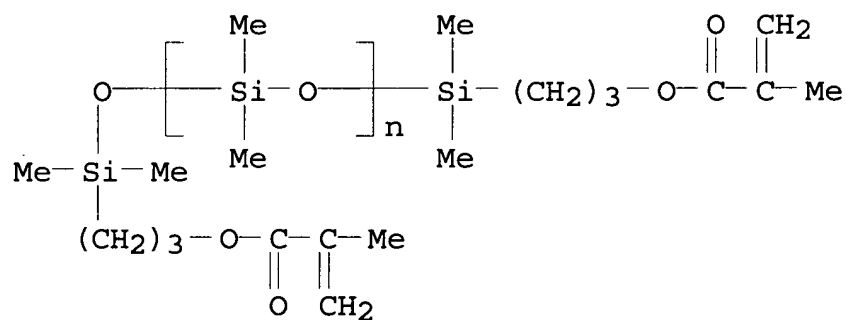


CM 2

CRN 58130-03-3

CMF (C2 H6 O Si)_n C18 H34 O5 Si2

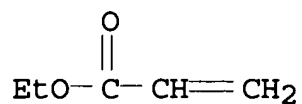
CCI PMS



CM 3

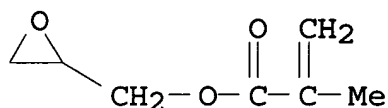
CRN 140-88-5

CMF C5 H8 O2



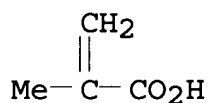
CM 4

CRN 106-91-2
CMF C7 H10 O3



CM 5

CRN 79-41-4
CMF C4 H6 O2



- IC ICM B41M005-00
CC 74-6 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 37, 42
ST polyurethane polyurea aq **ink recording**
material drying process
IT Gravure printing
 Ink-jet printing
 (ink-receiving layer of **recording** material
 for aqueous **ink**)
IT Drying
 (manufacture of **ink**-receiving layer of **recording**
 material for aqueous **ink**)
IT Polyurethanes, uses
 (polyurea-; **ink**-receiving layer of **recording**
 material for aqueous **ink**)
IT Polyureas
 (polyurethane-; **ink**-receiving layer of
 recording material for aqueous **ink**)
IT 26300-51-6, Acrylic acid-butyl acrylate-methyl methacrylate
copolymer 247240-90-0 247240-92-2 247240-94-4
247240-96-6 247240-98-8
 (ink-receiving layer of **recording** material
 for aqueous **ink**)
IT 201858-42-6P 201933-27-9P 247240-88-6P
 (ink-receiving layer of **recording** material

for aqueous ink)

L37 ANSWER 21 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1999:648833 HCAPLUS
 DOCUMENT NUMBER: 131:279296
 TITLE: UV-curable resins, their compositions, and
 solder photoresist inks thereof
 INVENTOR(S): Marusawa, Takashi; Hashimoto, Soichi
 PATENT ASSIGNEE(S): Gooh Chemical Industry Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
-----	----	-----	-----
JP 11279243	A2	19991012	JP 1998-87036

1998

0331

PRIORITY APPLN. INFO.: JP 1998-87036

1998

0331

AB The UV-curable resins have ≥ 2 ethylenically unsatd. groups, CO₂H, and Si and are prepared (i) by reacting HO₂C-containing ethylenically unsatd. monomers and (un)saturated polybasic acid anhydrides with copolymers comprising Si-containing ethylenically unsatd. monomers and epoxy-containing ethylenically unsatd. monomers or (ii) by reacting epoxy-containing ethylenically unsatd. monomers with copolymers comprising Si-containing ethylenically unsatd. monomers and HO₂C-containing ethylenically unsatd. monomers. The compns. contain the UV-curable resins and compds. with ≥ 2 epoxy groups. The solder photoresist inks contain the compns., photopolymn. initiators, and diluents. The inks can be developed using dilute alkali solns. and give solder resists having excellent resistance to solvents, acids, Ag plating, and

electrolytic corrosion.

IT 245727-49-5P, Acrylic acid-glycidyl methacrylate-1-(3-methacryloxypropyl)polydimethylsiloxane-methyl methacrylate-tetrahydrophthalic anhydride copolymer
 245727-51-9P, Acrylic acid-glycidyl methacrylate-1-(3-methacryloxypropyl)polydimethylsiloxane-methyl methacrylate-N-phenylmaleimide copolymer
 (UV-curable silicon-containing acrylic polymers, their compns., and solder photoresist **inks** thereof)

RN 245727-49-5 HCAPLUS

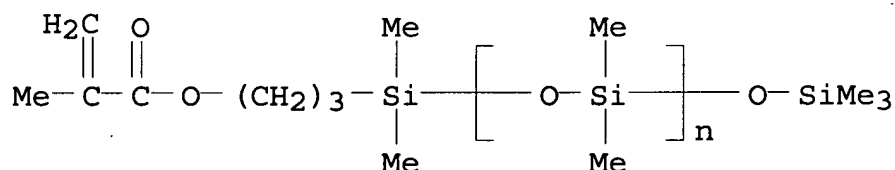
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], oxiranylmethyl 2-methyl-2-propenoate, 2-propenoic acid and 3a,4,7,7a-tetrahydro-1,3-isobenzofurandione (9CI) (CA INDEX NAME)

CM 1

CRN 123109-42-2

CMF (C2 H6 O Si)_n C12 H26 O3 Si2

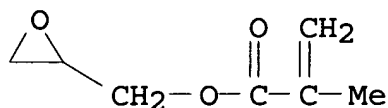
CCI PMS



CM 2

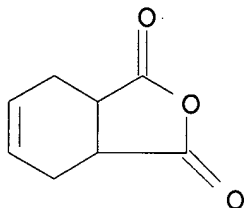
CRN 106-91-2

CMF C7 H10 O3



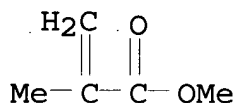
CM 3

CRN 85-43-8
CMF C8 H8 O3



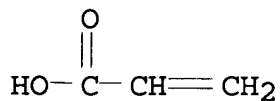
CM 4

CRN 80-62-6
CMF C5 H8 O2



CM 5

CRN 79-10-7
CMF C3 H4 O2

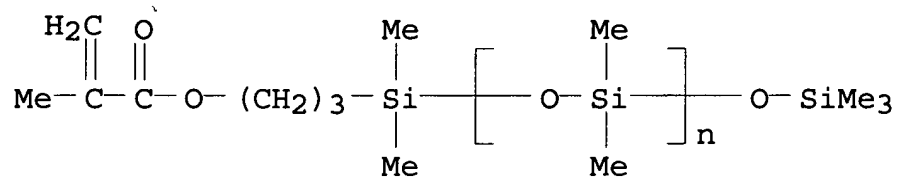


RN 245727-51-9 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with
 α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-
 ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)],
oxiranylmethyl 2-methyl-2-propenoate, 1-phenyl-1H-pyrrole-2,5-
dione and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 123109-42-2
CMF (C2 H6 O Si)_n C12 H26 O3 Si2

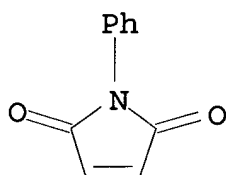
CCI PMS



CM 2

CRN 941-69-5

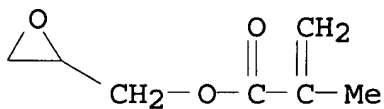
CMF C10 H7 N O2



CM 3

CRN 106-91-2

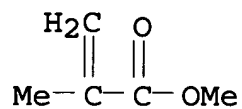
CMF C7 H10 O3



CM 4

CRN 80-62-6

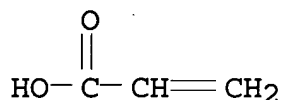
CMF C5 H8 O2



CM 5

CRN 79-10-7

CMF C3 H4 O2



IC ICM C08F299-00

ICS C08F002-48; C08F290-04; C09D011-10; G03F007-027;

G03F007-038;

G03F007-075; H05K003-28; C09D004-00

CC 74-5 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)

Section cross-reference(s): 37, 38

IT Epoxy resins, uses

(UV-curable silicon-containing acrylic polymers, their
compns., andsolder photoresist **inks** thereof)

IT Polysiloxanes, preparation

(acrylic; UV-curable silicon-containing acrylic polymers,
theircompns., and solder photoresist **inks** thereof)

IT Solder resists

Solder resists

(photoresists; UV-curable silicon-containing acrylic polymers,
their compns., and solder photoresist **inks** thereof)

IT Photoresists

Photoresists

(solder; UV-curable silicon-containing acrylic polymers, their
compns., and solder photoresist **inks** thereof)IT **245727-49-5P**, Acrylic acid-glycidyl methacrylate-1-(3-

methacryloxypropyl)polydimethylsiloxane-methyl

methacrylate-tetrahydrophthalic anhydride copolymer

245727-50-8P, Acrylic acid-glycidyl methacrylate-methyl

methacrylate-tetrahydrophthalic anhydride-trimethylsilylmethyl

methacrylate copolymer **245727-51-9P**, Acrylic

acid-glycidyl

methacrylate-1-(3-methacryloxypropyl)polydimethylsil

oxane-methyl methacrylate-N-phenylmaleimide copolymer

(UV-curable silicon-containing acrylic polymers, their
compns., and

solder photoresist **inks** thereof)
 IT 28825-96-9, TEPIC 29570-58-9 71868-10-5, Irgacure 907
 87912-85-4, Epiclon N 680 89118-70-7, YX 4000
 (UV-curable silicon-containing acrylic polymers, their
 compns., and
 solder photoresist **inks** thereof)

L37 ANSWER 22 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1999:648633 HCAPLUS

DOCUMENT NUMBER: 131:264821

TITLE: Adhesive printing paper with metallic luster

INVENTOR(S): Iguchi, Yuji; Nakajima, Toshimitsu

PATENT ASSIGNEE(S): Mitsubishi Paper Mills, Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
-----	----	-----	-----

JP 11277890	A2	19991012	JP 1998-87423

1998

0331

PRIORITY APPLN. INFO.: JP 1998-87423

1998

0331

AB The printing paper comprises on 1 side of a support an adhesive resin layer, a metal foil layer, and an ink receptor layer, and on

the other side of the support a hot-melt adhesive layer. The hot-melt adhesive layer may contain a surfactant and water-soluble

thermoplastics. A heat-insulator layer may be interposed between the support and the hot-melt adhesive layer. The printing paper can be adhered onto a postcard with a hot iron.

IC ICM B41M005-00

ICS B41M005-40; B41M005-38; G09F003-02

CC 74-6 (Radiation Chemistry, **Photochemistry**, and

Photographic and Other Reprographic Processes)

Section cross-reference(s): 38, 43

- IT **Polyoxyalkylenes**, uses
 (PEO 1, surfactant; adhesive printing paper with metallic luster for making printed postcard)
- IT **Polysiloxanes**, uses
 (di-Me, 3-hydroxypropyl Me, ethers with **polyethylene-polypropylene glycol** mono-Me ether, Silwet L 7001, surfactant; adhesive printing paper with metallic luster for making printed postcard)
- IT Ink-jet **recording** sheets
 Thermal-transfer printing materials
 (paper; adhesive printing paper with metallic luster for making printed postcard)

L37 ANSWER 23 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1997:701440 HCAPLUS

DOCUMENT NUMBER: 128:28565

TITLE: Nonagglomerating antifoamant for silver halide

photographic emulsions

INVENTOR(S): Orem, Michael William; Daubendiek, Richard Lee; Oehlbeck, Douglas Lee; Lighthouse, Joseph

George

PATENT ASSIGNEE(S): Eastman Kodak Co., USA

SOURCE: U.S., 5 pp.

CODEN: USXXAM

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
-----	----	-----	-----
US 5681692	A	19971028	US 1996-594611

1996

0202

PRIORITY APPLN. INFO.:

US 1996-594611

1996

0202

AB The invention relates to a solution for forming silver halide emulsions comprising water, gelatin containing less than 30 μmol of methionine per g of gelatin, and at least one antifoamant selected from the group consisting of $\text{RCO}_2(\text{CH}_2\text{CH}_2\text{O})_x\text{OCR}$ wherein RC and CR represent the carbon chains in carboxylic acids with chain lengths of predominantly 12-18 carbon atoms and x has a mean value of 4 to 5 from a mixture with a distribution of values between 2 and 7 and $(\text{H}_3\text{CSi})[(\text{OSi}(\text{CH}_3)_2)_d\text{O}(\text{CH}_2\text{CH}_2\text{CH}_2\text{O})_n\text{C}_4\text{H}_9]_3$ wherein the mol. weight is 2500 to 3500 and d and n have average values of less than 15.

IC ICM G03C001-043
ICS B01D019-04

NCL 430569000

CC 74-2 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

IT **Polyoxyalkylenes**, uses
(di-Me, Me hydrogen **polysiloxane** -, Silwet L-720; antifoamant for silver halide photog. emulsions)

IT **Polysiloxanes**, uses
(di-Me, Me hydrogen, **polyoxyalkylene**-, Silwet L-720; antifoamant for silver halide photog. emulsions)

IT **Polysiloxanes**, uses
(di-Me, [(methylsilylidyne)tris(oxy)]tris-, hydroxy-terminated, ethers with **polyethylene-polypropylene glycol** monoalkyl ether, Silwet L-722; antifoamant for silver halide photog. emulsions)

IT **Polysiloxanes**, uses
(di-Me, modified; antifoamants for silver halide photog. emulsions)

IT **Polyoxyalkylenes**, uses
(tall-oil fatty acid ester derivs.; antifoamant for silver halide photog. emulsions)

L37 ANSWER 24 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 1997:421082 HCAPLUS
DOCUMENT NUMBER: 127:57972
TITLE: Electrophotographic image formation
INVENTOR(S): Kato, Eiichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 42 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
JP 09106202	A2	19970422	JP 1996-208632
US 5725981	A	19980310	US 1996-692238
JP 1995-222778	A		

AB The title image formation uses a photoreceptor having 2 laminated peelable transfer layers to form an electrophotog. toner image and then to thermally transfer the toner image to a **recording** material, wherein the 1st transfer layer is formed by electro-depositing thermoplastic resin particles containing 2 kinds of specified resins with different softening point and glass transition point in 1 particle, and the 2nd transfer layer contains a different resin.

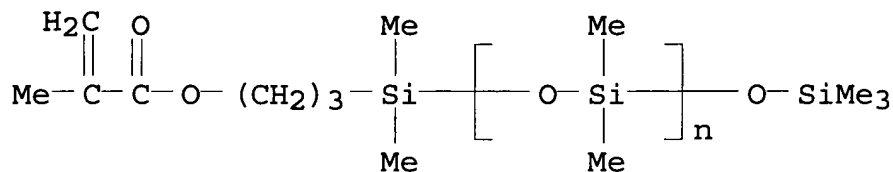
IT **190894-75-8 190894-78-1**
 (used for increasing peeling ability of transfer layer for electrophotog. photoreceptor for image formation)

RN 190894-75-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, ethyl ester, polymer with α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)] and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

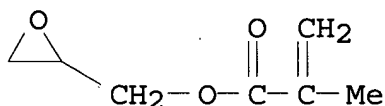
CM 1

CRN 123109-42-2
 CMF (C2 H6 O Si)_n C12 H26 O3 Si2
 CCI PMS



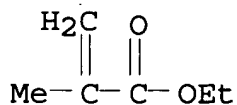
CM 2

CRN 106-91-2
 CMF C7 H10 O3



CM 3

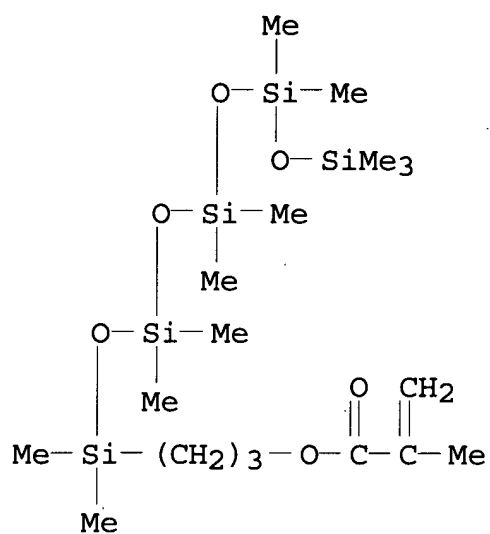
CRN 97-63-2
 CMF C6 H10 O2



RN 190894-78-1 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with methyl 2-propenoate, oxiranylmethyl 2-propenoate and 3-(undecamethylpentasiloxanyl)propyl 2-methyl-2-propenoate (9CI)
 (CA INDEX NAME)

CM 1

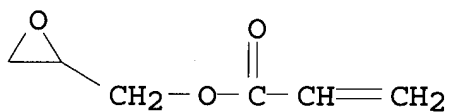
CRN 107642-12-6
 CMF C18 H44 O6 Si5



CM 2

CRN 106-90-1

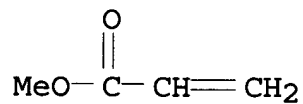
CMF C6 H8 O3



CM 3

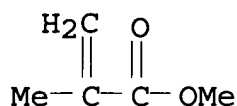
CRN 96-33-3

CMF C4 H6 O2



CM 4

CRN 80-62-6
CMF C5 H8 O2



IC ICM G03G015-16
ICS G03G007-00; G03G015-01
CC 74-3 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT 58258-12-1 162127-42-6 166594-75-8 **190894-75-8**
190894-76-9 190894-77-0D, reaction products with thioethyl
methacrylate **190894-78-1** 190894-79-2 190894-81-6
(used for increasing peeling ability of transfer layer for
electrophotog. photoreceptor for image formation)

L37 ANSWER 25 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 1997:119283 HCAPLUS
DOCUMENT NUMBER: 126:132219
TITLE: Fluorine-containing epoxy resin composition
highly soluble in solvents for adhesives and
photocurable soil-repellent hard coatings

with

good adhesion for **ink-jet**
heads

INVENTOR(S): Imamura, Isao
PATENT ASSIGNEE(S): Canon K. K., Japan
SOURCE: PCT Int. Appl., 57 pp.
CODEN: PIXXD2

DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
-----	----	-----	-----

WO 9641835	A1	19961227	WO 1996-JP1606

1996

0613

W: US

RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC,
NL, PT, SE

EP 779337 A1 19970618 EP 1996-917664

1996

0613

EP 779337 B1 20011024

R: DE, FR, GB, IT

JP 10053639 A2 19980224 JP 1996-152366

1996

0613

JP 3478669 B2 20031215

US 2001008907 A1 20010719 US 1997-776747

1997

0404

US 6291545 B2 20010918

PRIORITY APPLN. INFO.:

JP 1995-146269 A

1995

0613

JP 1996-140192 A

1996

0603

WO 1996-JP1606 W

1996

0613

AB The title composition comprises 5-80% a polyfunctional epoxy resin

having ≥ 2 epoxy groups and being free from F or Si, 5-40%
an epoxy compound having a perfluoro group at its terminal, and
5-80% a compound having ≥ 2 groups selected from epoxy, alc.,
carboxylate, amino and a mixture thereof together with F or Si.

An

adhesive for bonding alumite kettle lid and wood piece comprised
Epikote 828 60, MF-120 10,
1,3-bis(glycidoxypropyl)tetramethyldisi
loxane 30, siloxane group-containing amine hardener LS7430 30,
and

A-187 silane coupler 3 parts.

IT 186294-09-7P 186294-17-7P 186294-22-4P
186294-28-0P 186294-30-4P

(fluorine-containing epoxy resin composition highly soluble in solvents for

adhesives and photocurable soil-repellent hard coatings with good adhesion for **ink-jet** heads)

RN 186294-09-7 HCAPLUS

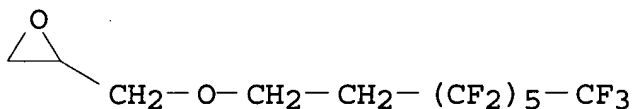
CN Phenol, 4,4'-(1-methylethylidene)bis-, polymer with (chloromethyl)oxirane, 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]disiloxane and

[[(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)oxy]methyl]oxirane
(9CI) (CA INDEX NAME)

CM 1

CRN 122193-68-4

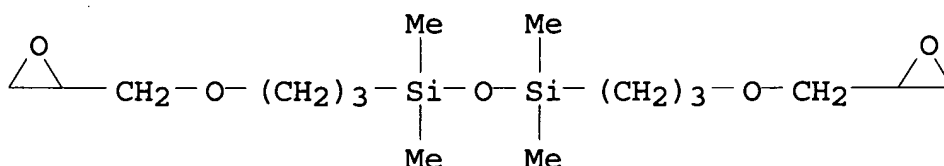
CMF C11 H9 F13 O2



CM 2

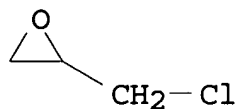
CRN 126-80-7

CMF C16 H34 O5 Si2



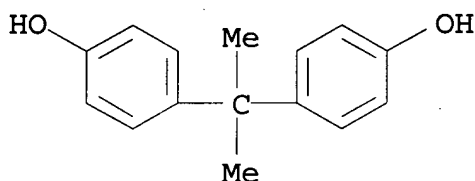
CM 3

CRN 106-89-8
CMF C3 H5 Cl O



CM 4

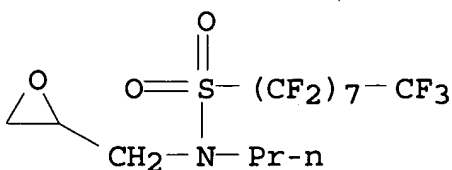
CRN 80-05-7
CMF C15 H16 O2



RN	186294-17-7	HCAPLUS
CN	1-Octanesulfonamide, 1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-N-(oxiranylmethyl)-N-propyl-, polymer with 3-oxiranyl-7-oxabicyclo[4.1.0]heptane, $\alpha,\alpha,\alpha',\alpha'$ -tetrakis(trifluoromethyl)-1,4-benzenedimethanol and 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]disiloxane (9CI) (CA INDEX NAME)	

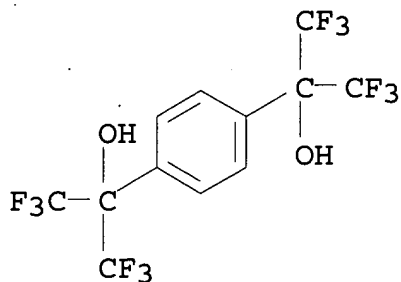
CM 1

CRN 77620-64-5
CMF C14 H12 F17 N O3 S



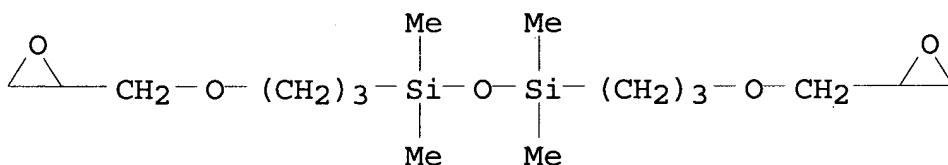
CM 2

CRN 1992-15-0
CMF C12 H6 F12 O2



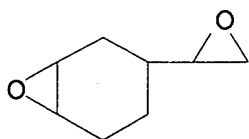
CM 3

CRN 126-80-7
CMF C16 H34 O5 Si2



CM 4

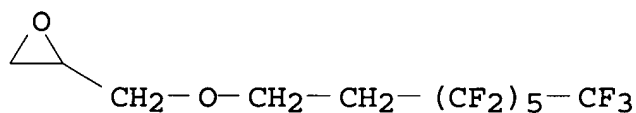
CRN 106-87-6
CMF C8 H12 O2



RN 186294-22-4 HCAPLUS
CN Disiloxane,
1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]-
, polymer with [[(3,3,4,4,5,5,6,6,7,7,8,8,8-
tridecafluorooctyl)oxy]methyl]oxirane (9CI) (CA INDEX NAME)

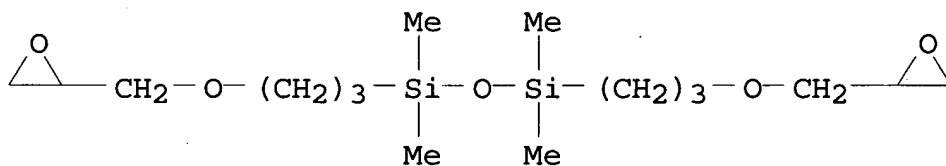
CM 1

CRN 122193-68-4
CMF C11 H9 F13 O2



CM 2

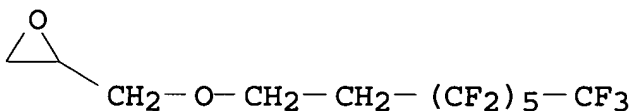
CRN 126-80-7
CMF C16 H34 O5 Si2



RN	186294-28-0	HCAPLUS
CN	7-Oxabicyclo[4.1.0]heptane-3-carboxylic acid, 7-oxabicyclo[4.1.0]hept-3-ylmethyl ester, polymer with 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]disiloxane and [[(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)oxy)methyl]oxirane (9CI) (CA INDEX NAME)	

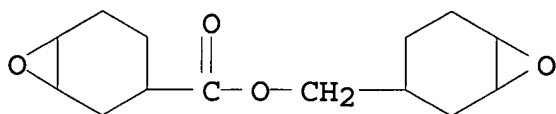
CM 1

CRN 122193-68-4
CMF C11 H9 F13 O2



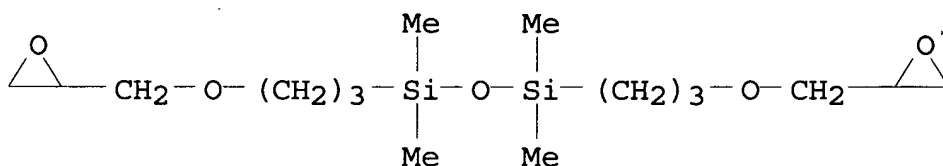
CM 2

CRN 2386-87-0
CMF C14 H20 O4



CM 3

CRN 126-80-7
CMF C16 H34 O5 Si2



RN 186294-30-4 HCAPLUS
CN Phenol, 4,4'-(1-methylethylidene)bis-, polymer with Cefral Coat A 101B, (chloromethyl)oxirane and 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]disiloxane (9CI) (CA INDEX NAME)

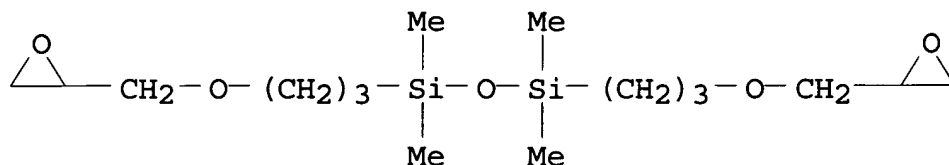
CM 1

CRN 137802-09-6
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

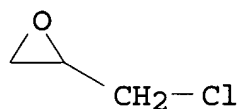
CRN 126-80-7
CMF C16 H34 O5 Si2



CM 3

CRN 106-89-8

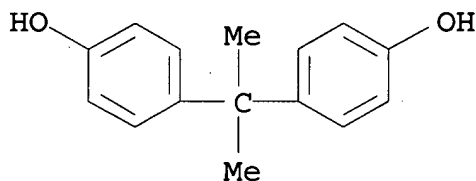
CMF C3 H5 Cl O



CM 4

CRN 80-05-7

CMF C15 H16 O2



IC ICM C08L063-00

ICS C08G059-20; C08G059-40; C09D163-00; C09J163-00; B41J002-05

CC 37-6 (Plastics Manufacture and Processing)

Section cross-reference(s): 74

ST epoxy compn fluorine contg adhesive; **ink jet**
head epoxy resin; coating fluorine contg epoxy resin

IT Adhesives

Printing apparatus

Ships

(fluorine-containing epoxy resin composition highly soluble
in solvents for
adhesives and photocurable soil-repellent hard coatings with
good adhesion for **ink-jet** heads)

IT Epoxy resins, uses
(fluorine-containing epoxy resin composition highly soluble
in solvents for
adhesives and photocurable soil-repellent hard coatings with
good adhesion for **ink-jet** heads)

IT Coating materials
(for ships; fluorine-containing epoxy resin composition
highly soluble in
solvents for adhesives and photocurable soil-repellent hard
coatings with good adhesion for **ink-jet**
heads)

IT 30603-97-5P **186294-09-7P** 186294-11-1P 186294-13-3P
186294-15-5P **186294-17-7P** 186294-20-2P
186294-22-4P 186294-24-6P 186294-26-8P 186294-27-9P
186294-28-0P 186294-29-1P **186294-30-4P**
186294-32-6P
(fluorine-containing epoxy resin composition highly soluble
in solvents for
adhesives and photocurable soil-repellent hard coatings with
good adhesion for **ink-jet** heads)

L37 ANSWER 26 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1997:8913 HCAPLUS

DOCUMENT NUMBER: 126:39656

TITLE: Electrostatographic toner particles
comprising

polysiloxane-modified resins
INVENTOR(S): Tavernier, Serge; Marien, August; Op De
Beeck,

Werner
PATENT ASSIGNEE(S): Agfa-Gevaert Naamloze Vennootschap, Belg.
SOURCE: Eur. Pat. Appl., 23 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
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EP 740217	A1	19961030	EP 1996-200738

1996

0318

R: BE, DE, FR, GB, NL
US 5620825 A 19970415 US 1996-617327

1996

0318
JP 08297380 A2 19961112 JP 1996-90453

1996

0319
JP 3089206 B2 20000918
US 5888657 A 19990330 US 1997-786022

1997

0121
PRIORITY APPLN. INFO.: EP 1995-200723 A

1995

0323
US 1996-617327 A3

1996

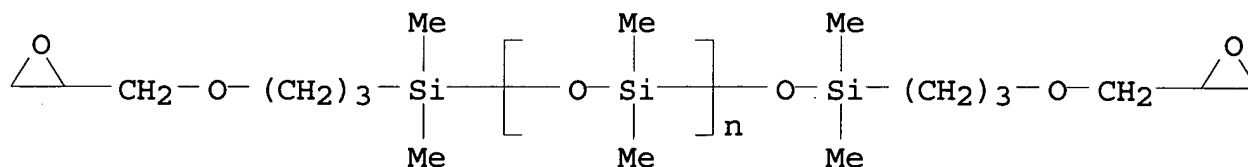
0318

AB There are provided dry electrostatog. toner particles wherein the toner resin comprises more than 10% by weight of one or more polysiloxane-modified resins. In these resins the polysiloxane moieties are attached to the other polymeric moieties of the copolymers over an ether group or an ester group. In a preferred embodiment the toner resin of the toner particles consists of one or more polysiloxane-modified resins.

IT 130167-23-6
(reaction with linear polyesters for preparing electrostatog. toners)

RN 130167-23-6 HCAPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]- (9CI) (CA INDEX NAME)



IC ICM G03G009-087
 CC 74-3 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
 IT **Recording**
 (magneto-; toners containing polysiloxane-modified resins for)
 IT **130167-23-6**
 (reaction with linear polyesters for preparing electrostatog.
 toners)

L37 ANSWER 27 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1996:595883 HCAPLUS
 DOCUMENT NUMBER: 125:234486
 TITLE: Photosensitive composition for volume
 hologram

recording, recording medium
 using the same and volume hologram formation
 method

INVENTOR(S): Sato, Masahiko; Mizutani, Kenzo; Kawabata,
 Masami; Sumyoshi, Iwao
 PATENT ASSIGNEE(S): Nippon Paint Co Ltd, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
JP 08160842	A2	19960621	JP 1995-254947
JP 3532675	B2	20040531	
US 5702846	A	19971230	US 1997-808546

0228

PRIORITY APPLN. INFO.:

JP 1994-238927

A1

1994

1003

US 1995-536103

B1

1995

0929

AB In the title composition comprising a cationic polymerizable compound, a

radical polymerizable compound, a cationic polymerization initiator and a

radical polymerization initiator, the cationic polymerizable compound

and/or the radical polymerizable compound contain siloxane linkage.

The radical polymerization initiator may contain a cyanine dye as a

sensitizer and a diaryl iodonium salt as an active radical generation compound The composition showed excellent

light-resistance

and heat-resistance.

IT 31305-85-8, TSL 9906

(siloxane linkage-containing cationic polymerizable compound of

photosensitive composition for volume hologram **recording**)

RN 31305-85-8 HCAPLUS

CN Disiloxane,

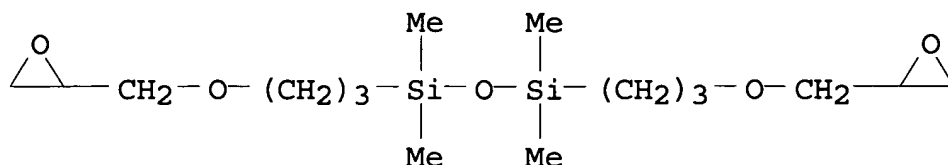
1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]-

, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 126-80-7

CMF C16 H34 O5 Si2



- IC ICM G03H001-02
ICS C08G059-40; G02B001-04; G03F007-004; G03F007-027;
G03F007-029; G03F007-075; G03H001-04; G03H001-28
- CC 74-8 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
- ST photosensitive compn vol hologram **recording**
- IT Holography
(photosensitive composition for volume hologram **recording**,
recording medium using the same and volume hologram
formation method)
- IT **Recording** materials
(holog., photosensitive composition for volume hologram
recording, **recording** medium using the same
and volume hologram formation method)
- IT Holography
(**recording** materials, photosensitive composition for volume
hologram **recording**, **recording** medium using
the same and volume hologram formation method)
- IT 17578-95-9 66003-76-7, Diphenyliodonium
trifluoromethanesulfonate
(radical polymerization initiator of photosensitive
composition for volume
hologram **recording**)
- IT 31305-85-8, TSL 9906 121225-97-6, XC 96B0370
(siloxane linkage-containing cationic polymerizable compound
of
photosensitive composition for volume hologram **recording**)
- IT 18151-85-4, TSL 9705 18547-93-8, TSL 9706 178953-28-1, PS 2A
(siloxane linkage-containing radical polymerizable compound of
photosensitive composition for volume hologram **recording**)

L37 ANSWER 28 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1996:449206 HCAPLUS

DOCUMENT NUMBER: 125:100301

TITLE: Photosensitive composition, volume hologram
recording material using it, hologram,
and its formation

INVENTOR(S): Sato, Masahiko; Mizutani, Kenzo; Kawabata,
Masami; Sumyoshi, Iwao

PATENT ASSIGNEE(S): Nippon Paint Co Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
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JP 08101500	A2	19960416	JP 1994-238932

1994

1003

JP 3532621 B2 20040531

PRIORITY APPLN. INFO.: JP 1994-238932

1994

1003

AB The composition contains (A) a siloxane-containing polymer binder (B) a radically polymerizable compound, (C) a cationic polymerizable compound, (D) a radical polymerization initiator, and (E) a cationic polymerization initiator. The material has a **recording** layer obtained from the composition. The title **recording** method involves the steps of (A) exposing the material to a laser or coherence interference pattern and (B) irradiating with UV light and/or visible light and/or (C) heating. The obtained hologram with good heat and light resistance is also claimed.

IT 31305-85-8P

(siloxane-containing photosensitive composition for volume hologram

recording material and formation of hologram)

RN 31305-85-8 HCAPLUS

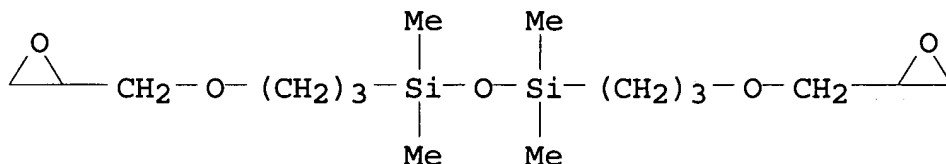
CN Disiloxane,

1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]-
, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 126-80-7

CMF C16 H34 O5 Si2



- IC ICM G03F007-004
ICS G03F007-027; G03F007-029; G03F007-033; G03F007-075;
G03F007-20; G03H001-02; G03H001-04
- CC 74-8 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
- IT Dyes, cyanine
(sensitizer; siloxane-containing photosensitive composition
for volume
hologram **recording** material and formation of
hologram)
- IT Holography
Photoimaging compositions and processes
Polymerization catalysts
(siloxane-containing photosensitive composition for volume
hologram
recording material and formation of hologram)
- IT Siloxanes and Silicones, uses
(siloxane-containing photosensitive composition for volume
hologram
recording material and formation of hologram)
- IT 66003-76-7, Diphenyliodonium trifluoromethanesulfonate
104558-94-3, UVI 6974 146297-31-6
(siloxane-containing photosensitive composition for volume
hologram
recording material and formation of hologram)
- IT 9051-49-4P, Pentaerythritol-propylene oxide copolymer
31305-85-8P 143410-64-4P 178953-29-2P 178953-32-7P
(siloxane-containing photosensitive composition for volume
hologram
recording material and formation of hologram)
- IT 178953-30-5, Ethyl acrylate-TSL 9705 copolymer
(siloxane-containing photosensitive composition for volume
hologram
recording material and formation of hologram)

L37 ANSWER 29 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1996:280445 HCAPLUS
 DOCUMENT NUMBER: 124:292552
 TITLE: Aqueous surface treating agents for plastic films for magnetic tapes or thermal-transfer sheets
 INVENTOR(S): Iguchi, Yoshinori; Takahashi, Naohiro; Kuwata,
 Satoshi
 PATENT ASSIGNEE(S): Shinetsu Chemical Industry. Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
JP 08045070	A2	19960216	JP 1994-182043

1994

0803

JP 3481683

B2

20031222

PRIORITY APPLN. INFO.:

JP 1994-182043

1994

0803

AB Title agents, with good adhesion, comprise (A) aqueous dispersions of branched non-fluidable silicones containing $R_{12}SiO_{2/2}$ and $R_1SiO_{3/2}$ (R_1 = C1-20 hydrocarbyl), (B) aqueous dispersions of $R_2R_3N(CH_2)_a[NR_4(CH_2)_b]cSiR_5(OR_6)_2$ (R_2-R_4 = H, C1-6 hydrocarbyl; R_5, R_6 = C1-6 hydrocarbyl; a, b = 1-6; c = 0-3) hydrolyzates, and (C) aqueous polyurethanes at an effective component of A/B/C of 9-90:0.1-40:9-90. An aqueous composition containing 49.4:0.6:50.0 octamethylcyclotetrasiloxane-phenyltriethoxysilane copolymer/3-aminopropylmethyldimethoxysilane/Elastron H 3 (reactive polyester-polyurethane) was applied on a PET film and baked to form a film showing dynamic friction coefficient 0.17 and good

soil resistance.

IT 170099-69-1

(aminosiloxane/polyurethane-containing aq coatings for plastic films for magnetic tapes or thermal-transfer sheets)

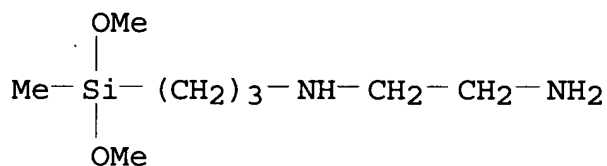
RN 170099-69-1 HCAPLUS

CN 1,2-Ethanediamine, N-[3-(dimethoxymethylsilyl)propyl]-, polymer with diethoxymethyl[3-(oxiranylmethoxy)propyl]silane, octamethylcyclotetrasiloxane and triethoxyphenylsilane (9CI) (CA INDEX NAME)

CM 1

CRN 3069-29-2

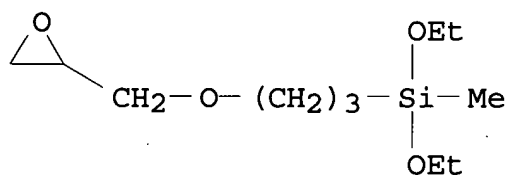
CMF C8 H22 N2 O2 Si



CM 2

CRN 2897-60-1

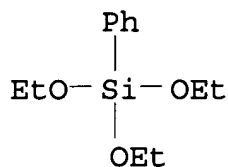
CMF C11 H24 O4 Si



CM 3

CRN 780-69-8

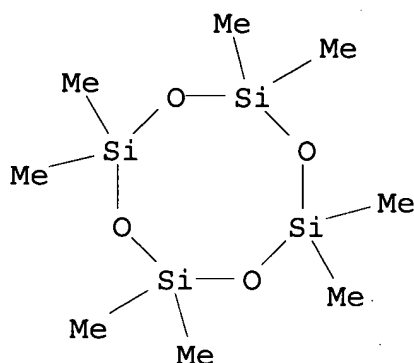
CMF C12 H20 O3 Si



CM 4

CRN 556-67-2

CMF C8 H24 O4 Si4



IC ICM G11B005-84

ICS B41M005-40; C08K005-54; C08L075-04; C08L083-04; C09D175-04;
C09D183-04

ICA B42D015-10

CC 42-10 (Coatings, Inks, and Related Products)
Section cross-reference(s): 74, 77IT **Recording** apparatus(magnetic tapes, aminosiloxane/polyurethane-containing aq
coatings
for plastic films for magnetic tapes or thermal-transfer
sheets)

IT 118478-14-1, Superflex 110 170099-69-1

(aminosiloxane/polyurethane-containing aq coatings for plastic
films for magnetic tapes or thermal-transfer sheets)

L37 ANSWER 30 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1995:849672 HCAPLUS

DOCUMENT NUMBER: 124:11046

TITLE: Water-based crosslinked siloxane-vinyl

INVENTOR(S): compound copolymer emulsions for coatings
Noda, Itsupei; Ishikawa, Masami; Yamawaki,
Masaji
PATENT ASSIGNEE(S): Takemoto Oil & Fat Co Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
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JP 07196750	A2	19950801	JP 1993-355410

1993

1229

JP 3361593	B2	20030107	
PRIORITY APPLN. INFO.:			JP 1993-355410

1993

1229

AB The compns. comprise 90-99/1-10 mixts. of linear units comprising R1R2SiO, R3SiX1O (I), and/or R4Si(Z1Y1)O (II) and crosslinked units comprising R5SiO3/2, SiX2O3/2 (III), Si(Z2Y2)O3/2 (IV), and/or SiO2 [R1-R5 = radically nonpolymerizable hydrocarbyl; X1, X2 = radically nonpolymerizable epoxy-containing

group-substituted

hydrocarbyl; Y1, Y2 = glycidyl (meth)acrylate-C1-4-alkyl (meth)acrylate (in 1-99:1-99 weight ratio) graft copolymer.

segment;

Z1, Z2 = divalent organic linking group], in which I + III form 0.5-15 mol%, II + IV form 0.5-5 mol%, and Y1 + Y2 form 25-75

weight%.

The compns. are useful for magnetic **recording** materials, printing plates, photog. materials, etc., showing surface smoothness and affinity to **inks** or adhesives. Thus, 97.7 g octamethylcyclotetrasiloxane was polymerized with 4.7 g (γ -glycidoxypopyl)trimethoxysilane and 5.0 g (γ -methacryloyloxypropyl)trimethoxysilane, then further treated with 100 g 48:48:4 mixture of Et acrylate, Me methacrylate,

and glycidyl methacrylate and K persulfate to give an aqueous emulsion, which was applied to a film to give a test piece showing good peeling resistance.

IT 171609-55-5P

(aqueous emulsions of siloxane-acrylate graft copolymers for coatings)

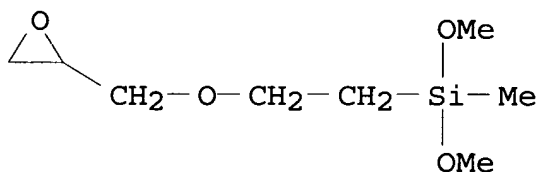
RN 171609-55-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with dimethoxymethyl[2-(oxiranylmethoxy)ethyl]silane, ethyl 2-propenoate, octamethylcyclotetrasiloxane, oxiranylmethyl 2-methyl-2-propenoate, trimethoxymethylsilane and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

CRN 171609-54-4

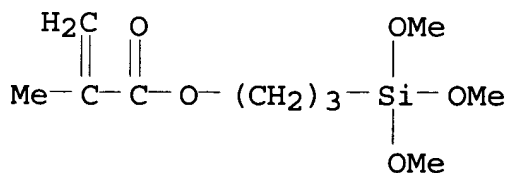
CMF C8 H18 O4 Si



CM 2

CRN 2530-85-0

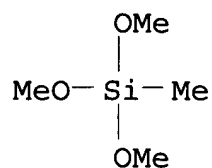
CMF C10 H20 O5 Si



CM 3

CRN 1185-55-3

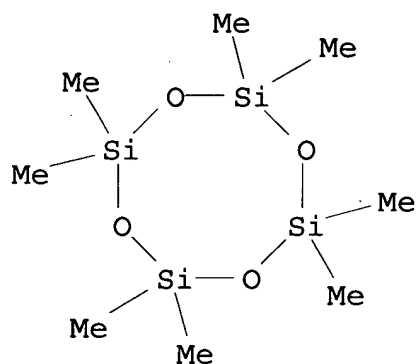
CMF C4 H12 O3 Si



CM 4

CRN 556-67-2

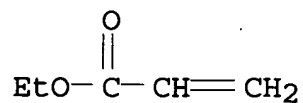
CMF C8 H24 O4 Si4



CM 5

CRN 140-88-5

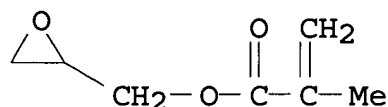
CMF C5 H8 O2



CM 6

CRN 106-91-2

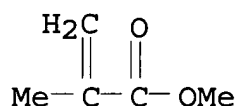
CMF C7 H10 O3



CM 7

CRN 80-62-6

CMF C5 H8 O2



IC ICM C08F283-12

ICS C09D151-08

CC 42-7 (Coatings, Inks, and Related Products)

Section cross-reference(s): 74

IT 171609-52-2P 171609-53-3P **171609-55-5P** 171609-56-6P

171609-57-7P

(aqueous emulsions of siloxane-acrylate graft copolymers for coatings)

L37 ANSWER 31 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1995:689971 HCAPLUS

DOCUMENT NUMBER: 123:70486

TITLE: Antistatic coating materials for **recording** media

INVENTOR(S): Kamyama, Kenichi

PATENT ASSIGNEE(S): Kao Corp, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
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JP 07070555	A2	19950314	JP 1993-158388

1993

0629

JP 3552060

B2

20040811

US 5534322

A

19960709

US 1994-231749

1994

0425

PRIORITY APPLN. INFO.:

JP 1993-158388

A

1993

0629

JP 1994-55725

A

1994

0325

AB The title materials comprise (A) polymerizable compds. containing (meth)acryloyl groups, (B) reactive-functional group-containing antistatic agents containing quaternary ammonium salt groups, ethylene glycol chains, C₂4 hydrocarbon groups, and polymerizable groups, and (C) silicone compds.

IT 165182-57-0P

(antistatic coating materials for **recording** media)

RN 165182-57-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(dihydroxymethylsilyl)propyl ester,

polymer with dimethylsilanediol, α, α' -[[[(4-ethenylphenyl)methyl]octadecyliminio]di-2,1-ethanediyl]bis[ω -hydroxypoly(oxy-1,2-ethanediyl)] dichloride, α -hydro- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl) ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), methylsilanediol,

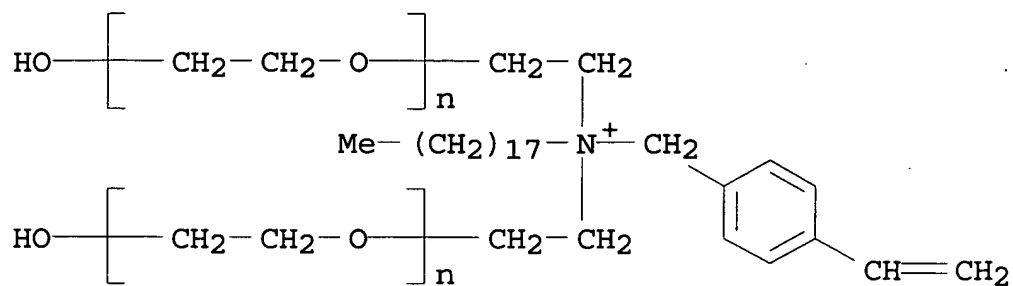
oxirane and α -(1-oxo-2-propenyl)- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl), graft (9CI) (CA INDEX NAME)

CM 1

CRN 159969-22-9

CMF (C2 H4 O)n (C2 H4 O)n C31 H56 N O2 . Cl

CCI PMS

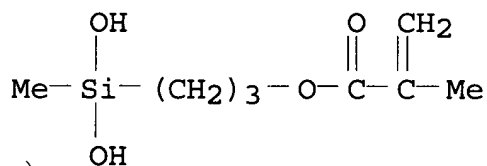


- Cl^-

CM 2

CRN 156787-79-0

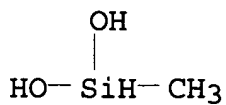
CMF C8 H16 O4 Si



CM 3

CRN 43641-90-3

CMF C H6 O2 Si



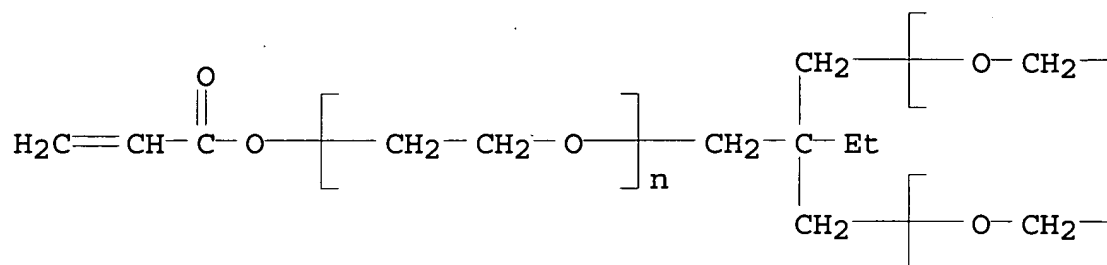
CM 4

CRN 28961-43-5

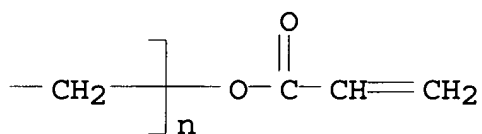
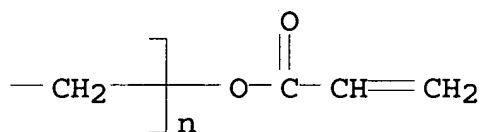
$$\text{CMF} \quad (\text{C}_2 \text{ H}_4 \text{ O})_n \quad (\text{C}_2 \text{ H}_4 \text{ O})_n \quad (\text{C}_2 \text{ H}_4 \text{ O})_n \quad \text{C}_{15} \text{ H}_{20} \text{ O}_6$$

CCI PMS

PAGE 1-A



PAGE 1-B

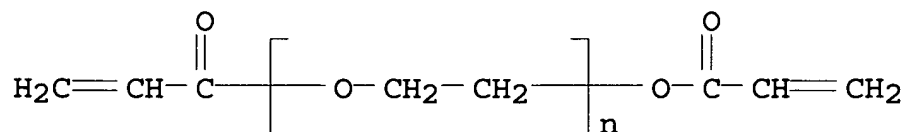


CM 5

CRN 26570-48-9

CMF (C2 H4 O)_n C6 H6 O3

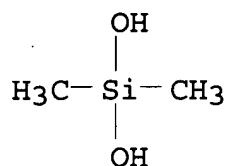
CCI PMS



CM 6

CRN 1066-42-8

CMF C2 H8 O2 Si



CM 7

CRN 75-21-8

CMF C2 H4 O



IT 201419-38-7DP, trrimethylsilyl-terminated
(polymerizable silicone compds. of antistatic coating materials)

RN 201419-38-7 HCAPLUS

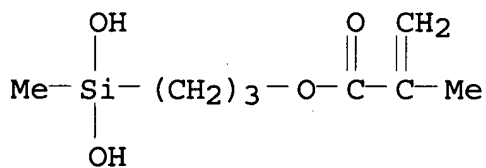
CN 2-Propenoic acid, 2-methyl-, 3-(dihydroxymethylsilyl)propyl ester,

polymer with dimethylsilanediol, methylsilanediol and oxirane, graft (9CI) (CA INDEX NAME)

CM 1

CRN 156787-79-0

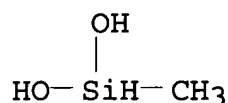
CMF C8 H16 O4 Si



CM 2

CRN 43641-90-3

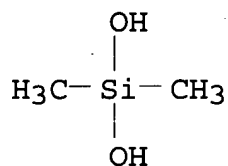
CMF C H6 O2 Si



CM 3

CRN 1066-42-8

CMF C2 H8 O2 Si



CM 4

CRN 75-21-8

CMF C2 H4 O



IC ICM C09K003-16

ICS C09K003-16; G11B007-24

CC 74-12 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
 Section cross-reference(s): 42, 77

ST antistatic coating material **recording** media

IT Coating materials
 (antistatic, antistatic coating materials for **recording**
 media)

IT Memory devices
 (magneto-optical disks, antistatic coating materials for
recording media)

IT Memory devices
 (optical disks, read-only, antistatic coating materials for
recording media)

IT Coating materials
(photocurable, scratch-resistant, antistatic coating materials
for **recording** media)
IT 165182-56-9P **165182-57-0P** 165182-58-1P
(antistatic coating materials for **recording** media)
IT **201419-38-7DP**, trimethylsilyl-terminated
(polymerizable silicone compds. of antistatic coating
materials)

L37 ANSWER 32 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1995:621508 HCAPLUS

DOCUMENT NUMBER: 123:22083

TITLE: Method and apparatus for forming
electrophotographic color transferred image

INVENTOR(S): Kato, Eiichi; Osawa, Sadao; Nakazawa, Yusuke

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: PCT Int. Appl., 108 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
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WO 9423345	A1	19941013	WO 1994-JP487
1994			
0325			
W: JP, US			
RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL,			
PT, SE			
JP 06337599	A2	19941206	JP 1993-349754
1993			
1228			
EP 651295	A1	19950503	EP 1994-910540
1994			
0325			
EP 651295	B1	19980610	
R: DE, GB			

US 5747214

A

19980505

US 1994-343476

1994

1125

PRIORITY APPLN. INFO.:

JP 1993-90488

A

1993

0326

JP 1993-93832

A

1993

0330

WO 1994-JP487

W

1994

0325

AB On the surface of an electrophotog. photosensitive element, a compound containing fluorine atoms and/or silicon atoms is provided in order to form a peelable transfer layer on the photosensitive element, a toner image of ≥ 1 colors is formed on the transfer layer by electrophotog. process, and then the toner image is transferred to a transfer material together with the transfer layer. A color copy of high-definition and high quality can be easily and stably obtained without any color misregistration, and a color image with stable preservability can be formed.

IC ICM G03G013-16
ICS G03G015-16

CC 74-3 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

IT Rubber, silicone, uses
Siloxanes and Silicones, uses
(transfer layer for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(aminoalkyl **di-Me**, KF 804; transfer layer for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(carboxy-containing, X-22-3701E; transfer layer for electrophotog.

- photoreceptor)
- IT **Siloxanes** and Silicones, uses
(di-Me, transfer layer for electrophotog. photoreceptor)
- IT **Polyoxyalkylenes**, uses
(di-Me siloxane-, transfer layer for electrophotog. photoreceptor)
- IT **Siloxanes** and Silicones, uses
(di-Me, 3-hydroxypropyl Me, ethoxylated, transfer layer for electrophotog. photoreceptor)
- IT **Siloxanes** and Silicones, uses
(di-Me, [(methylsilylidyne)tris(oxy)]tris-, hydroxy-terminated, ethers with **polyethylene-polypropylene glycol** monoalkyl ether, transfer layer for electrophotog. photoreceptor)
- IT **Siloxanes** and Silicones, uses
(di-Me, carboxy-terminated, TSF 4770; TSF 411; transfer layer for electrophotog. photoreceptor)
- IT **Siloxanes** and Silicones, uses
(di-Me, epoxy-containing, XF42-A5041; transfer layer for electrophotog. photoreceptor)
- IT **Siloxanes** and Silicones, uses
(di-Me, mercaptopropyl group-terminated, transfer layer for electrophotog. photoreceptor)
- IT **Siloxanes** and Silicones, uses
(di-Me, **polyoxyalkylene**-, transfer layer for electrophotog. photoreceptor)
- IT **Polyoxyalkylenes**, uses
(fluorine-containing, transfer layer for electrophotog. photoreceptor)
- IT **Siloxanes** and Silicones, uses
(hydroxy-terminated, transfer layer for electrophotog. photoreceptor)
- IT Fluoropolymers
Siloxanes and Silicones, uses
(**polyoxyalkylene**-, transfer layer for electrophotog. photoreceptor)
- IT **Polyoxyalkylenes**, uses
(**siloxane**-, transfer layer for electrophotog. photoreceptor)
- IT 75-21-8D, Oxirane, reaction products with **siloxanes**
82030-84-0, SURFLONS141 91105-71-4, SURFLONS-382 144070-79-1
163916-20-9 163916-21-0 163916-22-1 163916-23-2
163916-24-3 163916-27-6 163916-28-7 163916-29-8
164104-57-8 173611-09-1
(transfer layer for electrophotog. photoreceptor)

L37 ANSWER 33 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1995:248292 HCAPLUS
 DOCUMENT NUMBER: 122:20401
 TITLE: Magnetic particles used for
 electrophotographic and electrostatic
recording, and manufacture thereof
 INVENTOR(S): Shiozaki, Masaya; Kikuta, Shinji; Edahiro,
 Kazuhisa
 PATENT ASSIGNEE(S): Mita Industrial Co Ltd, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
JP 06102708	A2	19940415	JP 1992-253138

1992

0922

JP 3216916 B2 20011009
 PRIORITY APPLN. INFO.: JP 1992-253138

1992

0922

AB The title magnetic particles comprise magnetic powder whose
 surface is bonded with a polymer via a coupling agent. The
 manufacture
 comprises processing the powder with the coupling agent to
 introduce a functional group on the surface, attaching a
 polymerization
 initiator to the functional group, and polymerizing a vinyl
 monomer in
 a dispersed medium containing the particles. The magnetic
 particles
 exhibited excellent dispersibility and affinity with a binder
 resin.

IT 159654-95-2P
 (magnetic particles bonded with polymers)

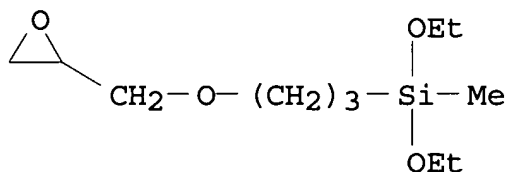
RN 159654-95-2 HCAPLUS

CN · 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
 diethenylbenzene,
 diethoxymethyl[3-(oxiranylmethoxy)propyl]silane,
 ethenylbenzene and 2,2'-oxybis[ethanol] (9CI) (CA INDEX NAME)

CM 1

CRN 2897-60-1

CMF C11 H24 O4 Si

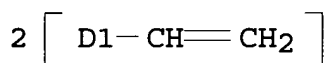
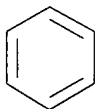


CM 2

CRN 1321-74-0

CMF C10 H10

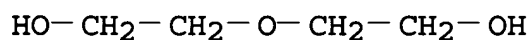
CCI IDS



CM 3

CRN 111-46-6

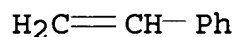
CMF C4 H10 O3



CM 4

CRN 100-42-5

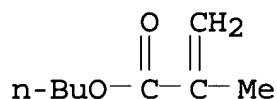
CMF C8 H8



CM 5

CRN 97-88-1

CMF C8 H14 O2



IC ICM G03G009-107

ICS C08F002-00; C08F002-18; C08F002-44; C08F004-02; G03G009-083

CC 74-3 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38

ST magnetic particle electrophotog; electrostatic **recording**
 magnetic particle

IT **Recording**
 (elec., magnetic particles bonded with polymers)

IT 159654-94-1P **159654-95-2P** 159654-96-3P
 (magnetic particles bonded with polymers)

L37 ANSWER 34 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1995:192032 HCAPLUS

DOCUMENT NUMBER: 122:20587

TITLE: Thermal transfer dye-donating material

INVENTOR(S): Kubodera, Seiichi

PATENT ASSIGNEE(S): Fuji Photo Film Co Ltd, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 31 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			

JP 06099667

A2

19940412

JP 1992-276834

1992

0922

PRIORITY APPLN. INFO.:

JP 1992-276834

1992

0922

AB The title material is obtained by coating and drying on a support a dye-donating layer composition containing a thermal migration type dye, a

binder resin, a mold releasing agent, and a F-containing compound in an

organic solvent of b.p. 100-170°. The thermal transfer dye-donating material can give stable images with high-d. and sharpness.

IC ICM B41M005-30

CC 74-7 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 42

IT **Siloxanes** and Silicones, uses

(amino, as mold releasing agent contained in thermal transfer dye-donating type material)

IT **Polyoxyalkylenes**, uses

(**di-Me siloxane**-, as mold releasing agent contained in thermal transfer dye-donating type material)

IT **Siloxanes** and Silicones, uses

(**di-Me**, hydroxypropyl Me, ethers with **polyethylene-polypropylene glycol mono-Pr ether**, [(trimethylsilyl)oxy]-terminated; as mold releasing agent contained in thermal transfer dye-donating type material)

IT **Siloxanes** and Silicones, uses

(**di-Me**, **polyoxyalkylene**-, as mold releasing agent contained in thermal transfer dye-donating type material)

IT **Siloxanes** and Silicones, uses

(epoxy, as mold releasing agent contained in thermal transfer

dye-donating type material)
 IT Epoxy resins, uses
 (siloxane-, as mold releasing agent contained in
 thermal transfer dye-donating type material)

L37 ANSWER 35 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1994:545411 HCAPLUS

DOCUMENT NUMBER: 121:145411

TITLE: Thermal transfer **recording** material

INVENTOR(S): Tanaka, Kazuyoshi; Hashimoto, Yutaka; Kamei, Masayuki

PATENT ASSIGNEE(S): Dainippon Ink & Chemicals, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
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JP 05185757	A2	19930727	JP 1992-4835

1992

0114

JP 3209281

B2

20010917

PRIORITY APPLN. INFO.:

JP 1992-4835

1992

0114

AB In the title material consisting of a base film, an **ink** layer on 1 side of the base film, and a synthetic resin layer on the other side, the above resin layer contains a resin containing fluorinated-alkyl and polyorganosiloxo groups and, optionally, in addition, polyoxyalkylene or polyoxyalkylene and alkyl groups.

The

above resin consists of a polymer obtained from a fluorinated-alkyl group-containing ethylenic monomer and a polyorgnosiloxo group-containing ethylenic monomer and,

optionally, in

addition, a polyoxyalkylene group-containing ethylenic monomer

and

alkylene group-containing ethylenic monomer. The material treated with the above resin has anti-sticking characteristics and provides high-resolution and high-quality printings at high speed printing.

IT 157382-57-5

(treatment agent containing, thermal printing material treated)

RN 157382-57-5 HCAPLUS

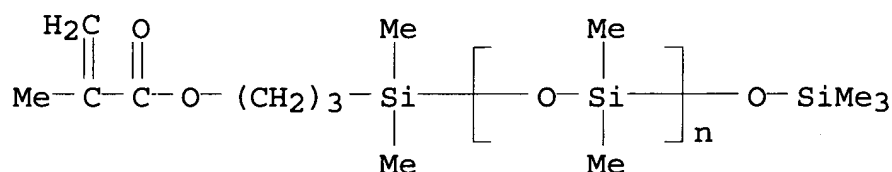
CN 2-Propenoic acid, dodecyl ester, polymer with α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], α -(ethenyldimethylsilyl)- ω -[(ethenyldimethylsilyl)oxy]poly[oxy(dimethylsilylene)], 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-propenoate and methyloxirane polymer with oxirane 2-[(1-oxo-2-propenyl)oxy]ethyl ester (9CI) (CA INDEX NAME)

CM 1

CRN 123109-42-2

CMF (C2 H6 O Si)_n C12 H26 O3 Si2

CCI PMS

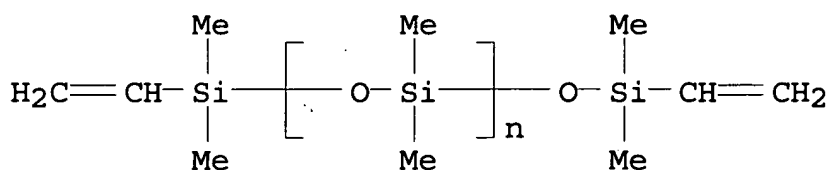


CM 2

CRN 59942-04-0

CMF (C2 H6 O Si)_n C8 H18 O Si2

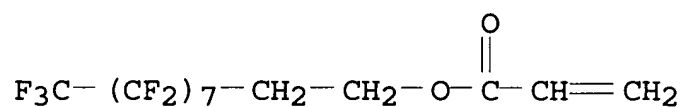
CCI PMS



CM 3

CRN 27905-45-9

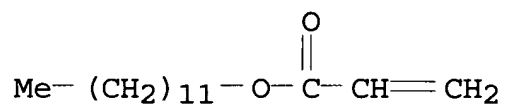
CMF C13 H7 F17 O2



CM 4

CRN 2156-97-0

CMF C15 H28 O2



CM 5

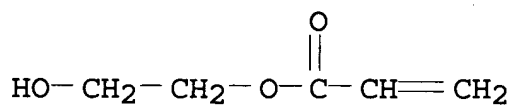
CRN 157184-95-7

CMF C5 H8 O3 . x (C3 H6 O . C2 H4 O) x

CM 6

CRN 818-61-1

CMF C5 H8 O3



CM 7

CRN 9003-11-6

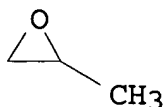
CMF (C3 H6 O . C2 H4 O) x

CCI PMS

CM 8

CRN 75-56-9

CMF C3 H6 O



CM 9

CRN 75-21-8

CMF C2 H4 O



IC ICM B41M005-40

CC 74-6 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)IT 156932-33-1 156932-35-3 156932-36-4 156932-38-6
156932-40-0 156932-44-4 156932-45-5 156932-47-7
156932-48-8 157177-62-3 **157382-57-5**(treatment agent containing, thermal printing material
treated)

L37 ANSWER 36 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1994:422385 HCAPLUS

DOCUMENT NUMBER: 121:22385

TITLE: Ternary surfactant system to reduce static
charges in silver halide photographic

material

INVENTOR(S): Schoenberg, Allan R.; Shu, Ming Tsai

PATENT ASSIGNEE(S): du Pont de Nemours, E. I., and Co., USA

SOURCE: U.S., 8 pp. Cont. of U.S. Ser. No. 627,872,
abandoned.

CODEN: USXXAM

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
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US 5258276	A	19931102	US 1992-885063

1992

0515

PRIORITY APPLN. INFO.:

US 1987-129805

B1

1987

1207

US 1990-511801

B1

1990

0416

US 1990-627872

B1

1990

1213

AB A ternary surfactant system useful in reducing the propensity of a silver halide photog. material to generate unwanted static charges is described. This ternary system comprises a mixture of a specific anionic and two specific nonionic surfactants and produces a surprising synergistic result. A solution of this ternary system is also useful in reducing static charges produced on the surface of an x-ray intensifying screen.

IC ICM G03C001-85

NCL 430527000

CC 74-2 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

IT **Siloxanes** and Silicones, properties (ternary surfactant systems containing, for reducing static charges in silver halide photog. materials)

- IT **Siloxanes** and Silicones, uses
(di-Me, 3-hydroxypropyl Me, ethers with
polyethylene-polypropylene glycol
mono-Me ether, with **polyethylene-**
polypropylene glycol mono-Me ether, ternary
surfactant systems containing Silwet L 77, for reducing static
charges in silver halide photog. materials)
- IT **Siloxanes** and Silicones, uses
(di-Me, 3-hydroxypropyl Me, ethoxylated
propoxylated, ternary surfactant systems containing ABIL B
8843,
for reducing static charges in silver halide photog.
materials)
- IT **Polyoxyalkylenes**, uses
(di-Me, Me hydrogen **siloxane-**,
ternary surfactant systems containing Dow Corning 193, for
reducing
static charges in silver halide photog. materials)
- IT **Siloxanes** and Silicones, uses
(di-Me, Me hydrogen,
polyoxyalkylene-, ternary surfactant systems containing Dow
Corning 193, for reducing static charges in silver halide
photog. materials)
- IT **Siloxanes** and Silicones, uses
(polyether-, ternary surfactant systems containing, for
reducing
static charges in silver halide photog. materials)

L37 ANSWER 37 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1990:506510 HCAPLUS

DOCUMENT NUMBER: 113:106510

TITLE: Receptor sheet for sublimation-type thermal
transfer **recording**

INVENTOR(S): Ichii, Masaru; Fukuda, Kozo; Komine, Tsutomu

PATENT ASSIGNEE(S): Nisshinbo Industries, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
	-----	----	-----	-----

	JP 01232096	A2	19890918	JP 1988-58344

1988

0314

PRIORITY APPLN. INFO.:

JP 1988-58344

1988

0314

AB In obtaining the title receptor sheet by forming a dye-receiving layer with a water-based binder, the above layer is formed with a mixed solution containing a water-based saturated polyester resin, an associate-type thickener, and a (mold) release agent. The associate-type thickener is a nonionic-type thickener and the release agent is selected from amino-modified silicones and silane derivs.

and reaction products of amine-reactive compds.

IT 101638-90-8

(thermal-transfer printing receptor sheets containing)

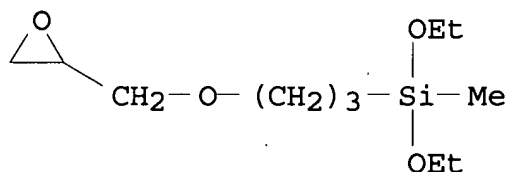
RN 101638-90-8 HCAPLUS

CN Silane, diethoxymethyl[3-(oxiranylmethoxy)propyl]-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 2897-60-1

CMF C11 H24 O4 Si



IC ICM B41M005-26

ICS D21H001-28; D21H005-00

CC 74-12 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

ST thermal transfer receptor sheet; **recording** thermal transfer receptor sheet; copying thermal transfer receptor sheet

IT 3069-29-2 101638-90-8 101962-84-9, Borchigel-L-75
128004-35-3, QR 1001

(thermal-transfer printing receptor sheets containing)

L37 ANSWER 38 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1978:24332 HCAPLUS
 DOCUMENT NUMBER: 88:24332
 TITLE: Stabilization of chromium dioxide magnetic pigments
 INVENTOR(S): Schoenafinger, Eduard; Motz, Herbert; Ohlinger, Manfred; Deigner, Paul; Grau, Werner
 PATENT ASSIGNEE(S): BASF A.-G., Fed. Rep. Ger.
 SOURCE: Ger. Offen., 17 pp.
 CODEN: GWXXBX
 DOCUMENT TYPE: Patent
 LANGUAGE: German
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
1976	DE 2617809	A1	19771103	DE 1976-2617809
0423	DE 2617809	C2	19840920	
	US 4275114	A	19810623	US 1977-776224
1977				
0310	JP 52130306	A2	19771101	JP 1977-44183
1977				
0419	JP 60019566	B4	19850516	
	NL 7704316	A	19771025	NL 1977-4316
1977				
0420	NL 185019	B	19890801	
	NL 185019	C	19900102	
	BE 853856	A1	19771024	BE 1977-176926

1977

0422

FR 2349629 A1 19771125 FR 1977-12227

1977

0422

FR 2349629 B1 19830107
GB 1572359 A 19800730 GB 1977-16796

1977

0422

PRIORITY APPLN. INFO.: DE 1976-2617809 A

1976

0423

AB CrO₂ pigments are stabilized against loss of magnetic properties by treatment in aqueous or alc. suspension with **polyoxyalkylene**-siloxane block polymers and drying at 50-200°. Thus, 40 parts CrO₂ in 110 parts H₂O is stirred with 4.8 parts **polyethylene-polypropylene glycol-dimethyl** siloxane ether 2 h at 40° and pH 3.6-3.9, filtered, and dried 8 h at 90°. Magnetic tape containing this CrO₂ has orientation factor 3.22 and time at 65° and 95% relative humidity for loss of 10% magnetic saturation 18.0 day, compared with 2.67 and 6.3, resp., for untreated CrO₂.

IC C04B035-12

CC 42-5 (Coatings, Inks, and Related Products)
Section cross-reference(s): 77ST chromium dioxide magnetic stabilization; pigment magnetic stabilization; siloxane stabilizer magnetic pigment;
polyoxyalkylene stabilizer magnetic pigmentIT Pigments
(magnetic, stabilization of, with polyoxyalkylated **siloxanes**)IT **Recording** apparatus
(magnetic tape, chromium dioxide magnetic pigments for, stabilization of)IT **Siloxanes** and Silicones, uses and miscellaneous
(polyoxyalkylated, stabilization by, of chromium dioxide)

- magnetic pigments)
- IT 12018-01-8
(pigments, magnetic stabilization of, by polyoxyalkylated
siloxanes)
- IT 9003-11-6D, ethers with **siloxanes** 25322-68-3D, ethers
with **siloxanes** 25322-69-4D, ethers with
siloxanes
(stabilization by, of chromium dioxide magnetic pigment)